

# *Lecture 13: Glass Finishing (Grinding & Polishing)*

**Glass Processing Course (Lehigh University; Spring 2015)  
International Materials Institute for New Functionality in Glass (IMI-NFG)**

**March 5, 2015 1:00 -2:15 pm (EST)**

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 **Lawrence Livermore  
National Laboratory**

LLNL-PRES-668080

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# Useful Reading Material

**H. Karow, “Fabrication Methods of Precision Optics” John Wiley & Sons (1993)**

**N. Brown, “Optical Fabrication” LLNL Report MISC4476 (August 1989)**

**L. Cook, “Chemical Processes in Glass Polishing” Journal of Non-Crystalline Solids 120 (1990) 152-171**

**T. Izumatani, “Optical Glass” (Kyoritsu Shuppan Company, Tokyo 1984; Lawrence Livermore National Laboratory (USA); American Institute of Physics (New York 1986)**

**D. Anderson, J. Burge, “The Handbook of Optical Engineering: Chapter 28: Optical Fabrication”**

**D. Malacara, “Optical Shot Testing” Wiley-Interscience (2007)**

**Other references quoted through the presentation**

# What is optical fabrication?

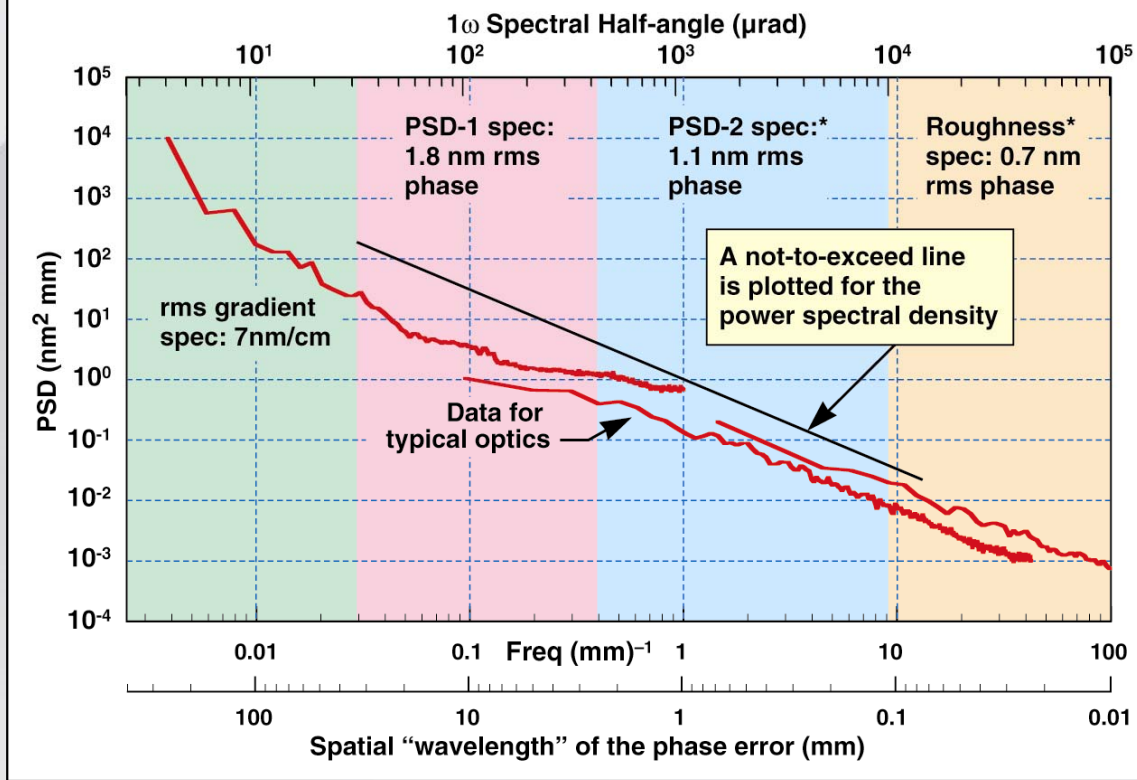
**The objective of optical fabrication is to manufacture an optical element (e.g., lense, flat, mirror, active optic) which is often made of glass**

## **Key Requirements**

- 1) Surface Figure (affects wavefront)**
- 2) Surface Quality (affects scatter and laser damage resistance)**
  - a) Roughness**
  - b) Sub-surface damage (scratch/dig)**

# An example of specifying the requirements of an optic

## Power Spectral Density for Optic Surface



## High Level Requirements<sup>1</sup>

### Surface

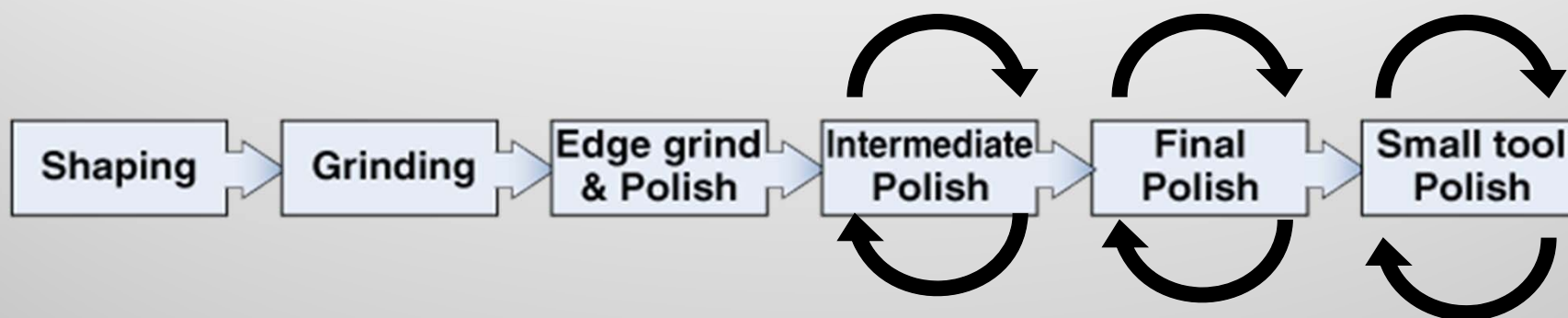
Peak-to-Valley	211 nm ( $\lambda/3$ )
Gradient	<7 nm/cm
PSD1	1.8 nm
PSD2	1.1 nm
Roughness	4-10 Ang
Scratch/Dig <sup>2</sup>	20/10

### Bulk

Homogeneity	<5 ppm
Inclusions(>5 $\mu\text{m}$ )	0
Lenslets	0

<sup>1</sup>For typical  $3\omega$  NIF optics; <sup>2</sup>Post-etch with number of scratches (width >  $8\mu\text{m}$ ) < 12-50

## Typical steps of an optical fabrication process



# Examples of grinding techniques



# Examples of polishing techniques



# The materials science behind grinding & polishing

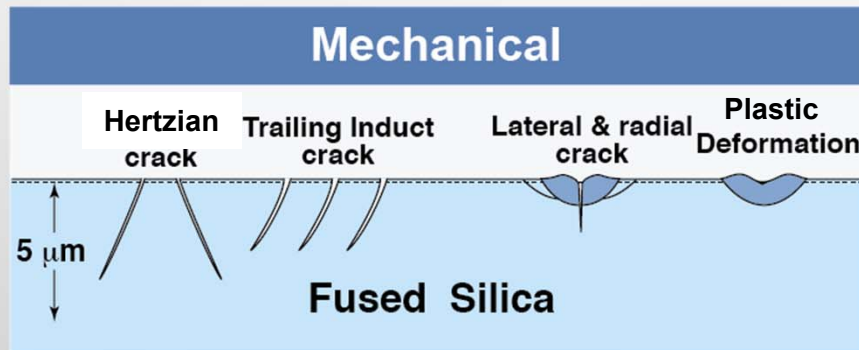
**1. Sub-surface Damage (scratch/dig)**

**2. Roughness**

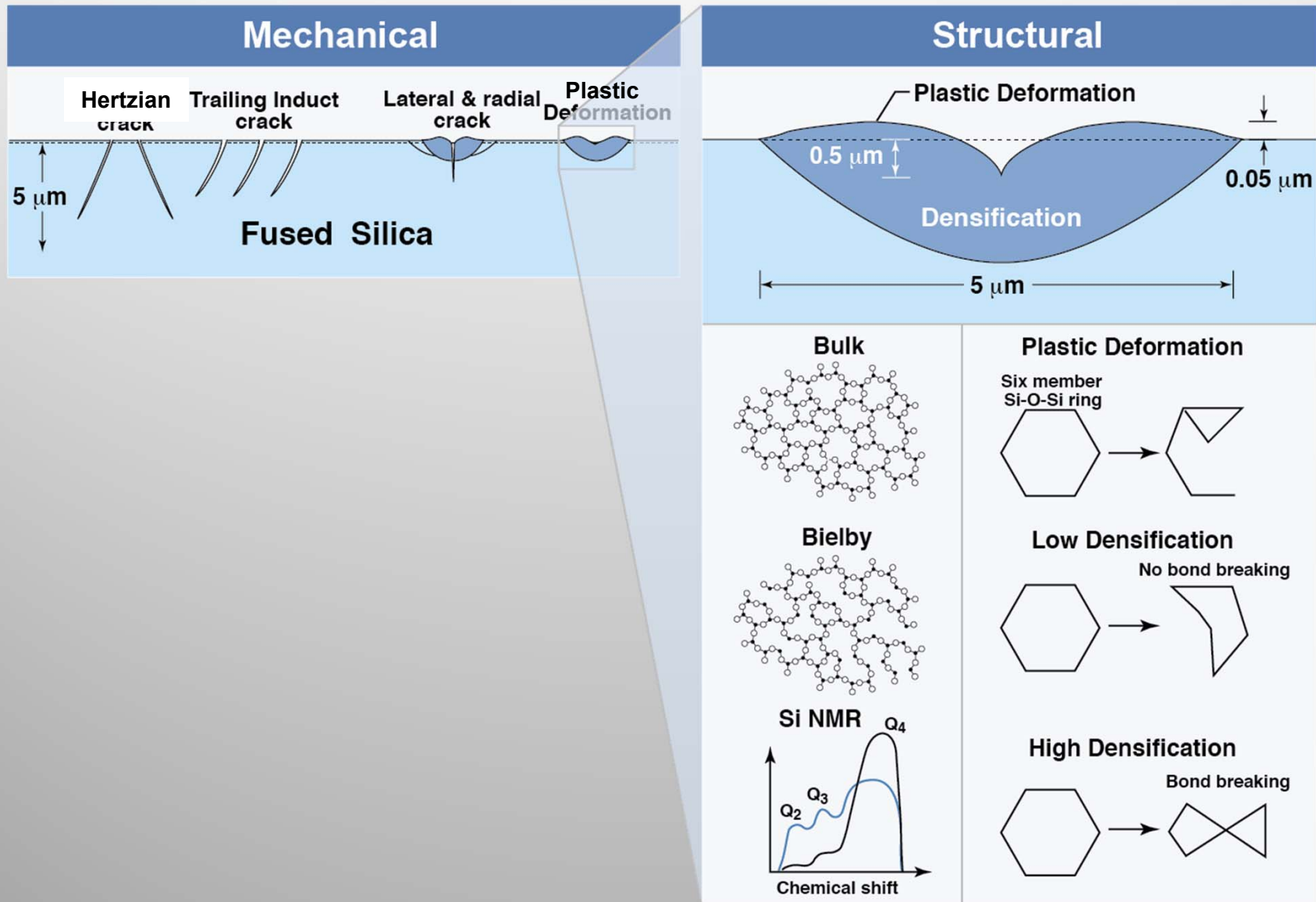
**3. Surface Figure**



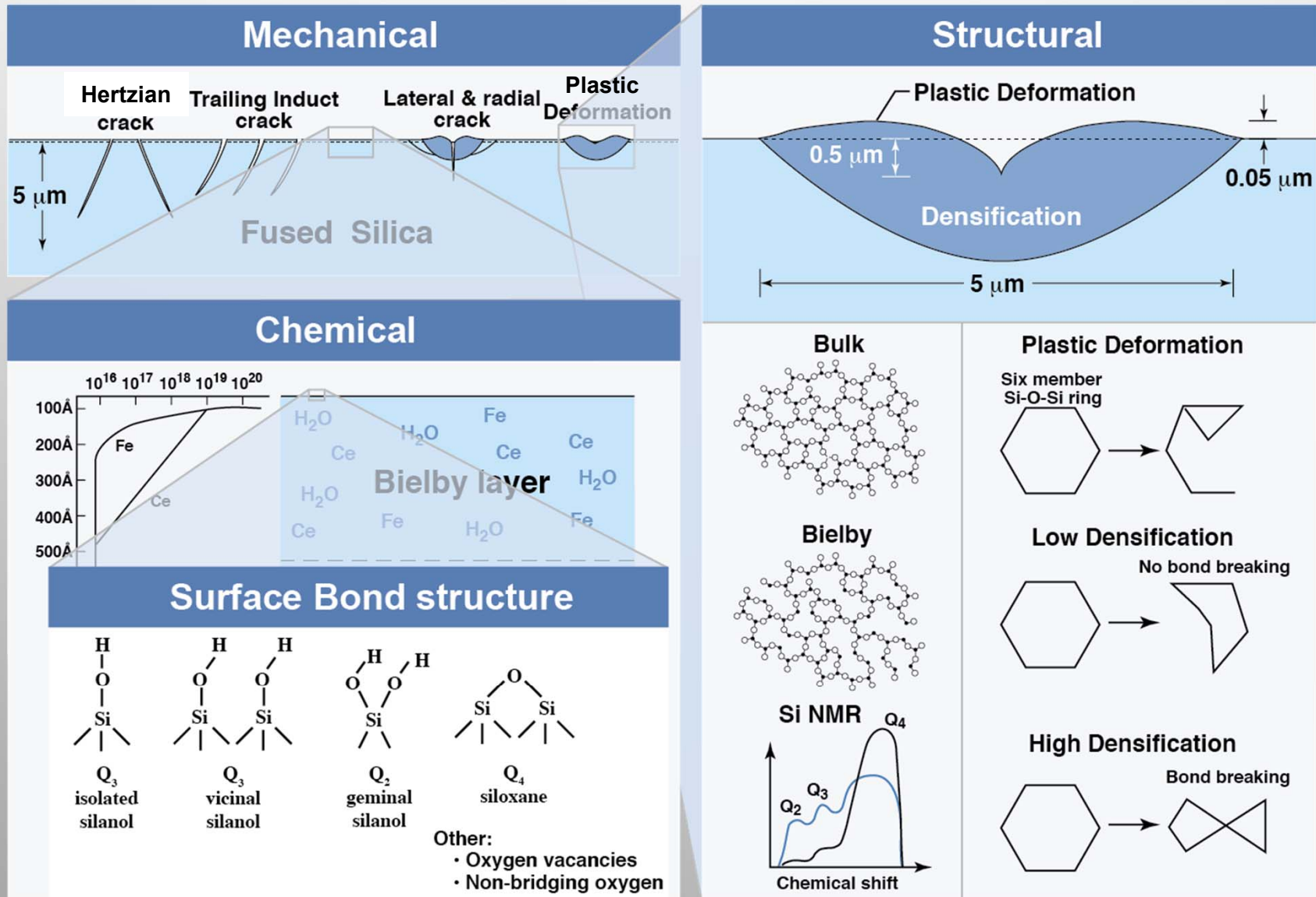
# There are numerous mechanical, structural and chemical effects on the glass surface during grinding and polishing



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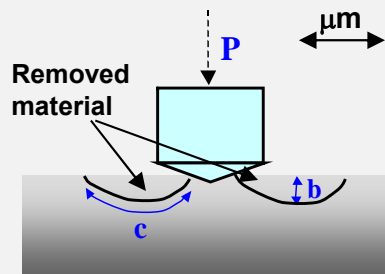


# There are numerous mechanical, structural and chemical effects on the glass surface during grinding and polishing



# The load/particle determines the removal mechanism

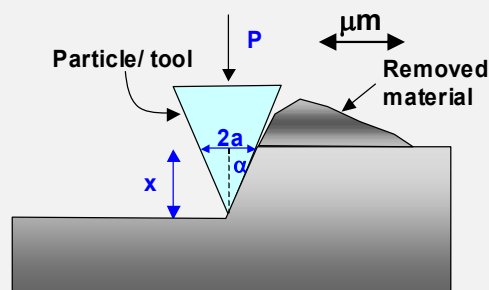
## Brittle Removal Grinding or scratching



$$P_{\text{crit}} > 0.1 \text{ N}$$

- Material within lateral cracks are removed (grinding process)
- Leads to scratches

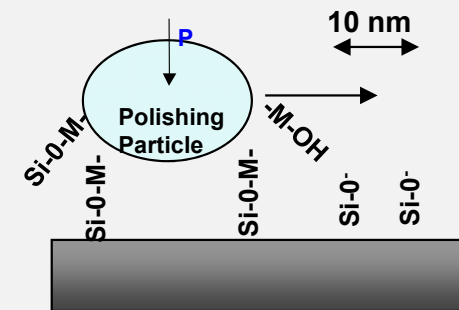
## Plastic Removal Ductile Polishing



$$P_{\text{crit}} > 5 \times 10^{-5} \text{ N}$$

- Portion of deformed material removed
- Leads to plastic scratches or sleeks
- Determined removal amount  $\sim 1 \text{ nm}$

## Chemical removal Chemical Polishing

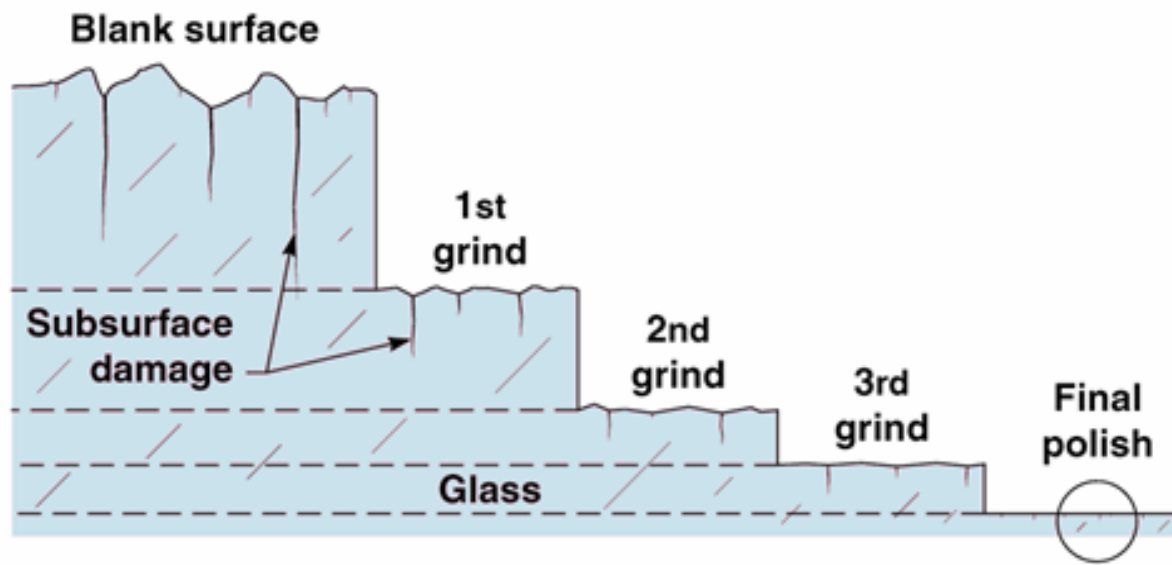


$$P_{\text{crit}} < 5 \times 10^{-5} \text{ N}$$

- Removal at the molecular level ( $\text{Si}(\text{OH})_4$ ) by condensation & hydrolysis
- Creates smooth surface
- Determined removal amount  $\sim 0.04 \text{ nm}$

# Approach for the management of sub-surface fractures (i.e. scratches/digs)

Schematic of material removal during various steps of the grinding/polishing process illustrating surface fracture removal

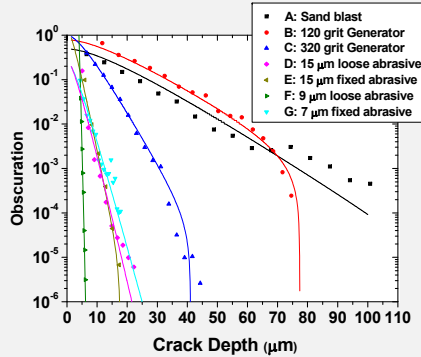


- Removal at each step is aimed at removal of deepest damage decreasing it to the level of deepest damage expected at current step (most economical design)
- Note each subsequent step has much lower removal rate
- This approach has been generally followed for hundreds of years

\*Preston (1921), Aleinikov (1957), Edwards & Hed (1987), Brown (1980), Lambropoulos (1996)

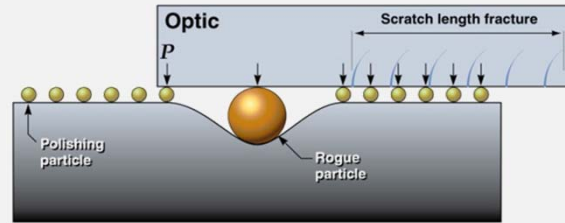
# There are five major areas of effort that have aided in managing sub-surface fractures

## GRINDING



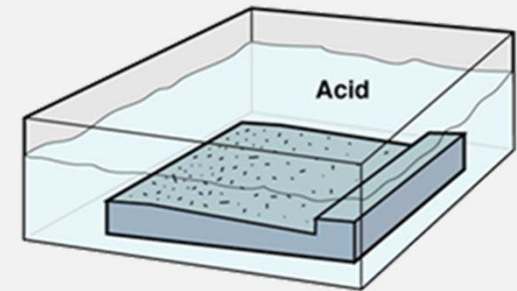
1. Developed fracture mechanics understanding of sub-surface fracture distributions

## POLISHING



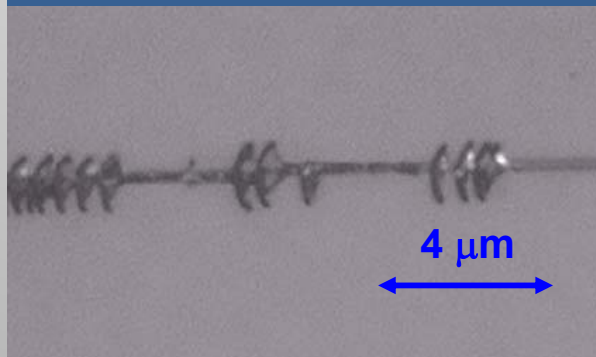
2. Identified/characterized behavior of rogue particles causing sub-surface fractures

## CHEMICAL ETCHING



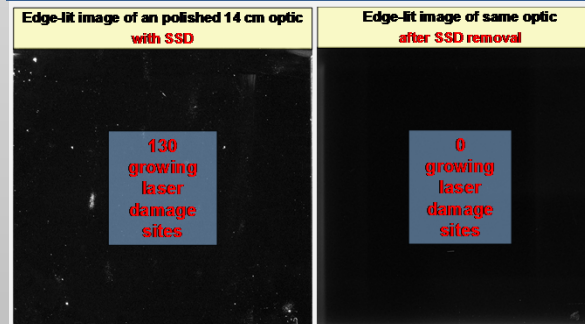
3. Established techniques using etching to reveal and remove subsurface fractures

## SCRATCH FORENSICS



4. Developed quantitative rules for post-diagnosis of cause of surface fractures

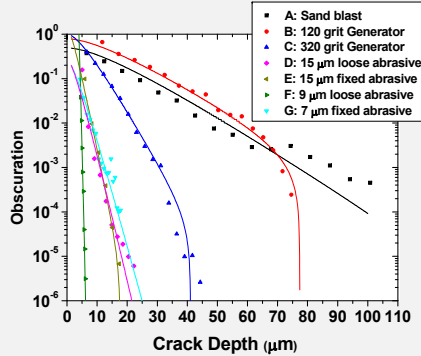
## LASER DAMAGE



5. Showed link between sub-surface fracture removal & improved laser resistance

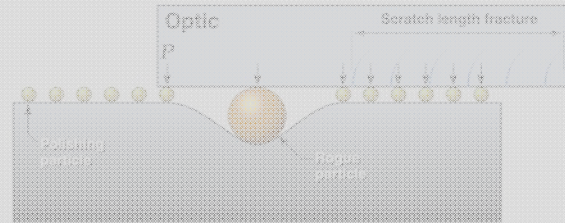
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## GRINDING



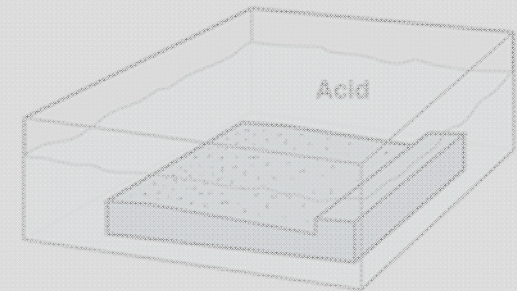
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## POLISHING



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## CHEMICAL ETCHING



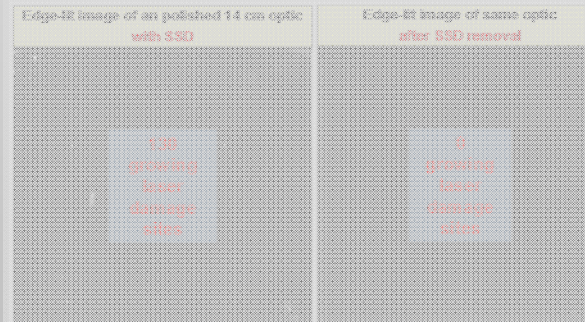
3. Established techniques using etching to reveal and remove subsurface fractures

## SCRATCH FORENSICS



4. Developed quantitative rules for post-diagnosis of cause of surface fractures

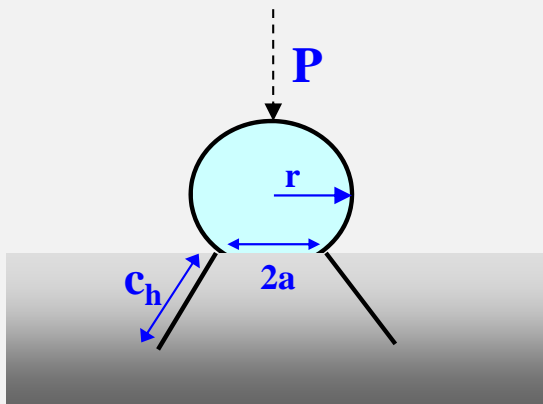
## LASER DAMAGE



5. Showed link between sub-surface fracture removal & improved laser resistance

# There are three basic types of cracks created by **static** brittle indentation

## Hertzian Cracks<sup>1</sup> (blunt)



**Initiation**

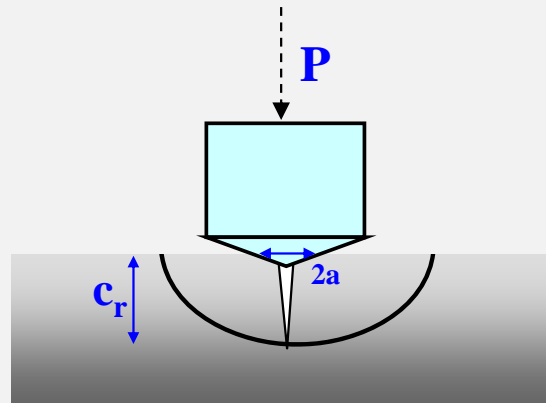
$$P_c = A r$$

**Growth**

$$c_h = \left( \frac{\chi_h P}{K_{Ic}} \right)^{2/3}$$

Leads to subsurface damage

## Radial Cracks<sup>1</sup> (sharp)

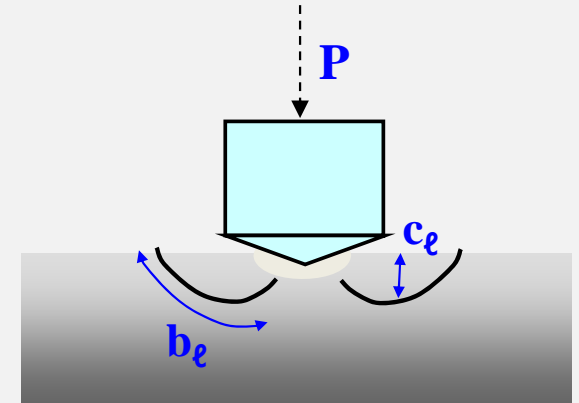


$$P_c = \alpha_r \frac{K_{Ic}^4}{H^3}$$

$$c_r = \left( \frac{\chi_r P}{K_{Ic}} \right)^{2/3}$$

Leads to subsurface damage

## Lateral Cracks<sup>2</sup> (sharp)



$$P_c = P_{c\ell}$$

$$b_\ell = \frac{\chi_\ell \left( \frac{E}{H} \right)^{3/5} P^{5/8}}{K_{Ic}^{1/2} H^{1/8}} \quad c_\ell = \frac{\chi_{\ell 2} \left( \frac{E}{H} \right)^{2/5} P^{1/2}}{H^{1/2}}$$

Leads to material removal

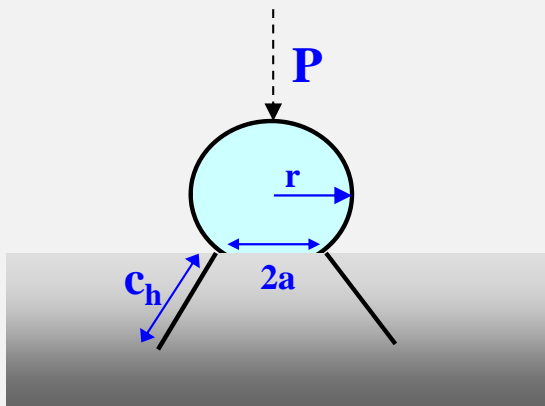
<sup>1</sup>B. Lawn, "Fracture of Brittle Materials" (1993)

<sup>2</sup>I. Hutchings "Tribology: Friction and Wear of Engineering Materials" (1992)



# The fracture initiation and growth constants need to be known to quantitatively use these relationships

## Hertzian Cracks<sup>1</sup> (blunt)



Initiation

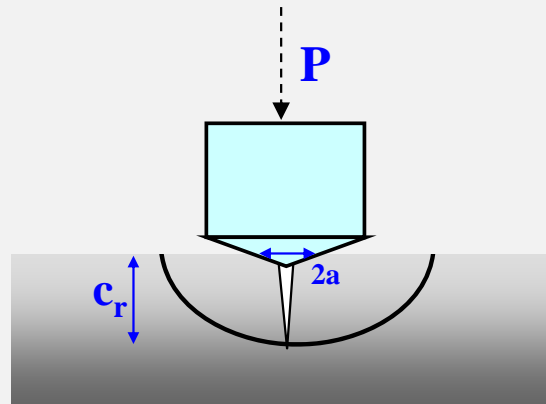
$$P_c = A r$$

Growth

$$c_h = \left( \frac{\chi_h P}{K_{Ic}} \right)^{2/3}$$

Leads to subsurface damage

## Radial Cracks<sup>1</sup> (sharp)

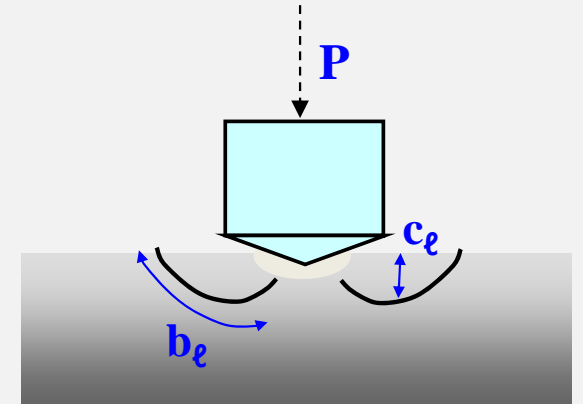


$$P_c = \alpha \frac{K_{Ic}^4}{H^3}$$

$$c_r = \left( \frac{\chi_r P}{K_{Ic}} \right)^{2/3}$$

Leads to subsurface damage

## Lateral Cracks<sup>2</sup> (sharp)



$$P_c = P_{cl}$$

$$b_e = \frac{\chi_\ell \left( \frac{E}{H} \right)^{3/5} P^{5/8}}{K_{Ic}^{1/2} H^{1/8}} \quad c_\ell = \frac{\chi_{\ell 2} \left( \frac{E}{H} \right)^{2/5} P^{1/2}}{H^{1/2}}$$

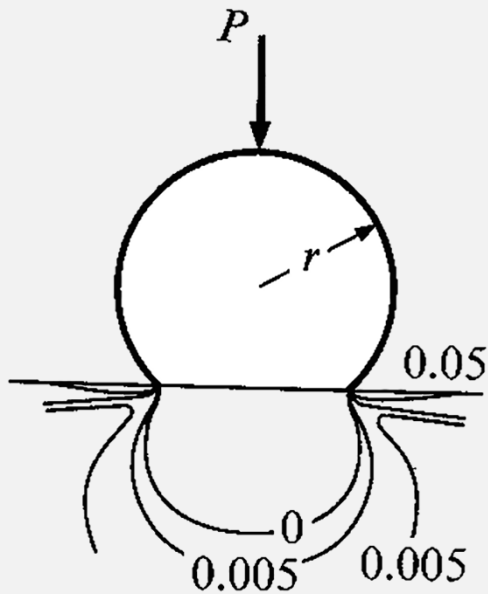
Leads to material removal

<sup>1</sup>B. Lawn, "Fracture of Brittle Materials" (1993)

<sup>2</sup>I. Hutchings "Tribology: Friction and Wear of Engineering Materials" (1992)

# Friction strongly influences fracture initiation for a sliding particle indentation (i.e. scratching)

## Static Sphere<sup>1</sup>



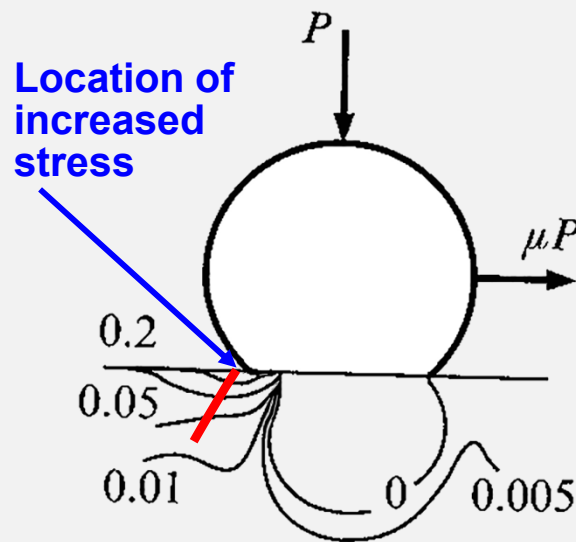
Initiation

$$P_c = A r$$

Growth

$$P = \frac{K_{Ic}}{\chi_h} c^{3/2}$$

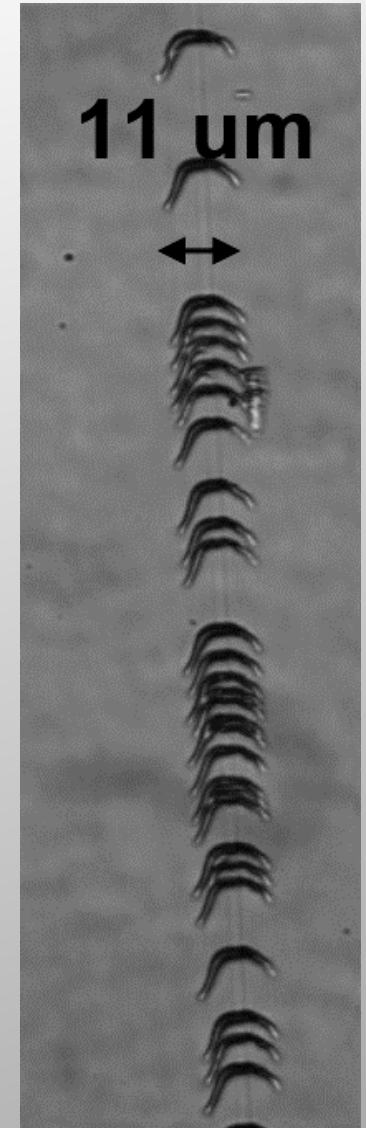
## Sliding Sphere<sup>1,2</sup>



$$P_c = \frac{A r}{(1 + B\mu)^2}$$

$$P_c = \frac{C r^2}{(1 + B\mu)^3}$$

$$P = \frac{K_{Ic}}{\chi_h (1 + \mu^2)^2} c^{3/2}$$

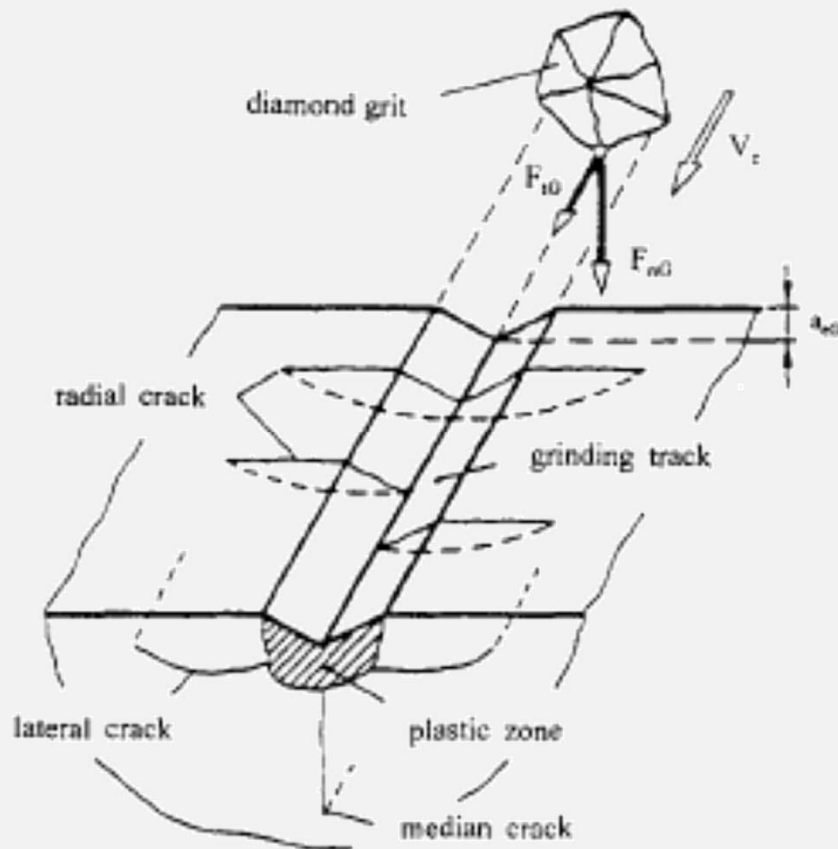


<sup>1</sup>Lawn, Fracture of Brittle Solids (1993)

<sup>2</sup>Lawn, Indentation Fracture: Principles and Applications (1975)

# The effect of load on the fracture behavior of scratches has been measured

## Schematic description of fractures associated with a scratch



- **At low loads ( $P < 0.1$  N),** no cracking is observed just a ductile track
- **At intermediate loads ( $0.1$  N  $< P < 5$  N),** well defined median and lateral cracks form
- **At high loads ( $P > 5$  N),** the plastically observed track appears to shatter and the median and lateral crack are not as extending as in the higher end of the intermediate loads

Refs: Review: K. Li, Journal of Materials Processing Technology 57 (1996) 206  
Review: M. Swain, Proc. R. Soc. London A, 366 (1979) 575

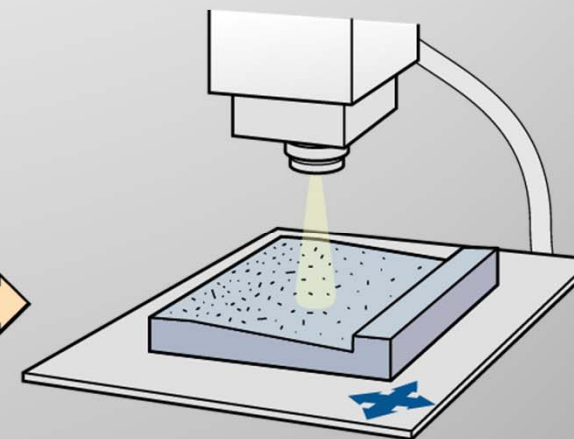
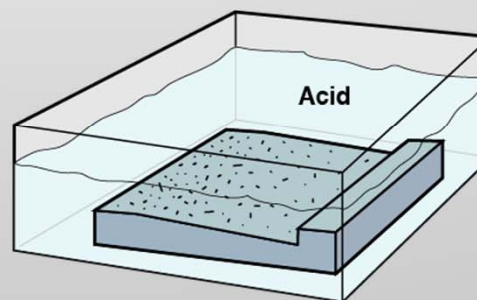
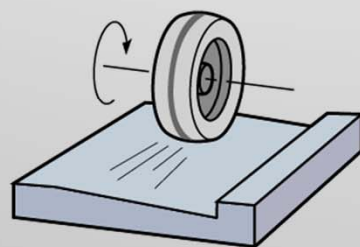
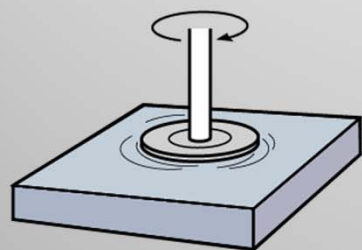
# A wedge or taper polishing\* technique was developed to directly measure the SSD distribution

Finishing Operation

MRF Taper

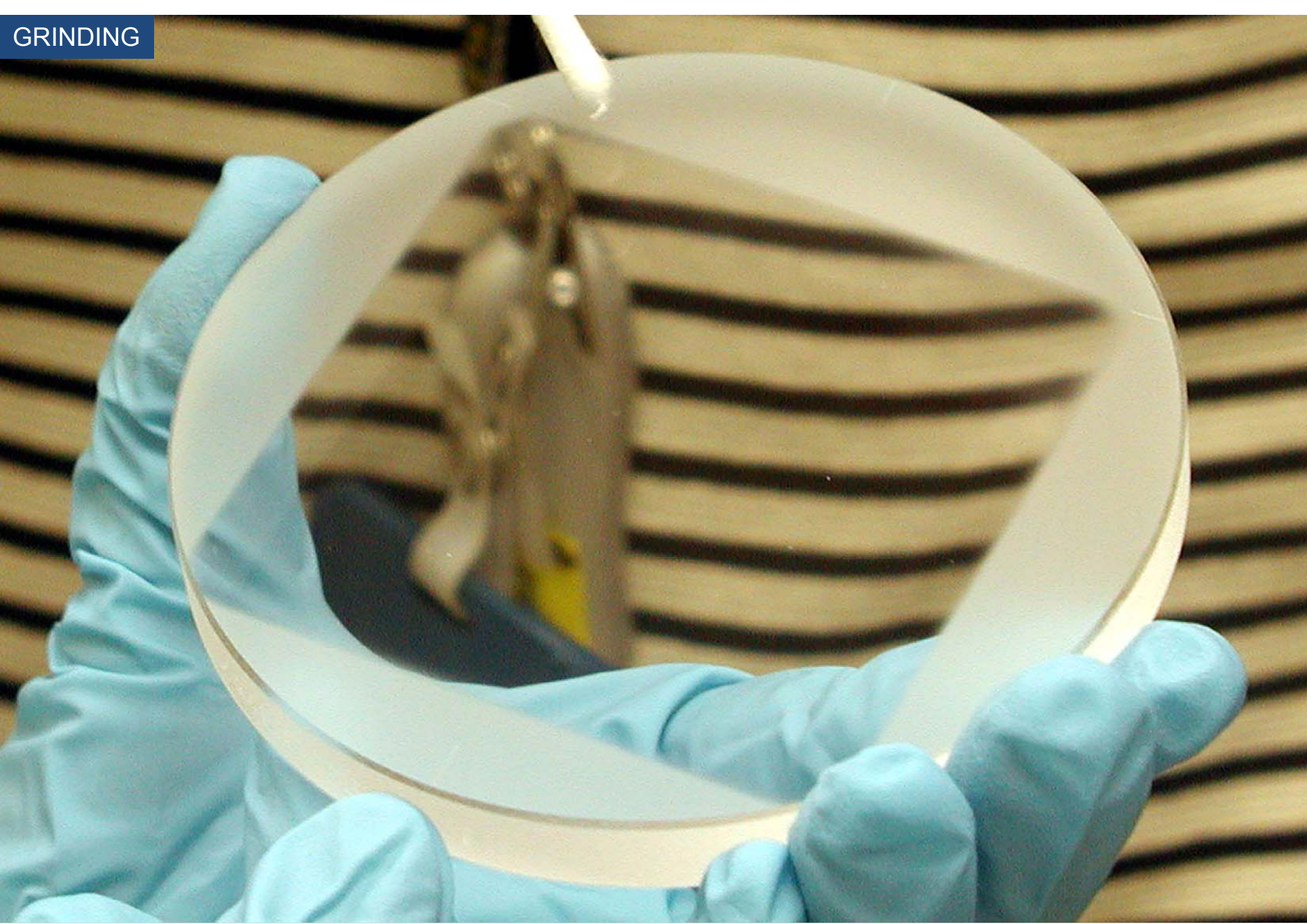
HF Etching

Microscope

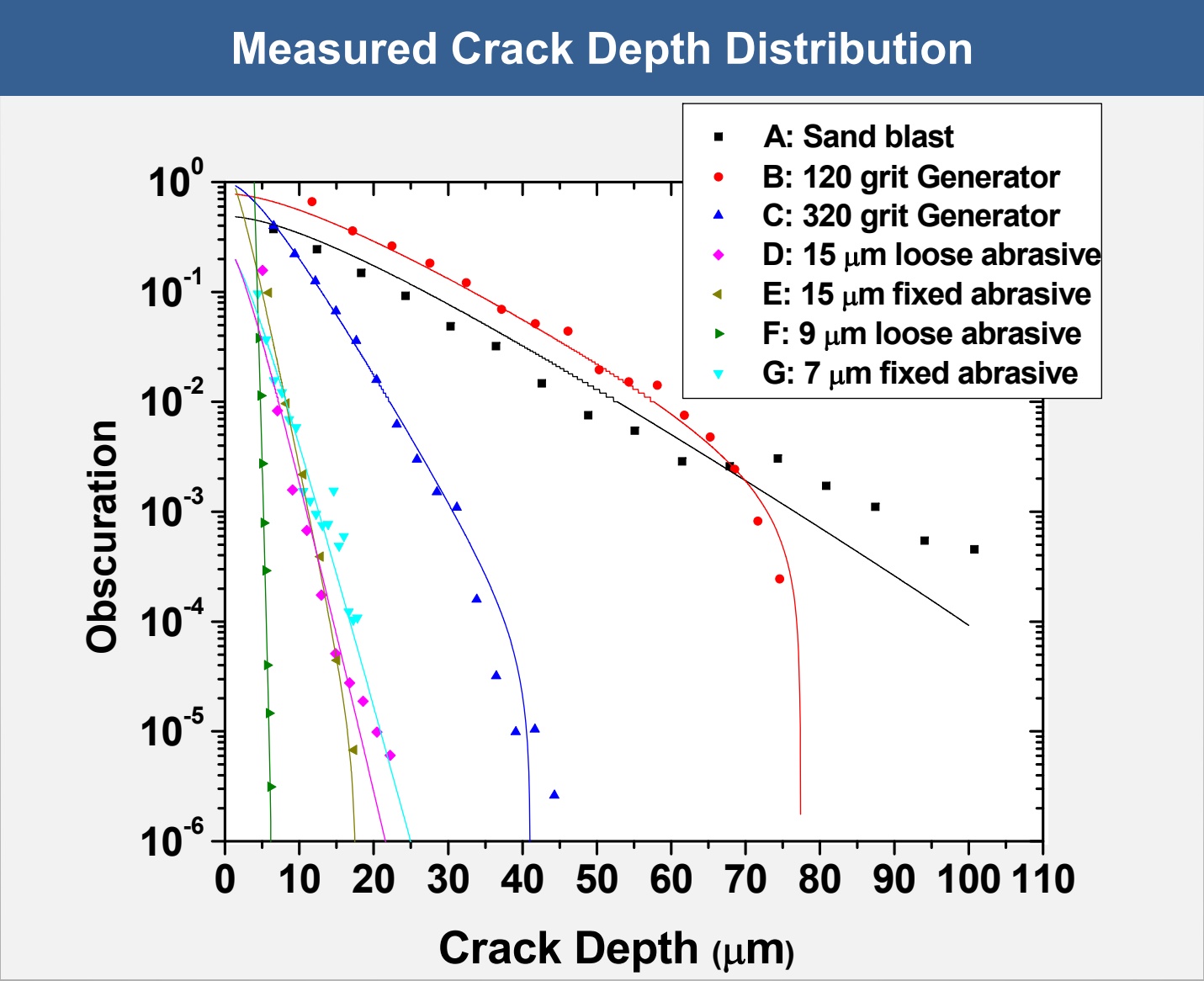


\*J. Menapace, SPIE 2005, Boulder Damage Symposium;  
Based on tapering technique used by Hed & Edwards (1987)

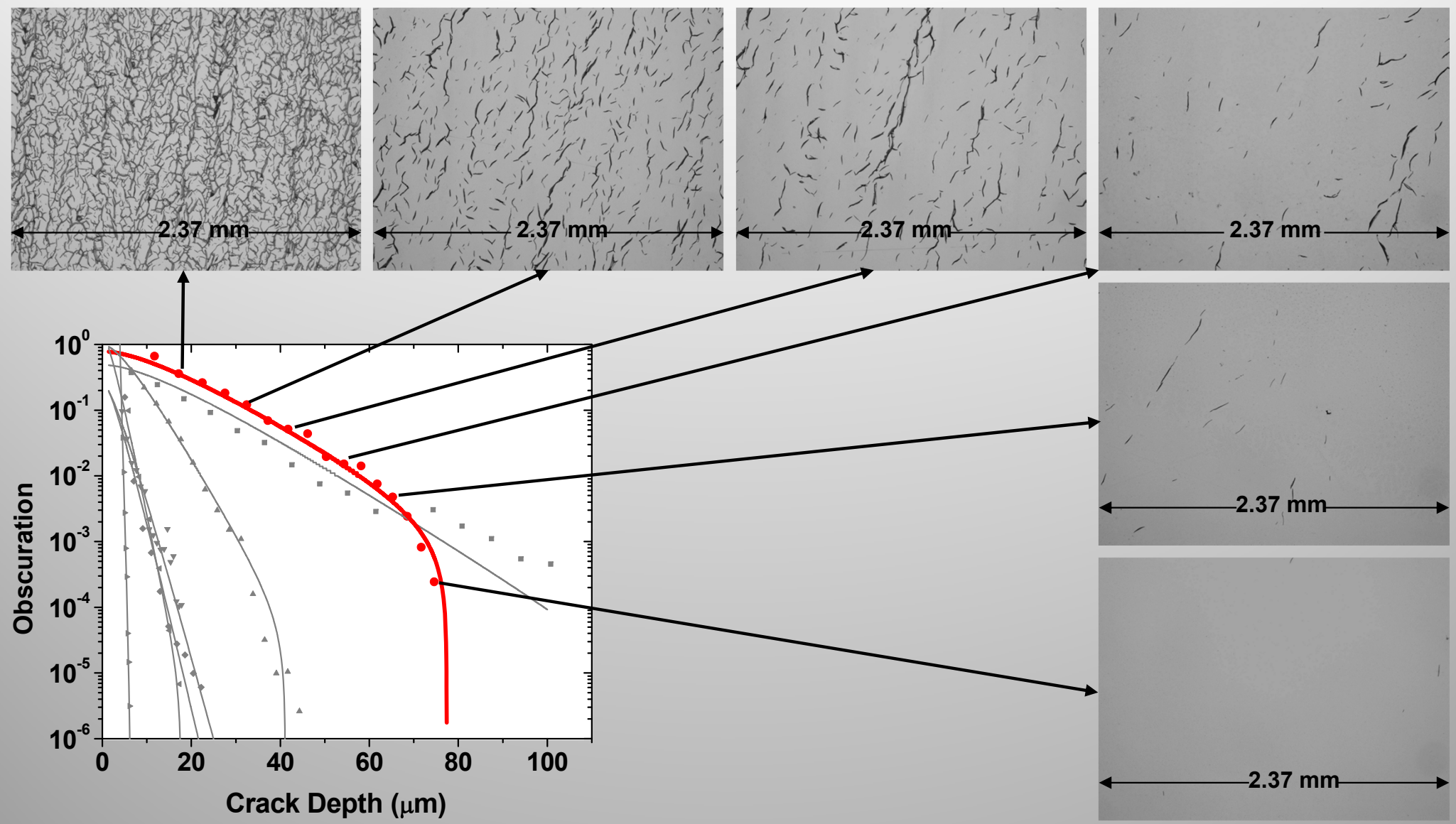
GRINDING



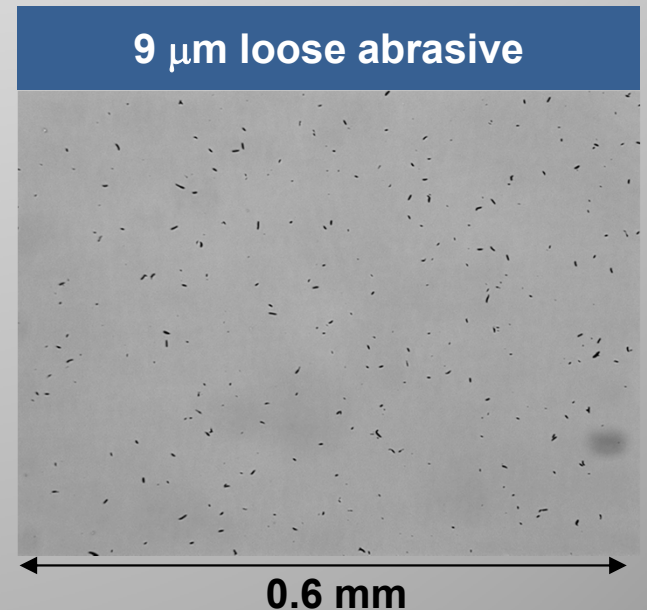
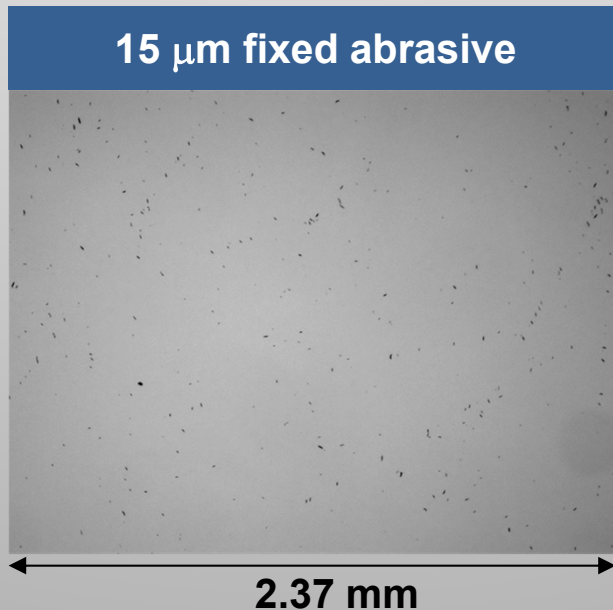
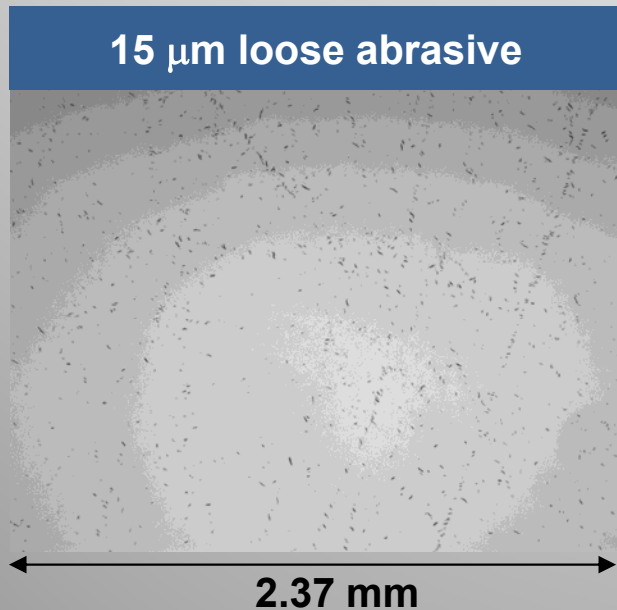
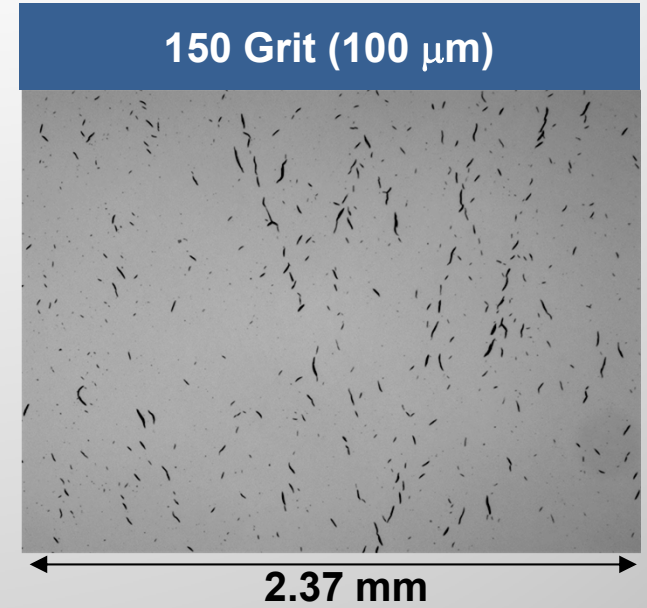
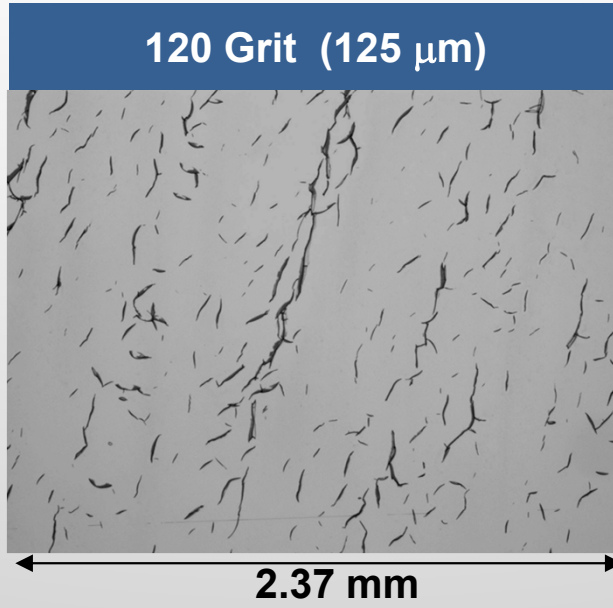
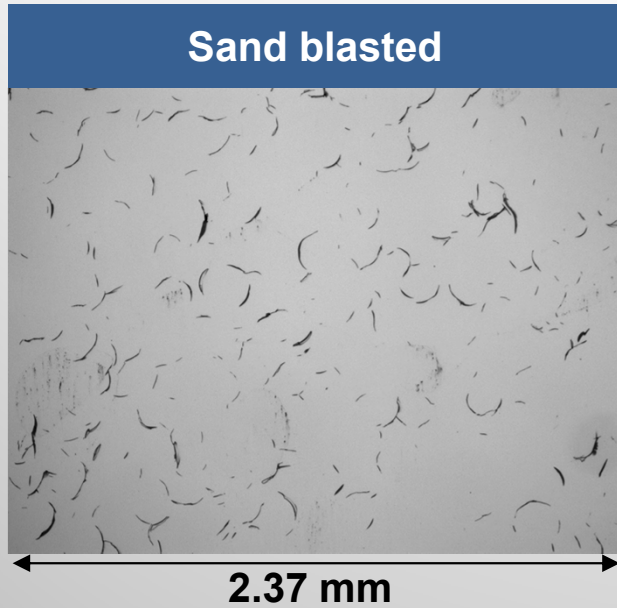
# The SSD depth distribution has been measured for a series of standard grinding processes



# Coarse Generator Grind (120 grit) (Sample B)

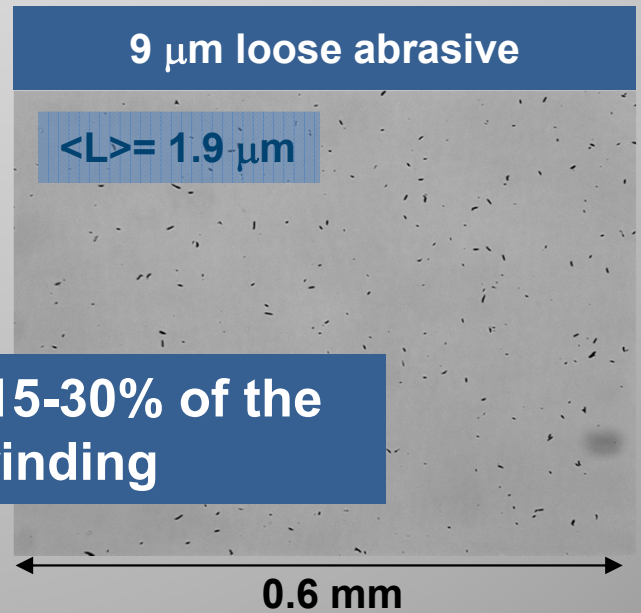
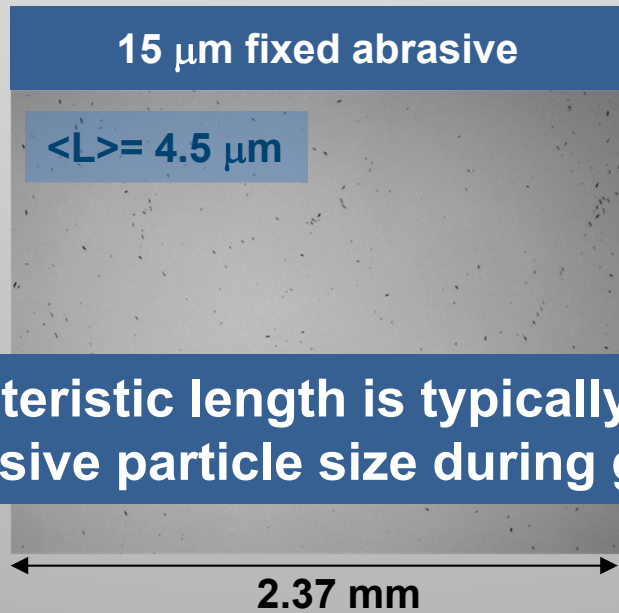
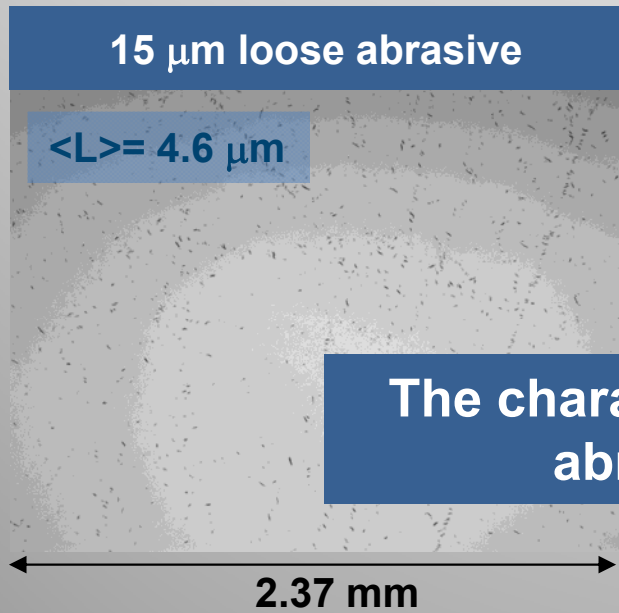
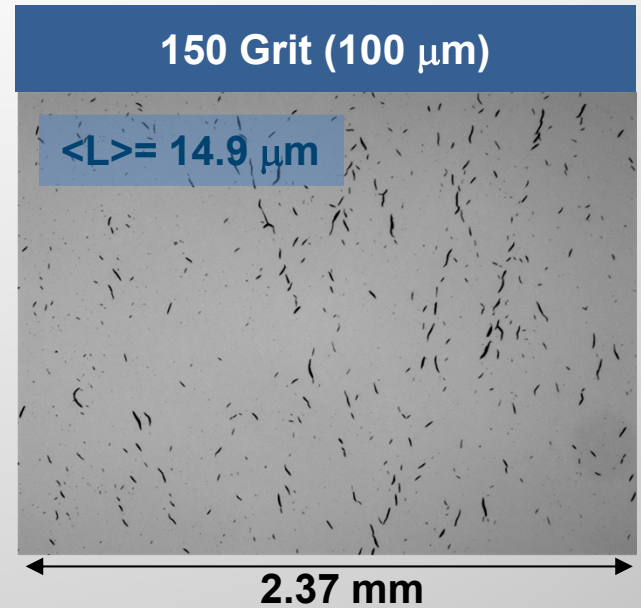
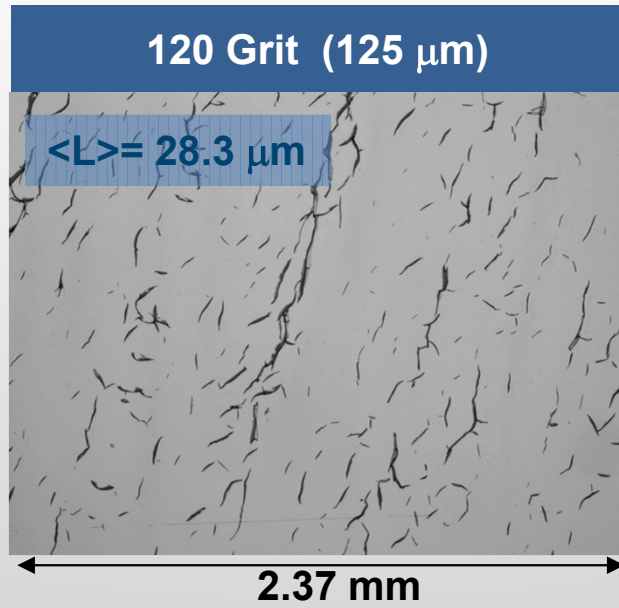
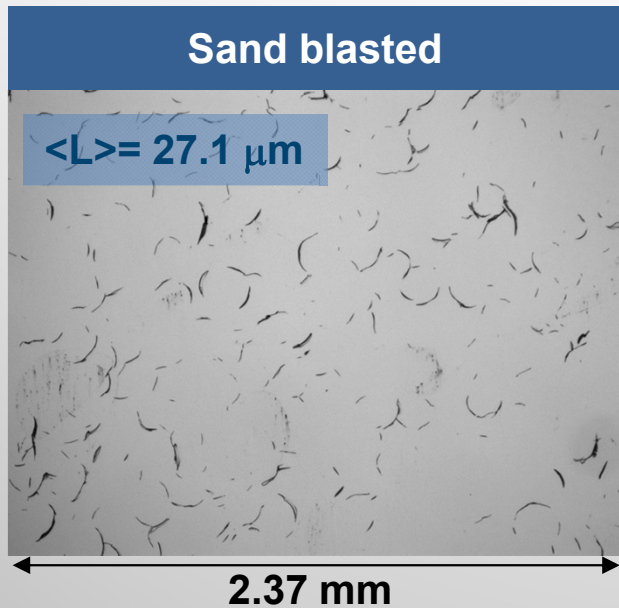


# Microscope images of the fractures show a unique size character for each grinding step



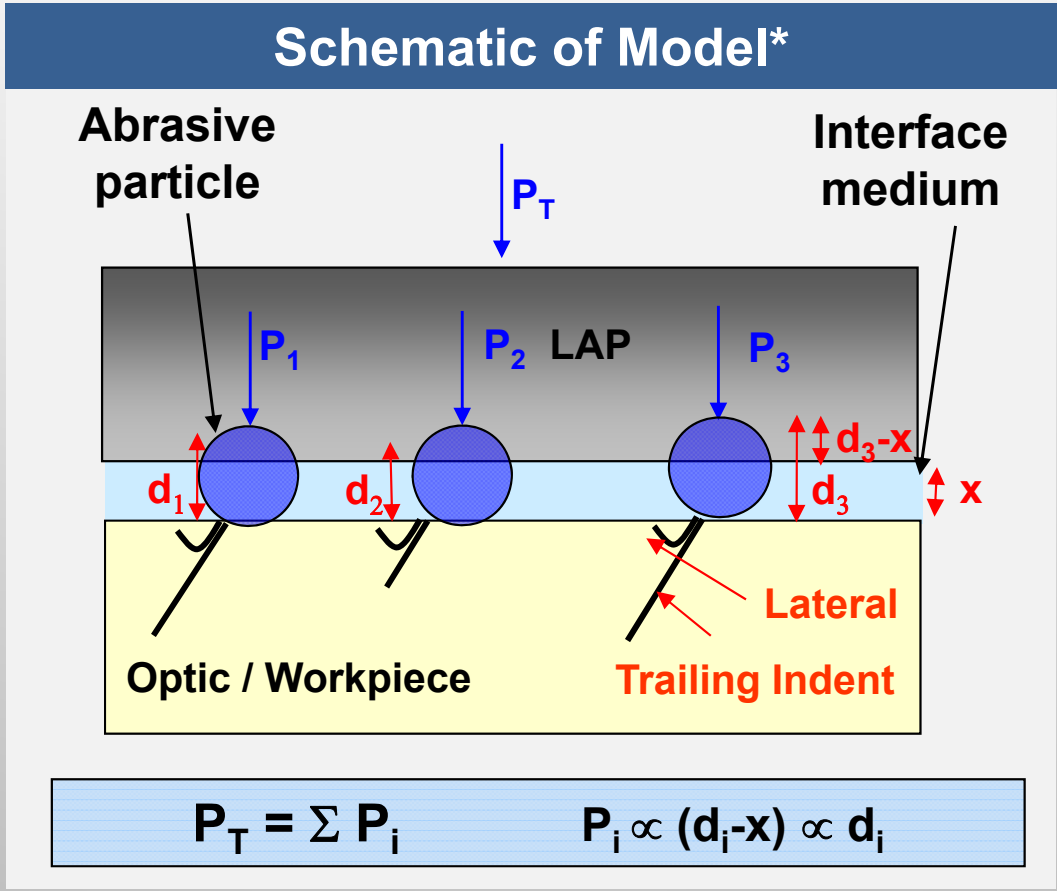


# Microscope images of the fractures show a unique size character for each grinding step



The characteristic length is typically 15-30% of the abrasive particle size during grinding

# A brittle fracture model has been successfully used to explain the observed distribution of crack depth and lengths

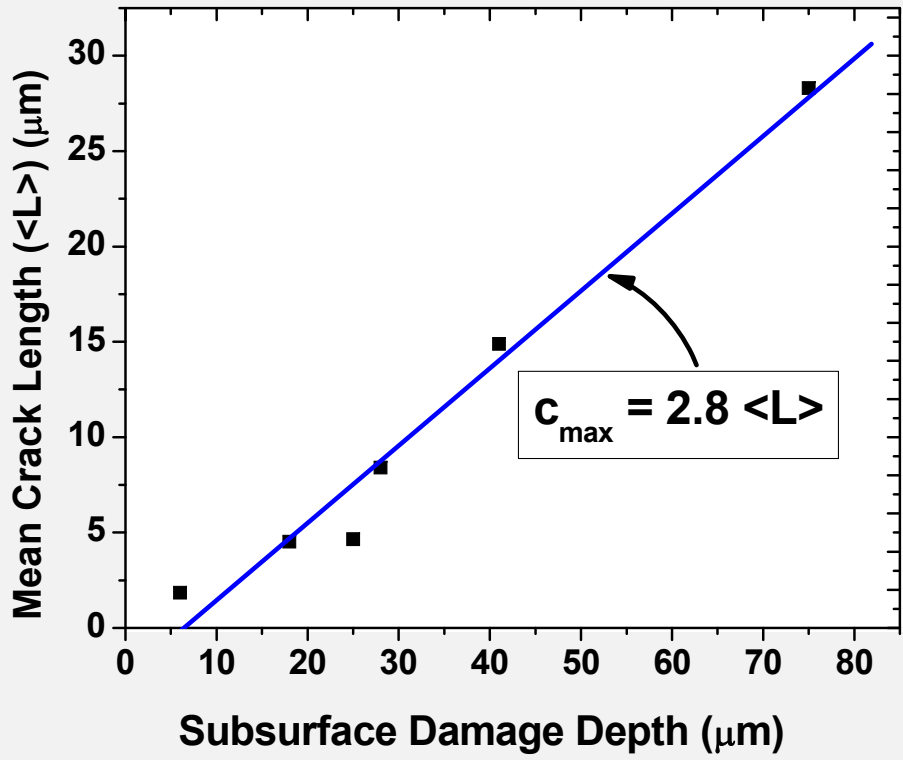


**Key assumption:** The load on particle is proportional to its vertical dimension

\*T. Suratwala, JNCS 352 (2006) 5601.  
 \*P. Miller, SPIE 5991 (2006).

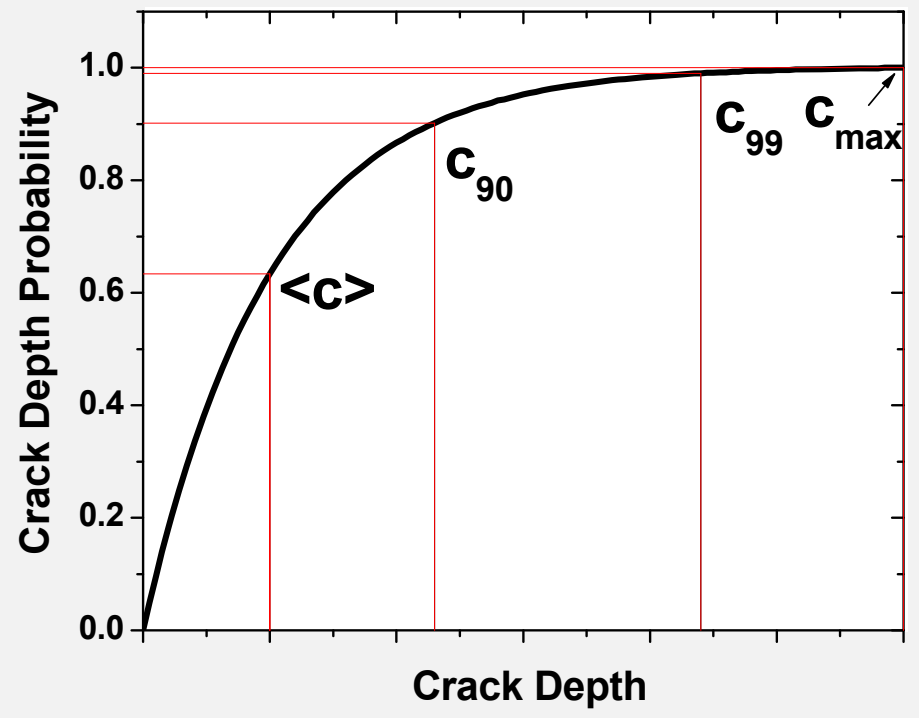
We recommend using the '90' rule for material removal ( $c_{90}=0.9\langle L \rangle$ ) for isolated SSD observed on polished parts

Measured mean crack length vs SSD depth



$$c_{max} = 2.8 \langle L \rangle$$

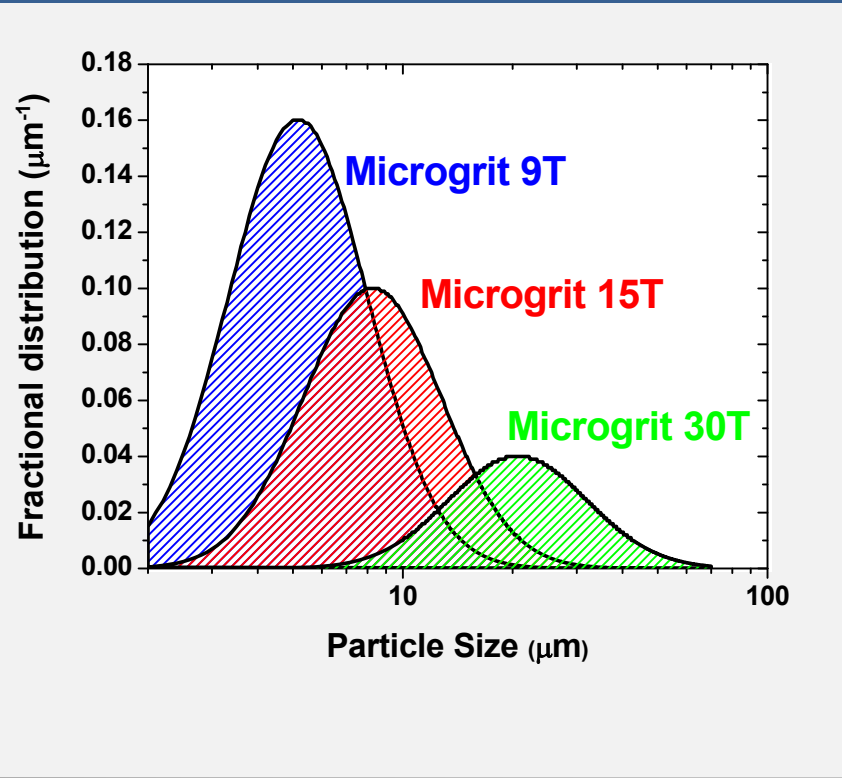
Probability of finding a crack of depth c for a given crack length



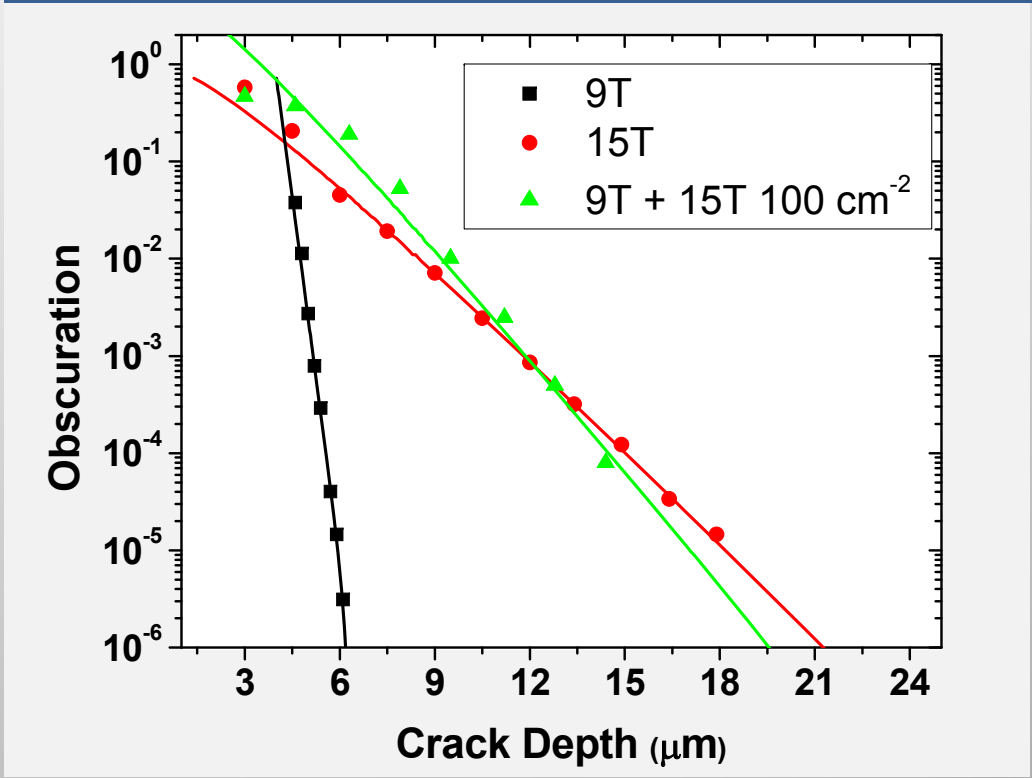
$$c_{90} = 0.9 \langle L \rangle$$

# The addition of a small amount of 15 μm particles in a 9 μm slurry results in a significant increase in SSD

Particle size distributions of the alumina particles used

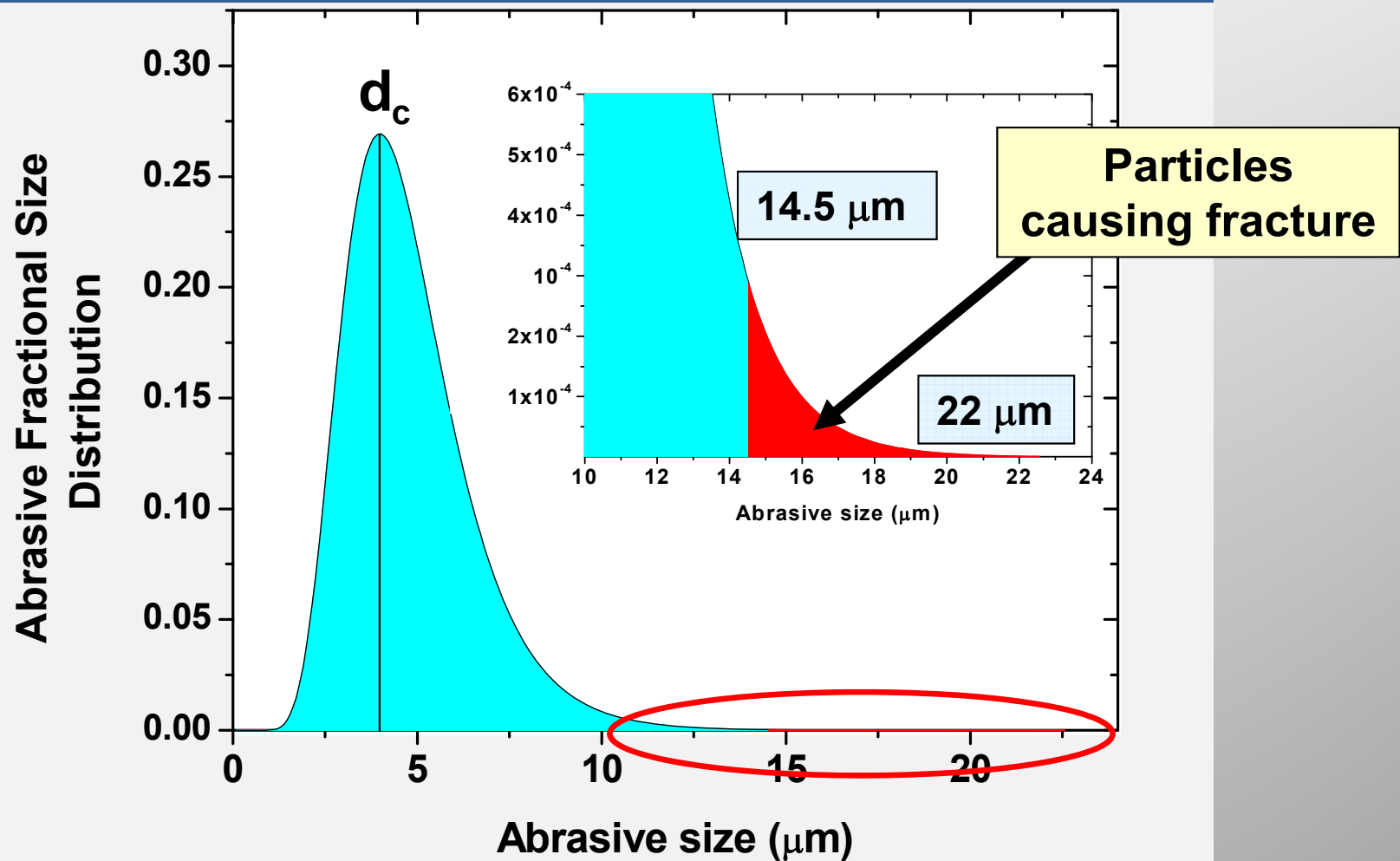


Crack depth distributions: Loose abrasive grinding with addition of rogue particles



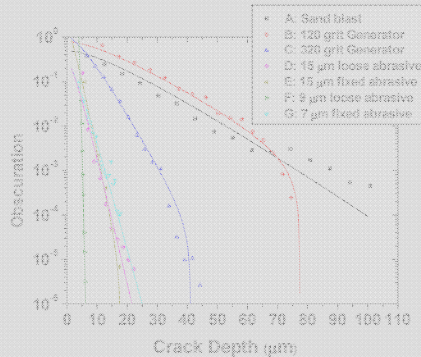
# The loaded particles are the largest particles in the abrasive particle distribution

## Abrasive size distribution for 9 $\mu\text{m}$ loose abrasive



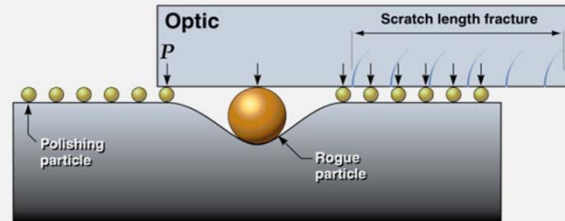
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## GRINDING



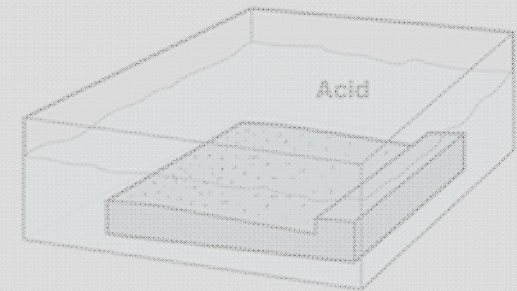
1. Developed fracture mechanics understanding of sub-surface fracture distributions

## POLISHING



2. Identified/characterized behavior of rogue particles causing sub-surface fractures

## CHEMICAL ETCHING



3. Established techniques using etching to reveal and remove subsurface fractures

## SCRATCH FORENSICS



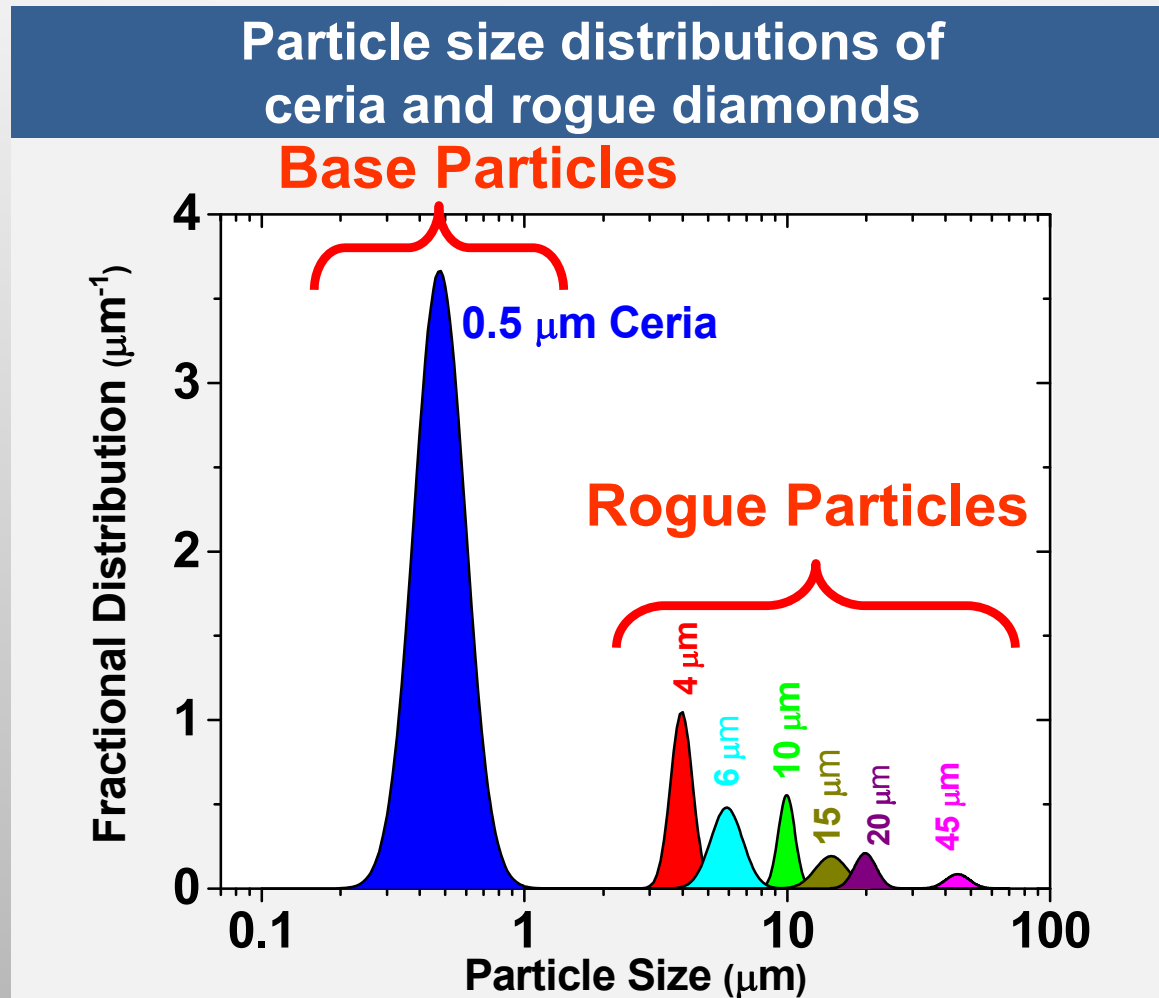
4. Developed quantitative rules for post-diagnosis of cause of surface fractures

## LASER DAMAGE



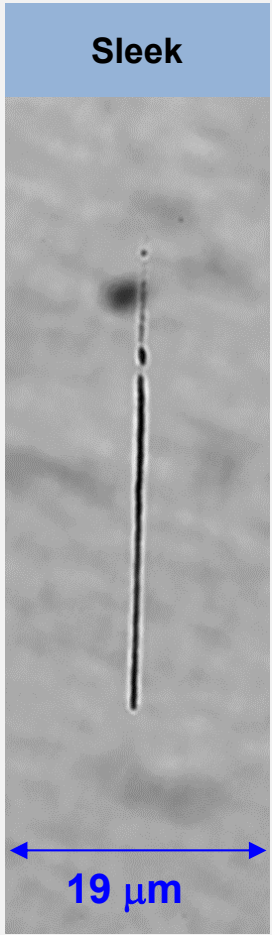
5. Showed link between sub-surface fracture removal & improved laser resistance

# Rogue particles of diamond were added to a ceria slurry during polishing at various sizes & concentrations

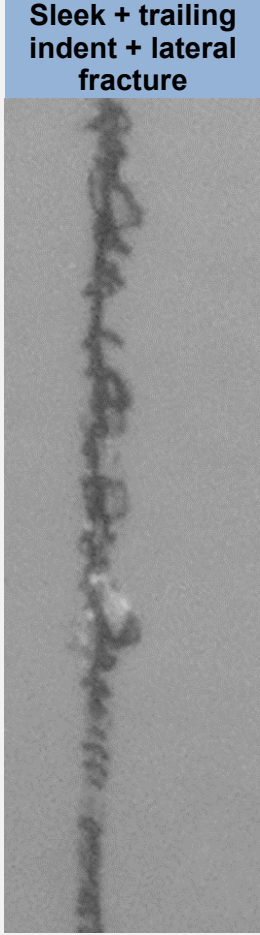
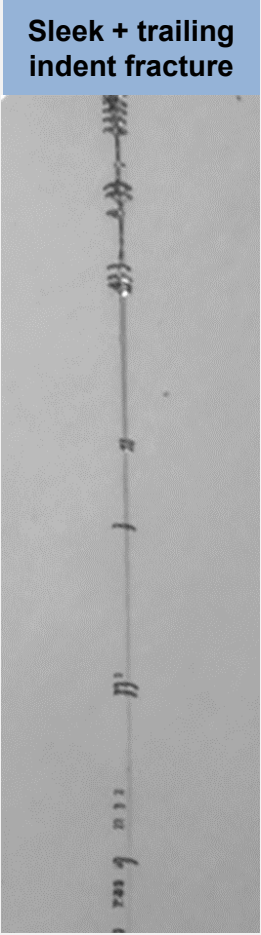
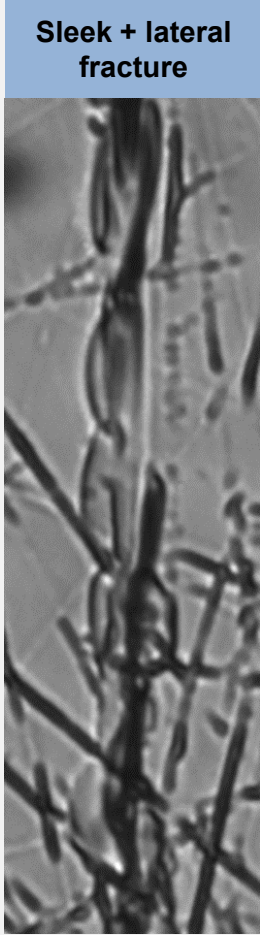


# Rogue particles can cause multiple types of scratches

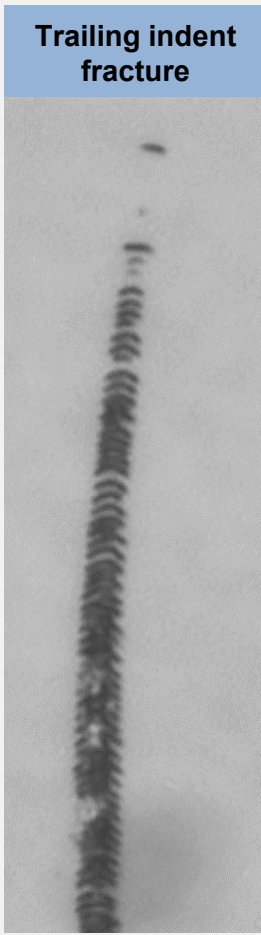
## Plastic Abrasive Wear



## Mixed Brittle fracture / Plastic Abrasive Wear

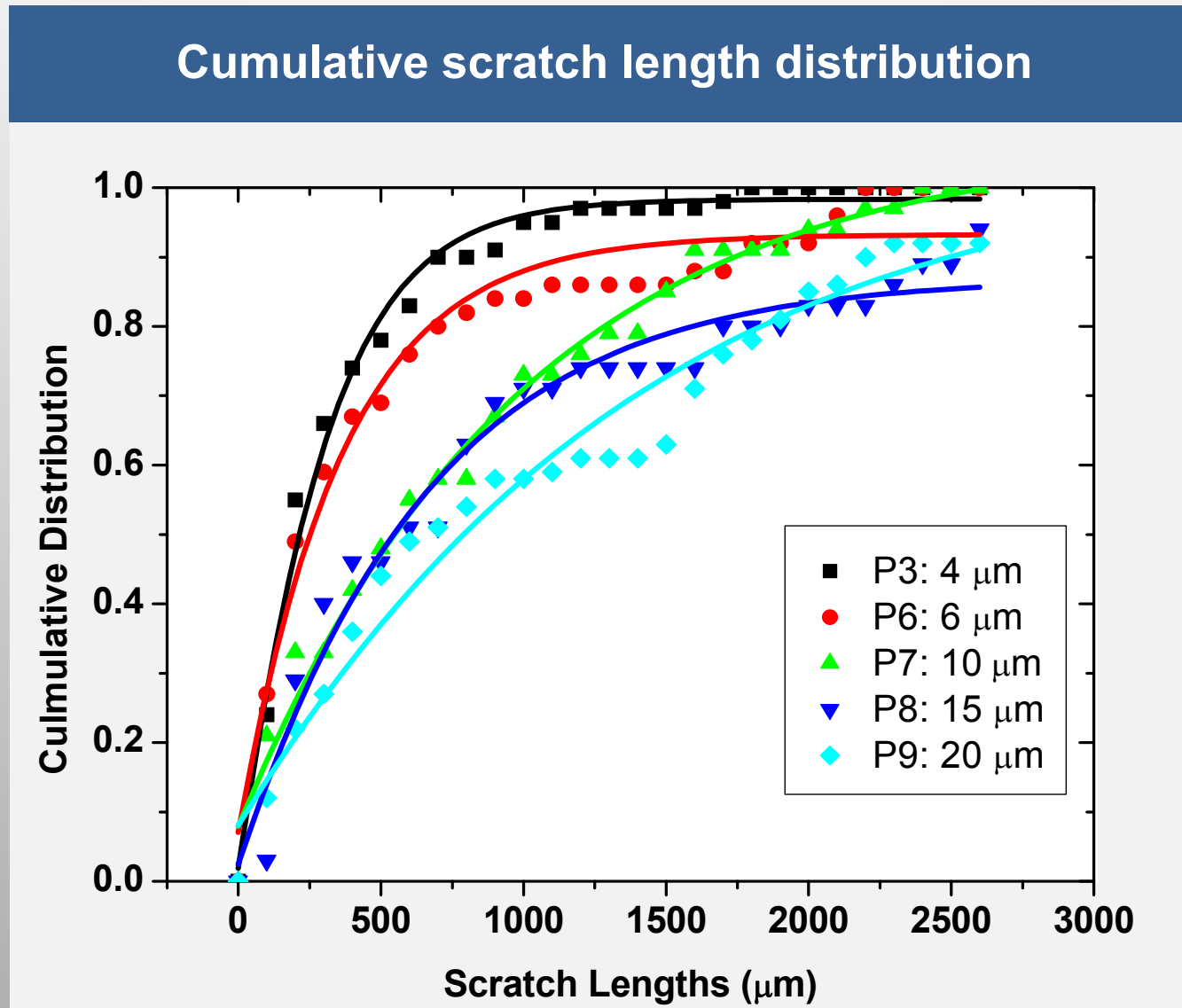


## Brittle Fracture





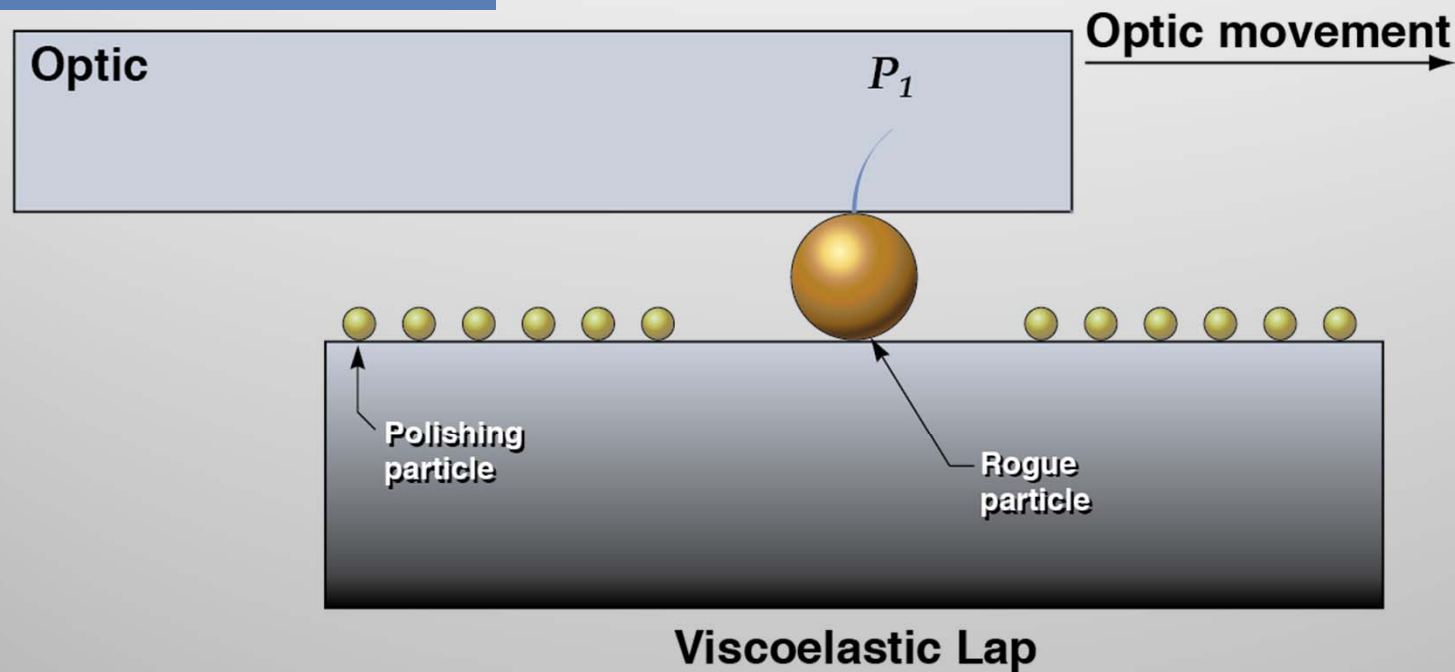
# The scratch length increases with rogue particle size



# The observed scratch lengths can be explained by the viscoelastic penetration of a rogue particle

$$L_{scratch} = 8.9 \frac{v_{ave} \eta R^2}{P}$$

$t = t_0$   
 $P_1 = \text{Load on rogue particle}$

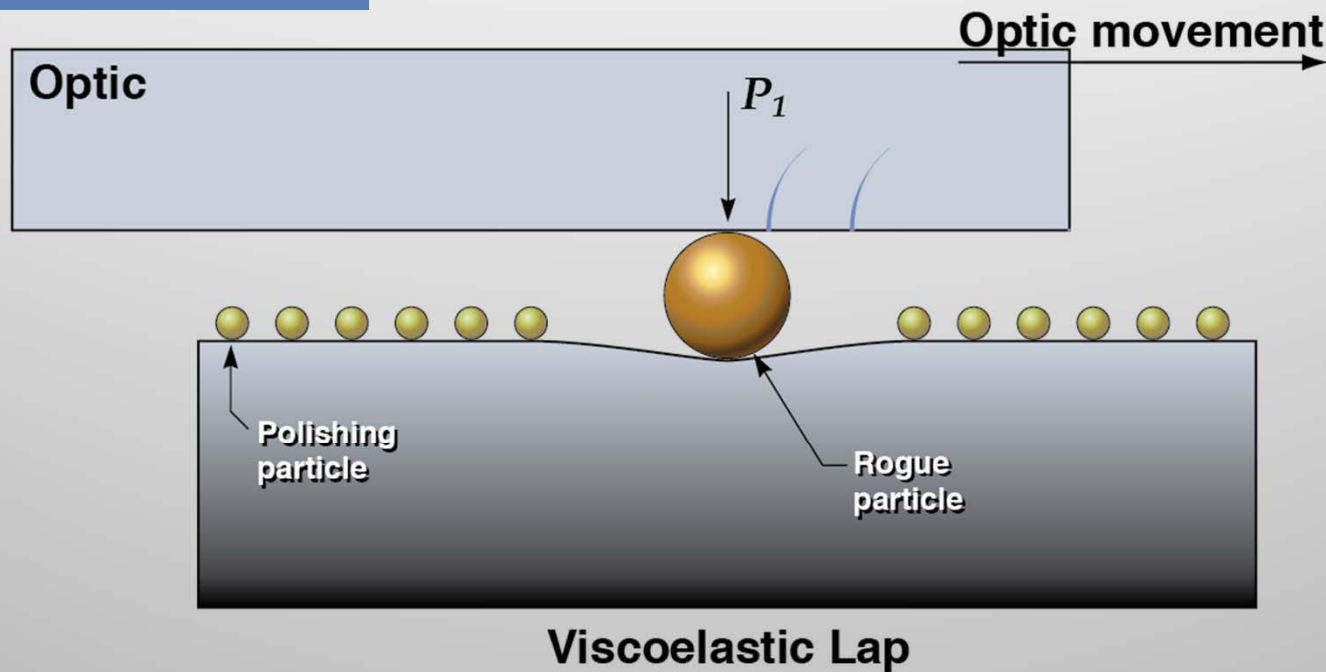


This behavior has been modeled using hard sphere penetration into a linear viscoelastic lap at large penetration

# The observed scratch lengths can be explained by the viscoelastic penetration of a rogue particle

$$L_{scratch} = 8.9 \frac{v_{ave} \eta R^2}{P}$$

$t = t_1$   
 $P_1 = \text{Load on rogue particle}$



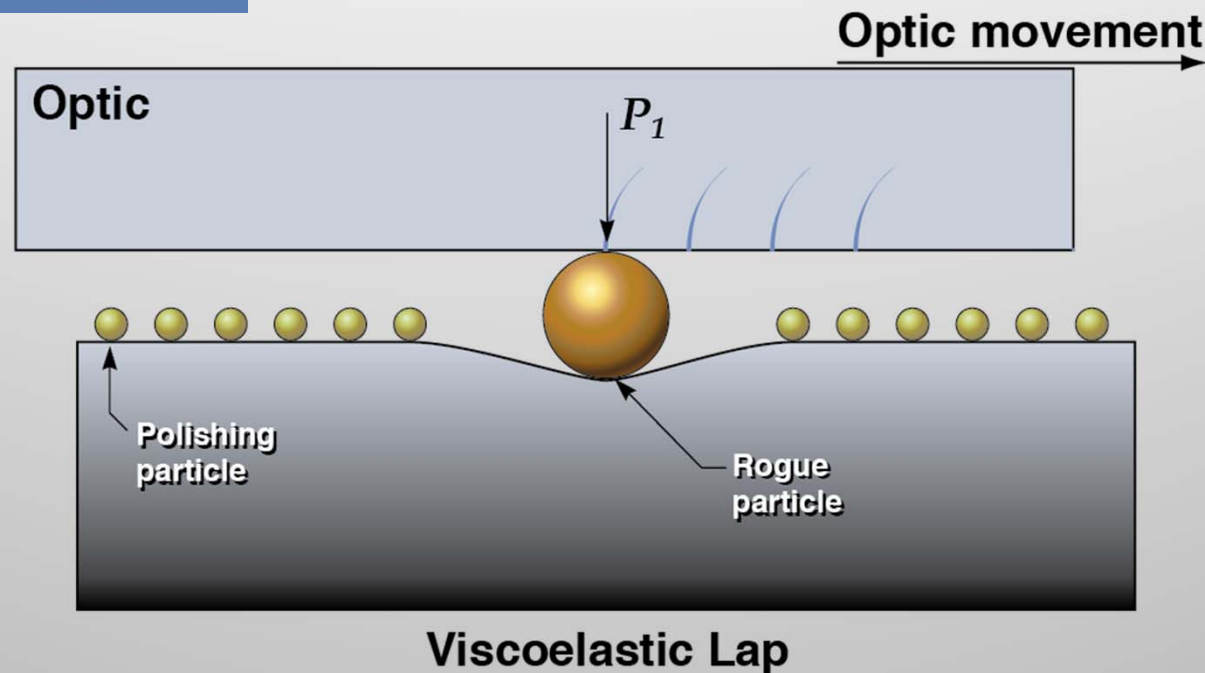
This behavior has been modeled using hard sphere penetration into a linear viscoelastic lap at large penetration

# The observed scratch lengths can be explained by the viscoelastic penetration of a rogue particle

$$L_{scratch} = 8.9 \frac{v_{ave} \eta R^2}{P}$$

$$t = t_2$$

$P_1 = \text{Load on rogue particle}$



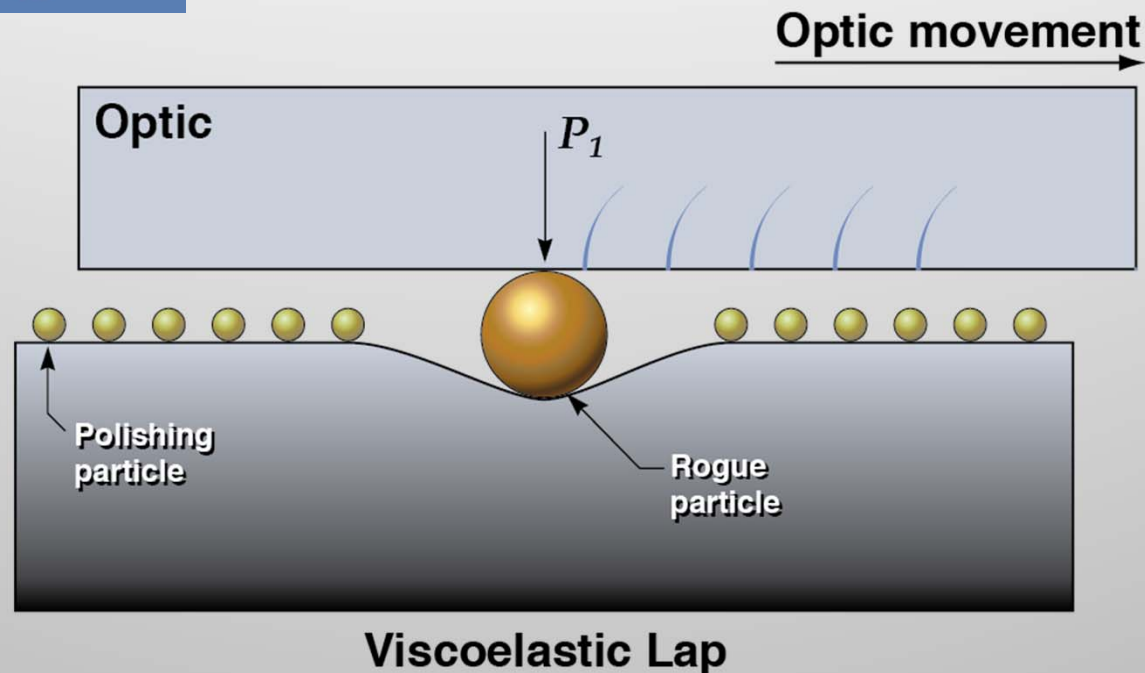
This behavior has been modeled using hard sphere penetration into a linear viscoelastic lap at large penetration

# The observed scratch lengths can be explained by the viscoelastic penetration of a rogue particle

$$L_{scratch} = 8.9 \frac{v_{ave} \eta R^2}{P}$$

$$t = t_3$$

$P_1 = \text{Load on rogue particle}$



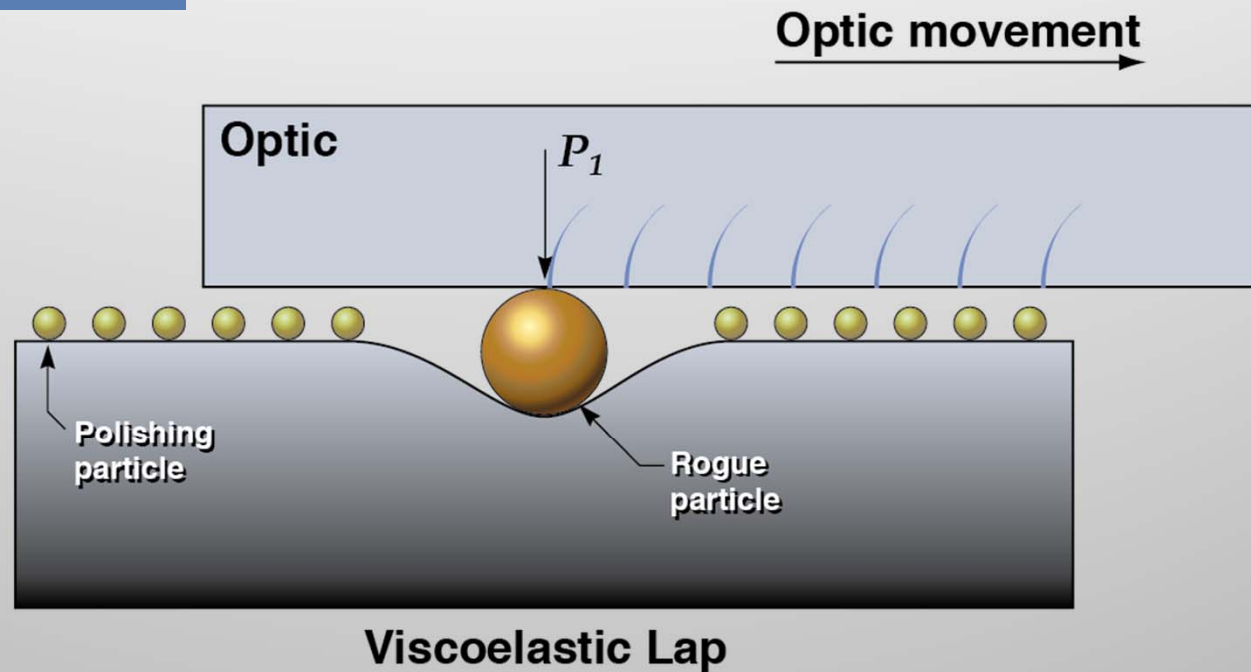
This behavior has been modeled using hard sphere penetration into a linear viscoelastic lap at large penetration

# The observed scratch lengths can be explained by the viscoelastic penetration of a rogue particle

$$L_{scratch} = 8.9 \frac{v_{ave} \eta R^2}{P}$$

$$t = t_4$$

$P_1 = \text{Load on rogue particle}$



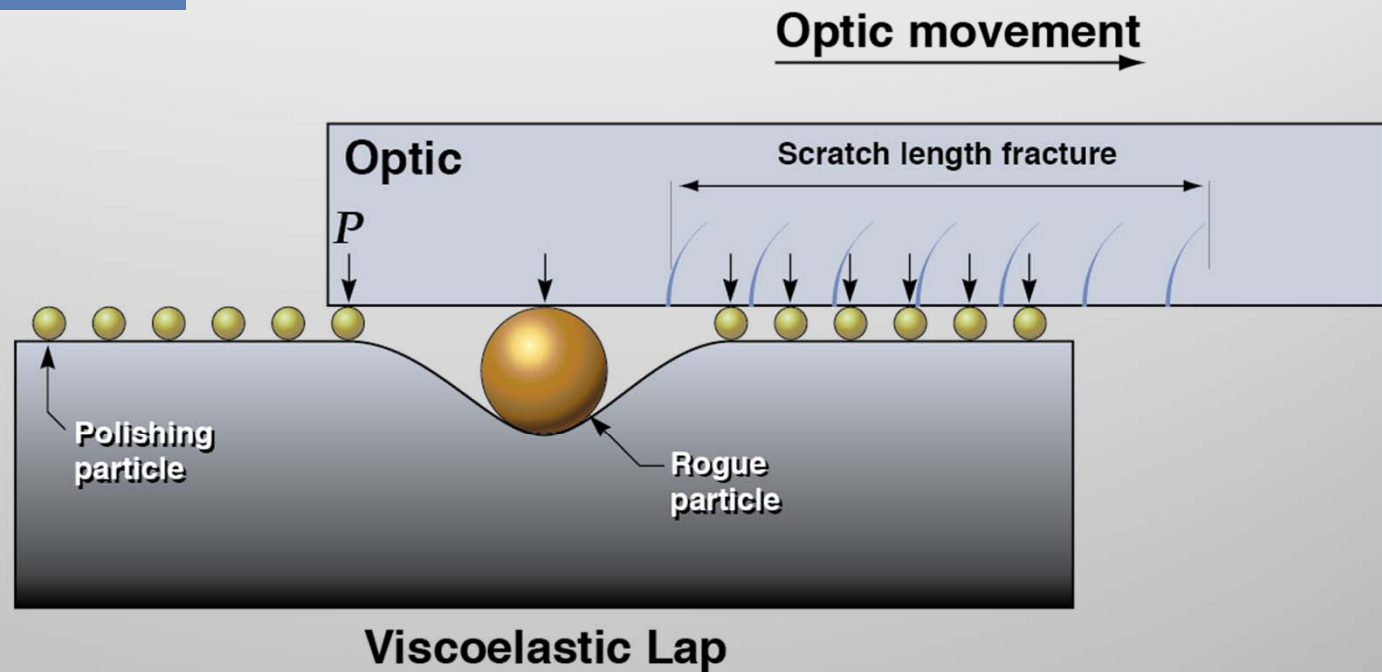
This behavior has been modeled using hard sphere penetration into a linear viscoelastic lap at large penetration

# The observed scratch lengths can be explained by the viscoelastic penetration of a rogue particle

$$L_{scratch} = 8.9 \frac{v_{ave} \eta R^2}{P}$$

$$t = t_5$$

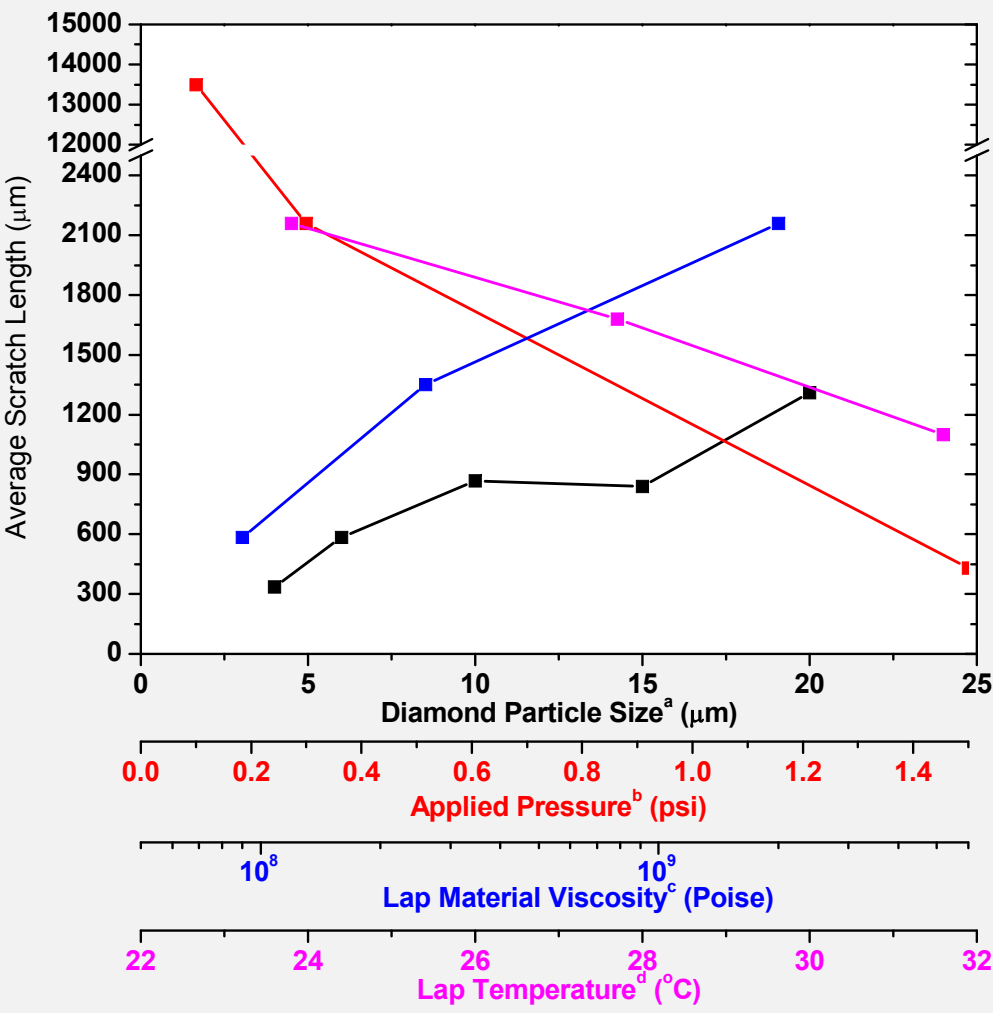
$P = \text{Load on all particles}$



This behavior has been modeled using hard sphere penetration into a linear viscoelastic lap at large penetration

The scratch length correlates with viscoelastic model wrt rogue particle size, pressure, lap viscosity, and lap temperature

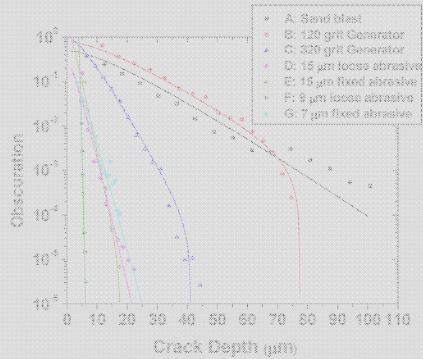
Scratch length as a fn of various process parameters





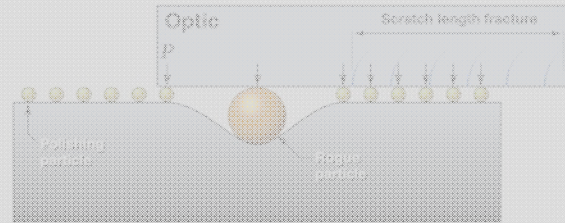
# There are five major areas of effort that have aided in managing sub-surface fractures

## GRINDING



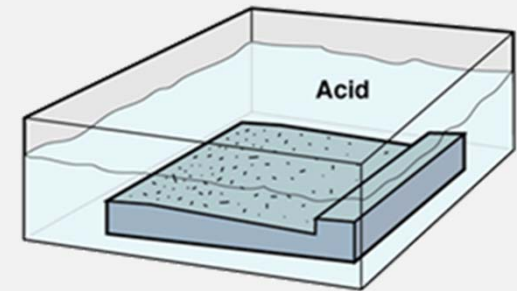
1. Developed fracture mechanics understanding of sub-surface fracture distributions

## POLISHING



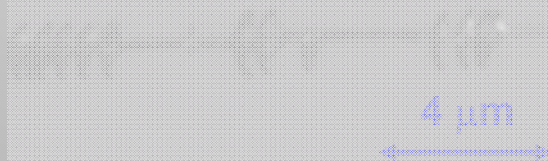
2. Identified/characterized behavior of rogue particles causing sub-surface fractures

## CHEMICAL ETCHING



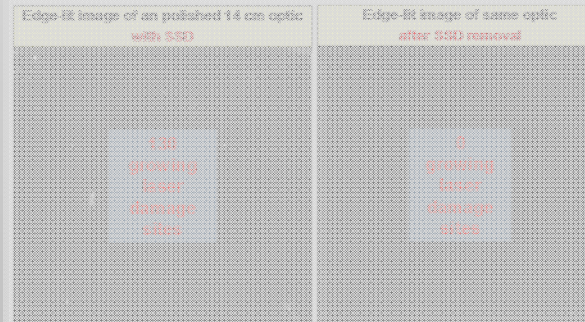
3. Established techniques using etching to reveal and remove subsurface fractures

## SCRATCH FORENSICS



4. Developed quantitative rules for post-diagnosis of cause of surface fractures

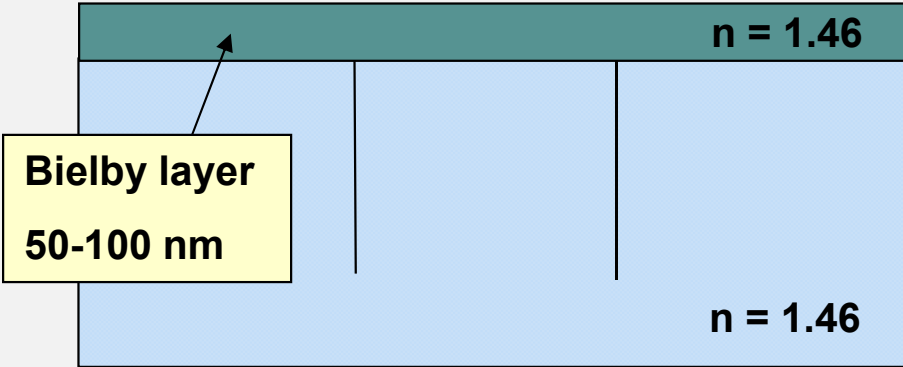
## LASER DAMAGE



5. Showed link between sub-surface fracture removal & improved laser resistance

# HF:NH<sub>4</sub>F etching of fused silica glass allows for removing the Bielby layer and visually observing surface cracks

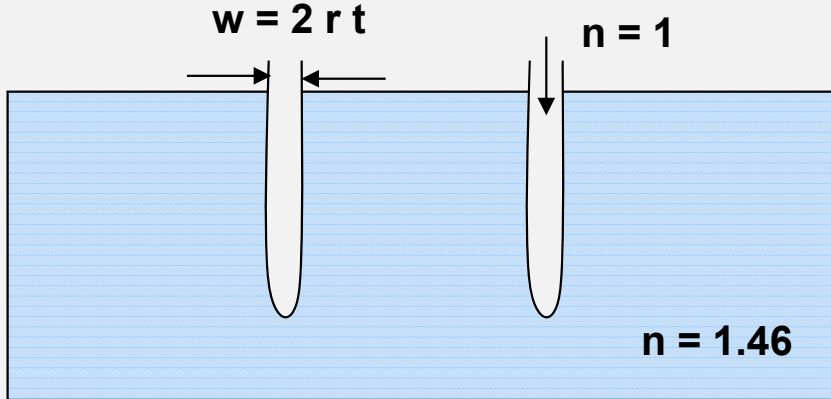
Cross section view of cracks *before* etching



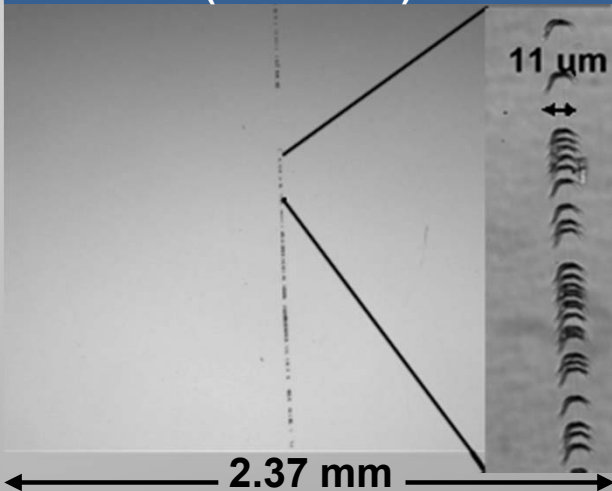
Sleek on fused silica optic (before etch)



Cross section view of cracks *after* etching

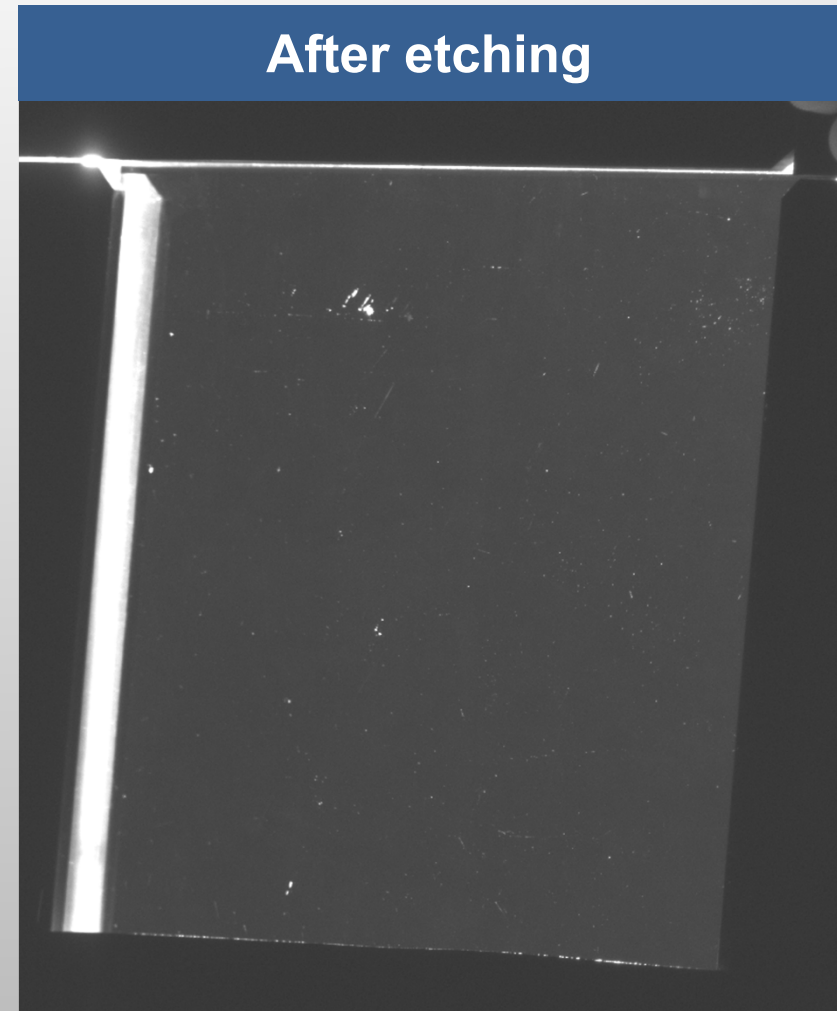
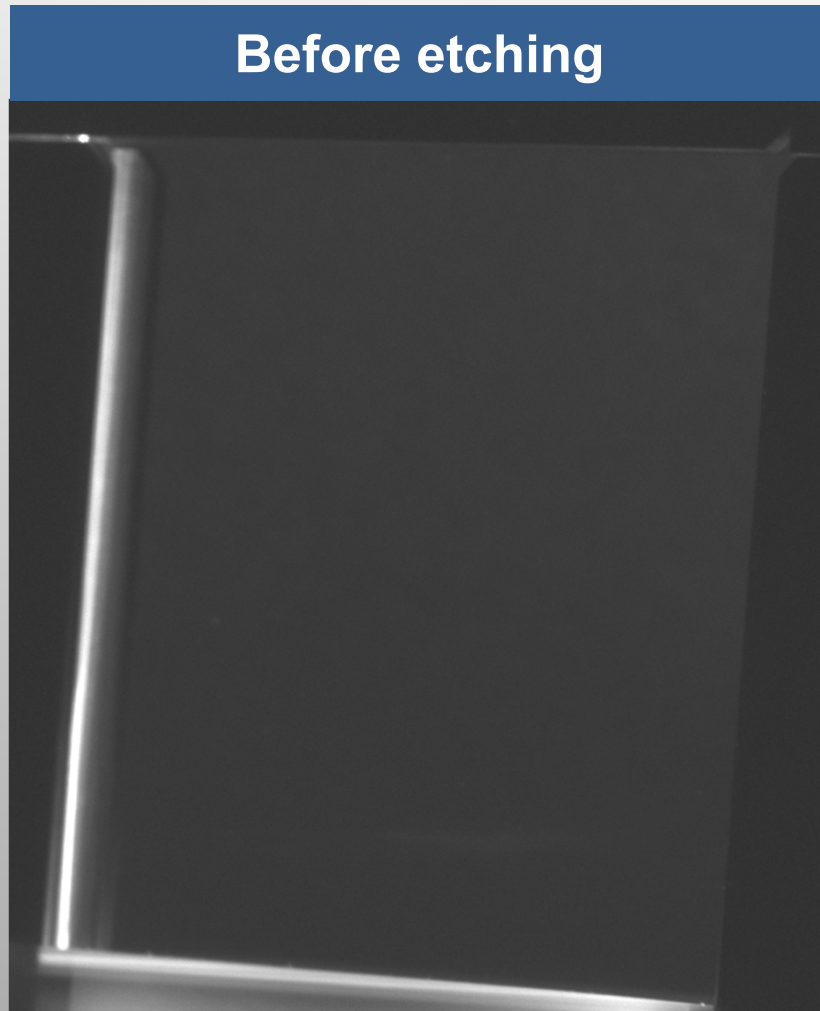


Sleek on fused silica optic (after etch)



## HF Etching exposes sub-surface fractures allowing detection

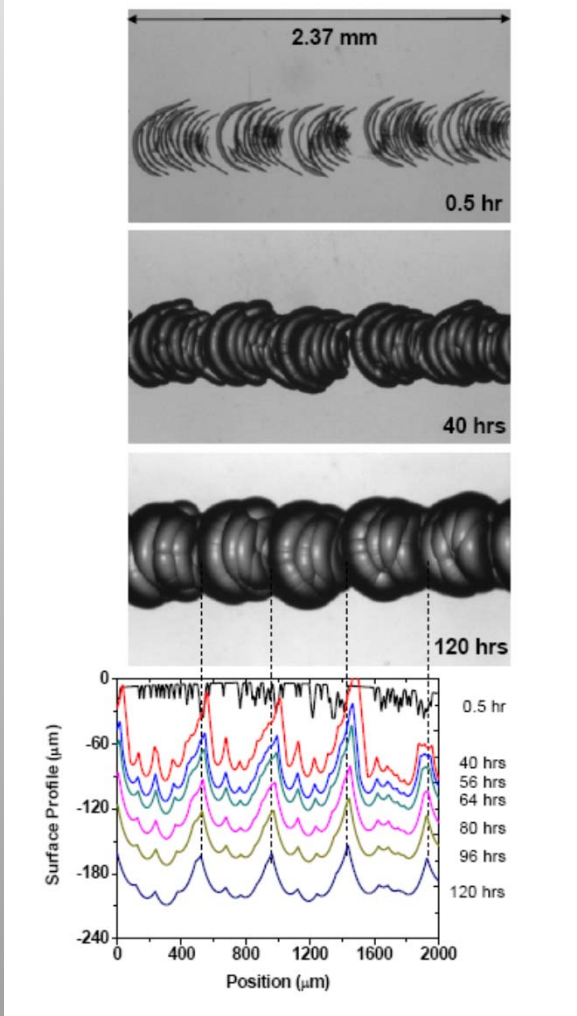
- Polished Optic (14 cm x 14 cm) viewed off axis by side lighting



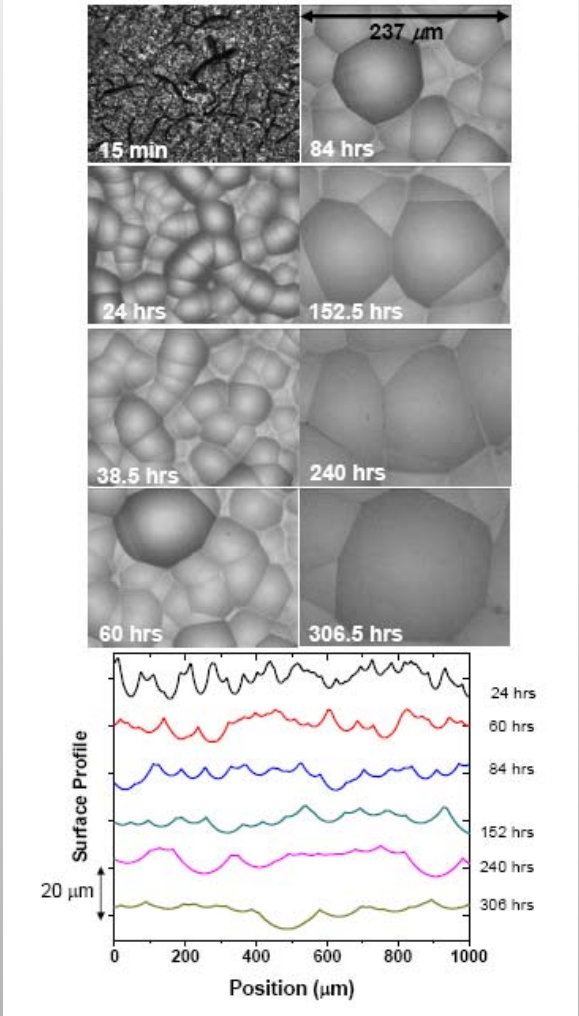
Preston reported this behavior in 1921

# HF etching can be used after grinding to remove subsurface fracture because it annihilates neighboring cracks

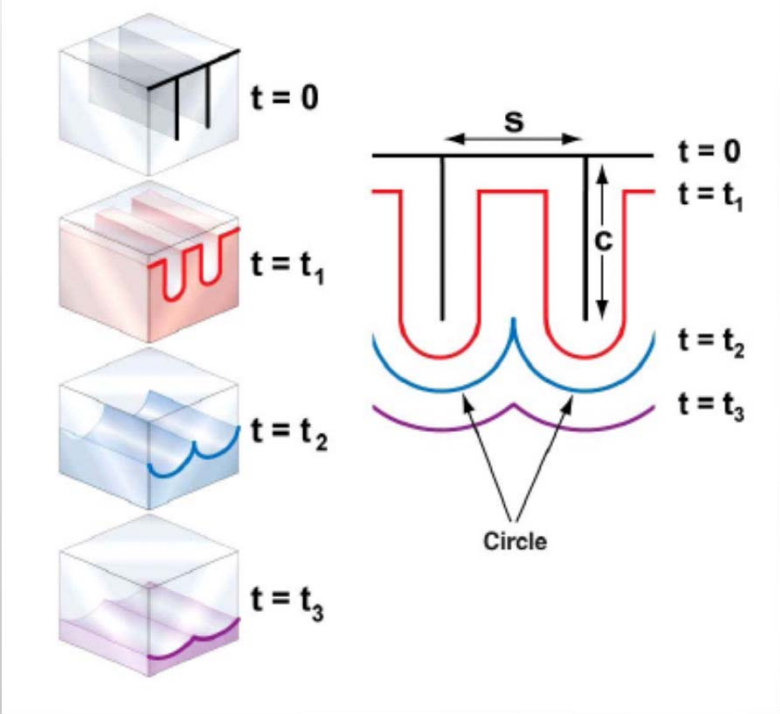
Etching a scratch



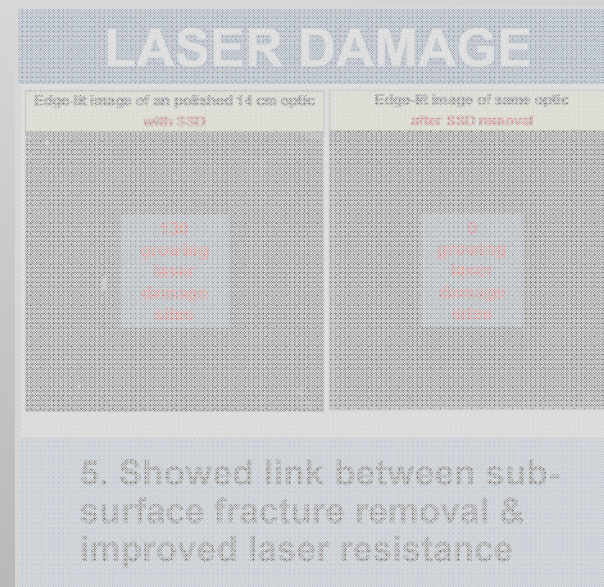
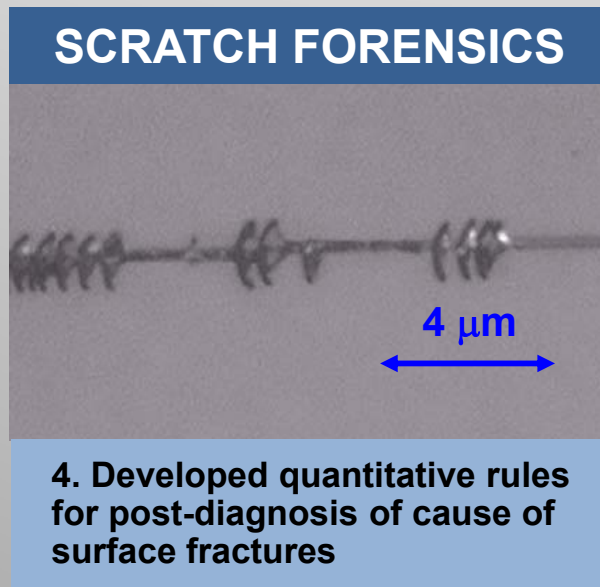
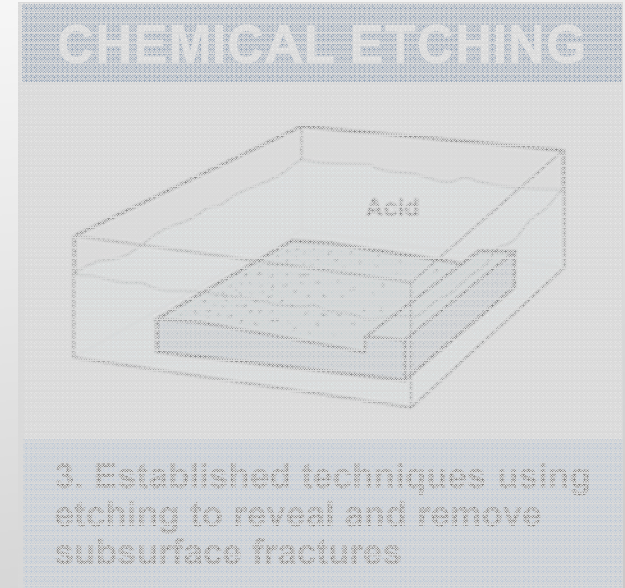
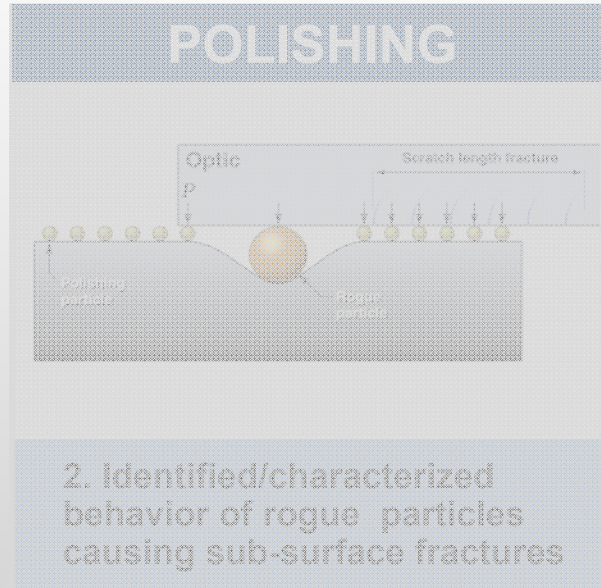
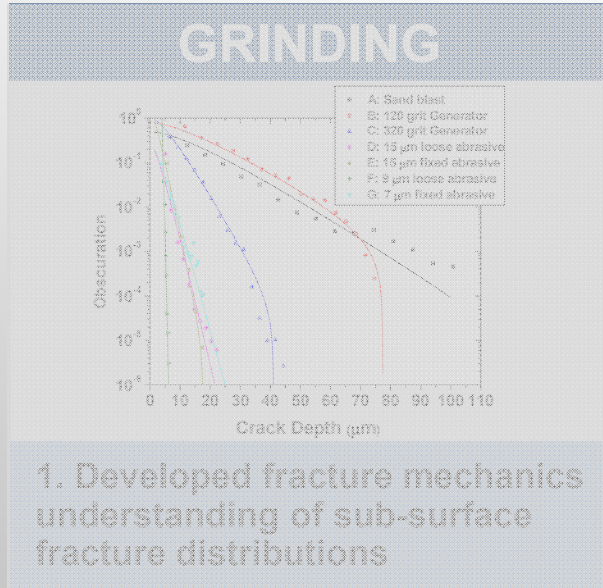
Etching ground surface



Simple Geometric Model



# There are five major areas of effort that have aided in managing sub-surface fractures



# Our studies have provided new rules that Opticians use to diagnose the cause of or to mitigate scratches

<u>Property of scratch</u>	<u>What can it tell you?</u>	<u>Rule / Example</u>
----------------------------	------------------------------	-----------------------

1. Scratch width or trailing indent length (L)

- Size of rogue particle (d)
- Size distribution of Rogue Particles
- Process step
- Depth of fracture ( $c_{90}$  or  $c_{max}$ )

For grinding

$$0.15 d \leq L \leq 0.3 d$$

For polishing

$$0.3 d \leq L \leq 0.5 d$$

2. Number density

- Rogue particle concentration

3. Scratch length ( $L_{scratch}$ )

- Lap properties and rogue particle size

4. Scratch type (plastic, brittle, mixed)

- Load during fracture
- Sharpness of particle

5. Orientation and pattern of trailing indent

- Particle movement direction
- Particle rotation
- Stick slip behavior

6. Curvature or scratch pattern

- Pathway of indenting particle
- Shape of tool
- Handling vs polishing

7. Location on optic

- Material removal and surface figure

Sample	<L>
A: Sandblast	27.1 $\mu\text{m}$
B: 120 grit	28.3 $\mu\text{m}$
C: 320 grit	14.9 $\mu\text{m}$
D: 15 $\mu\text{m}$ loose	4.6 $\mu\text{m}$
E: 15 $\mu\text{m}$ fixed	4.5 $\mu\text{m}$
F: 9 $\mu\text{m}$ loose	1.9 $\mu\text{m}$
G: 7 $\mu\text{m}$ fixed	8.4 $\mu\text{m}$

$$c_{90} = 0.9 \langle L \rangle \quad c_{max} = 2.8 \langle L \rangle$$

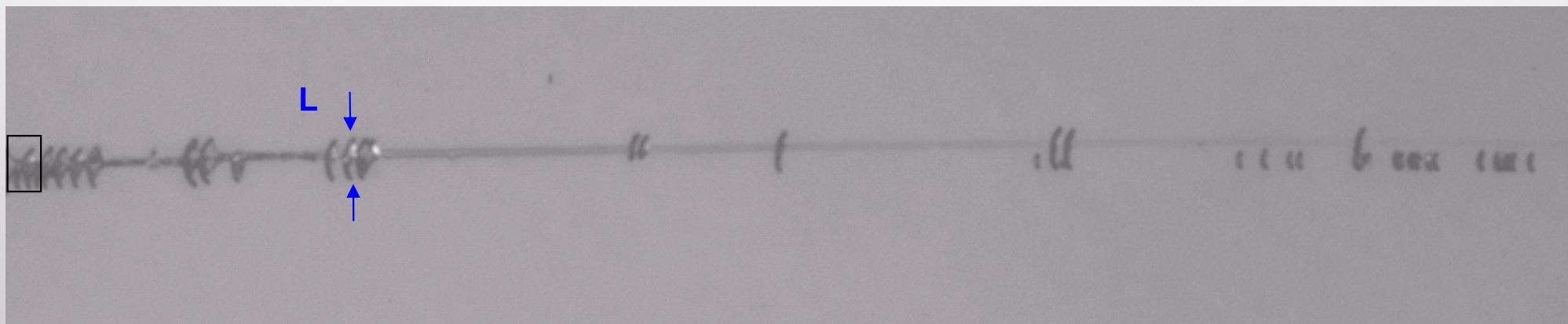
$P \approx 0.001 - 0.1 N$  Plastic only

$P \approx 0.1 - 5 N$  Plastic & Brittle

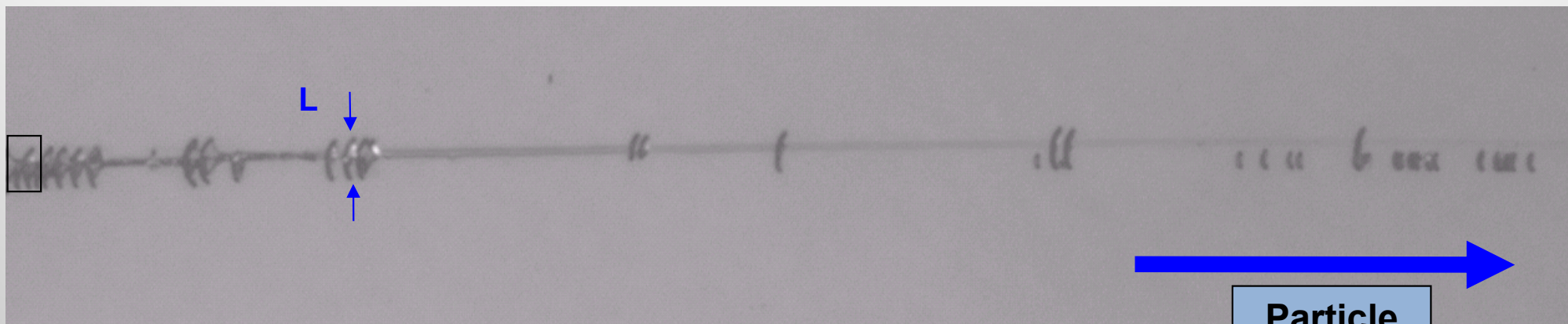
$P > 5 N$  Plastic & rubble

$$L_{scratch} = 8.9 \frac{v_{ave} \eta R^2}{P}$$

# Example of scratch forensics



# Example of scratch forensics



**Scratch Type = Plastic + Brittle: trailing indent**

**Particle Sliding Direction**

**Trailing Indent length:  $L = 1.9 \mu\text{m}$**

**Rogue Particle  $\sim 3.8 - 5.7 \mu\text{m}$**

**$c_{90} = 1.8 \mu\text{m}$**

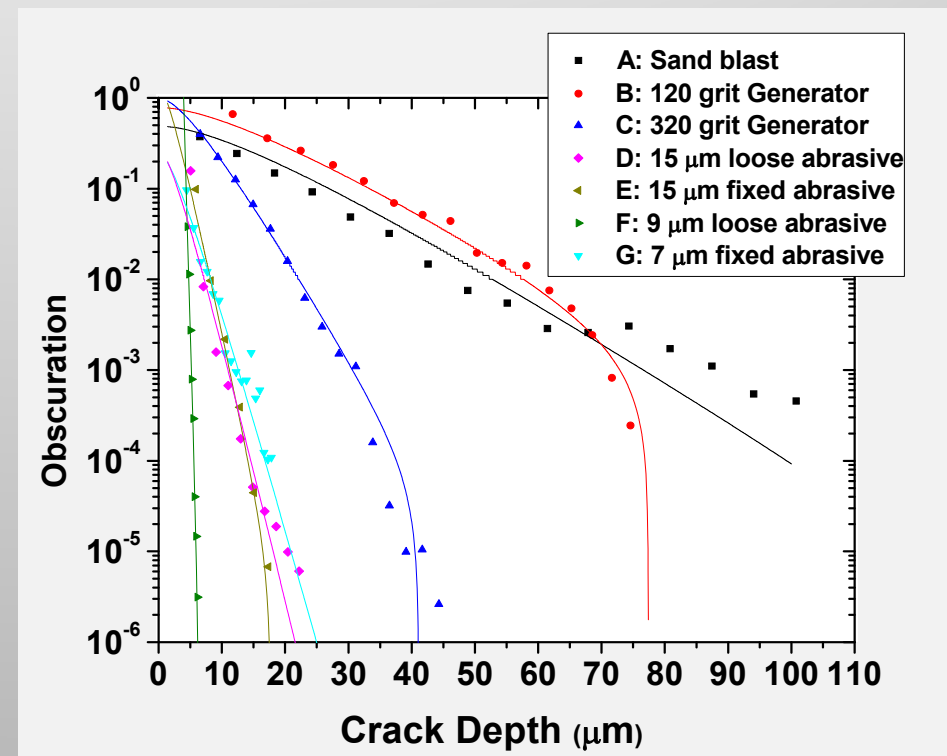
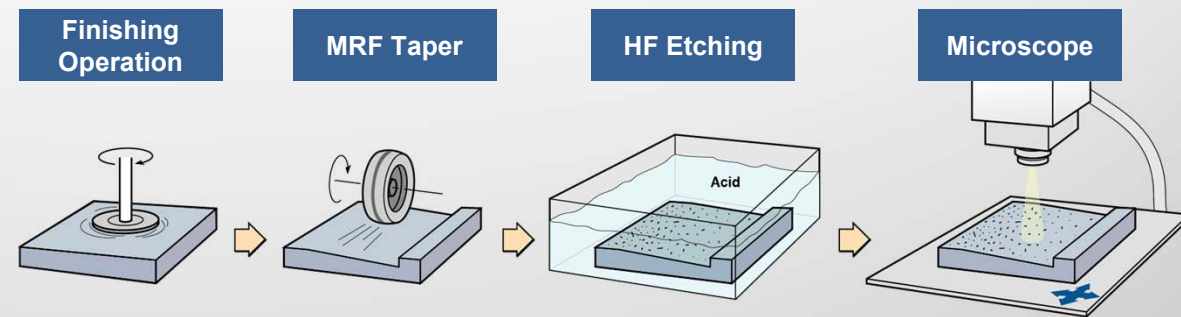
**Scratch Length  $\sim 130 \mu\text{m}$**

**Scratch time  $\sim 0.16 \text{ msec}$**



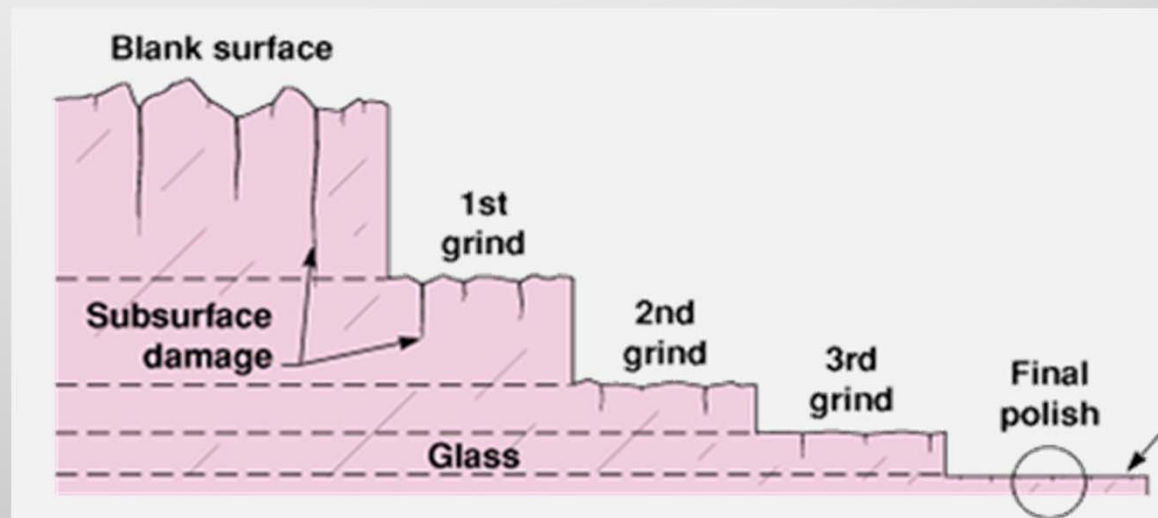
# Strategy for reducing the scratch density on optical surfaces

1. Measure the SSD at each step
2. Define proper removal rate at each step such that all the SSD from previous step is removed
3. Can use etching as a means to remove SSD just after grinding
4. Ensure handling and cleaning at each step does not let rogue particles make contact with surface
5. Remove all rogue particles in polishers; Use scratch forensics to determine source
6. Use etched scratch dig inspections between steps and at end of process



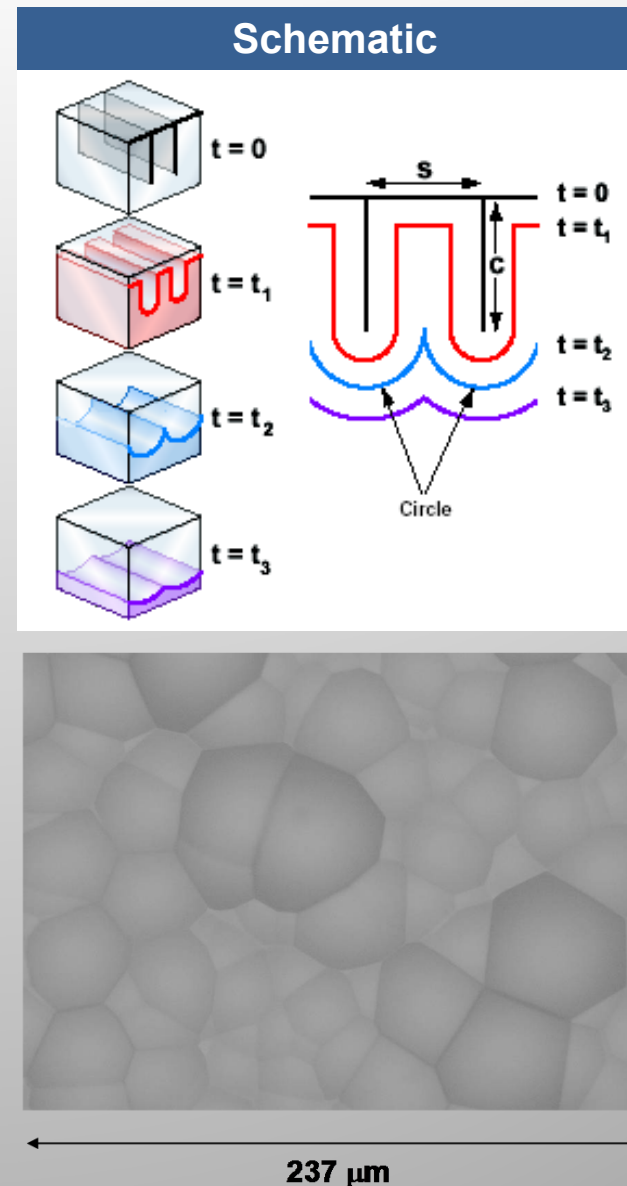
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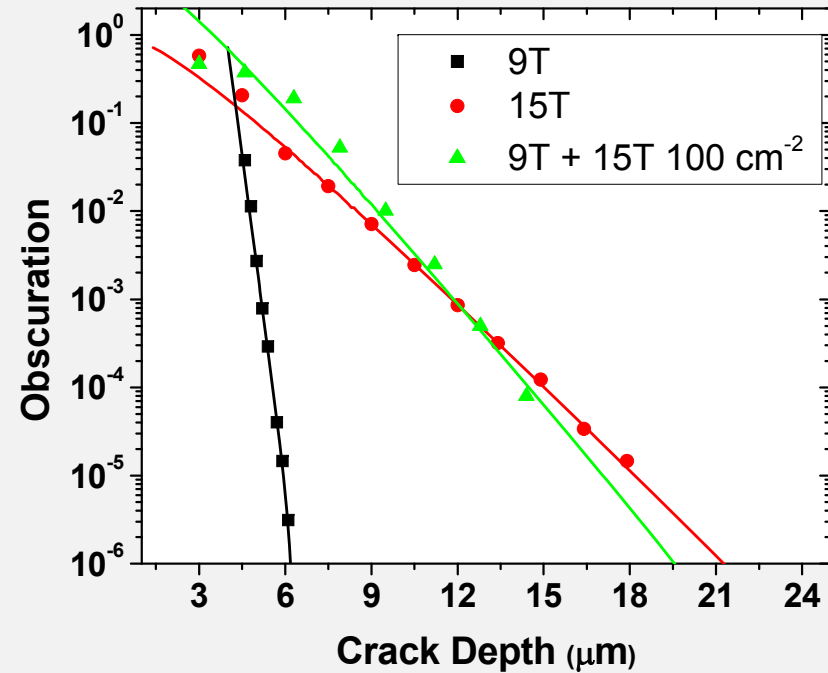
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Crack *depth* distributions:  
Loose abrasive grinding with addition of rogue particles



## Rogue particle sources

- 1) In slurry from foreign particle or agglomerates
- 2) Dried slurry on components falling in
- 3) Contamination from polisher exterior

# Strategy for reducing the scratch density on optical surfaces

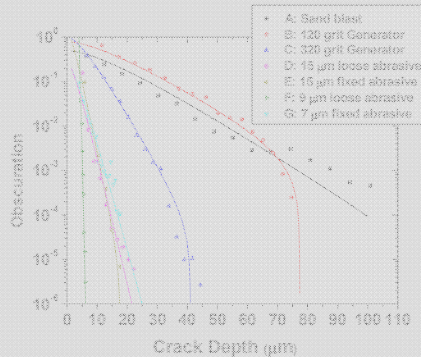
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Etching provides a means of revealing subsurface damage masked by hydrated silica



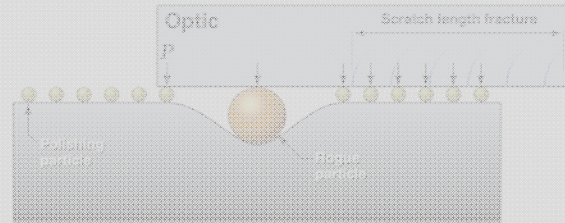
# There are five major areas of effort that have aided in managing sub-surface fractures

## GRINDING



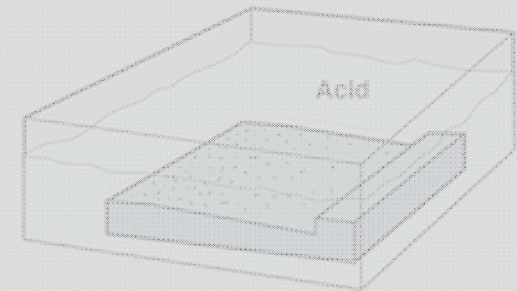
1. Developed fracture mechanics understanding of sub-surface fracture distributions

## POLISHING



2. Identified/characterized behavior of rogue particles causing sub-surface fractures

## CHEMICAL ETCHING



3. Established techniques using etching to reveal and remove subsurface fractures

## SCRATCH FORENSICS



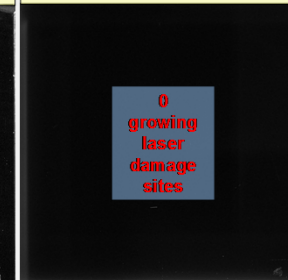
4. Developed quantitative rules for post-diagnosis of cause of surface fractures

## LASER DAMAGE

Edge-lit image of an polished 14 cm optic with SSD



Edge-lit image of same optic after SSD removal



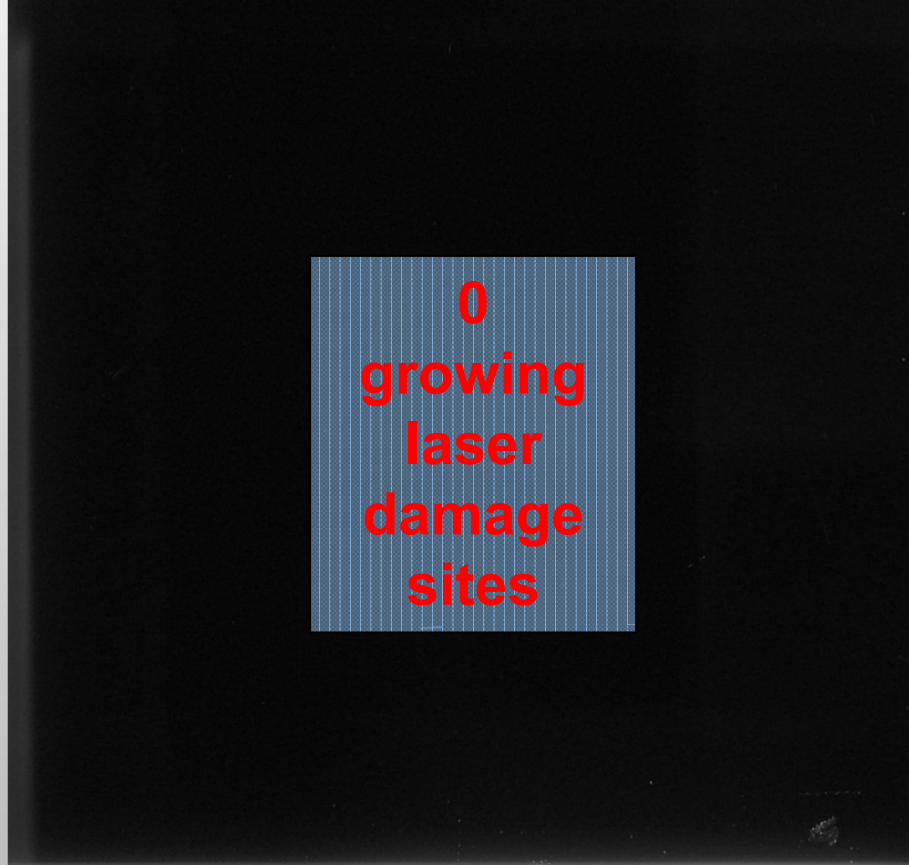
5. Showed link between sub-surface fracture removal & improved laser resistance

# SSD-free test optics have been fabricated such it does not laser damage, supporting the “absorber-in-a-crack” theory

Edge-lit image of an polished 14 cm optic **with SSD**



Edge-lit image of same optic **after SSD removal**



Laser testing on a 14 cm x 14 cm test optic to 14 J/cm<sup>2</sup> (351 nm, 3 ns equiv) resulted in the elimination of growing laser initiation site upon SSD removal

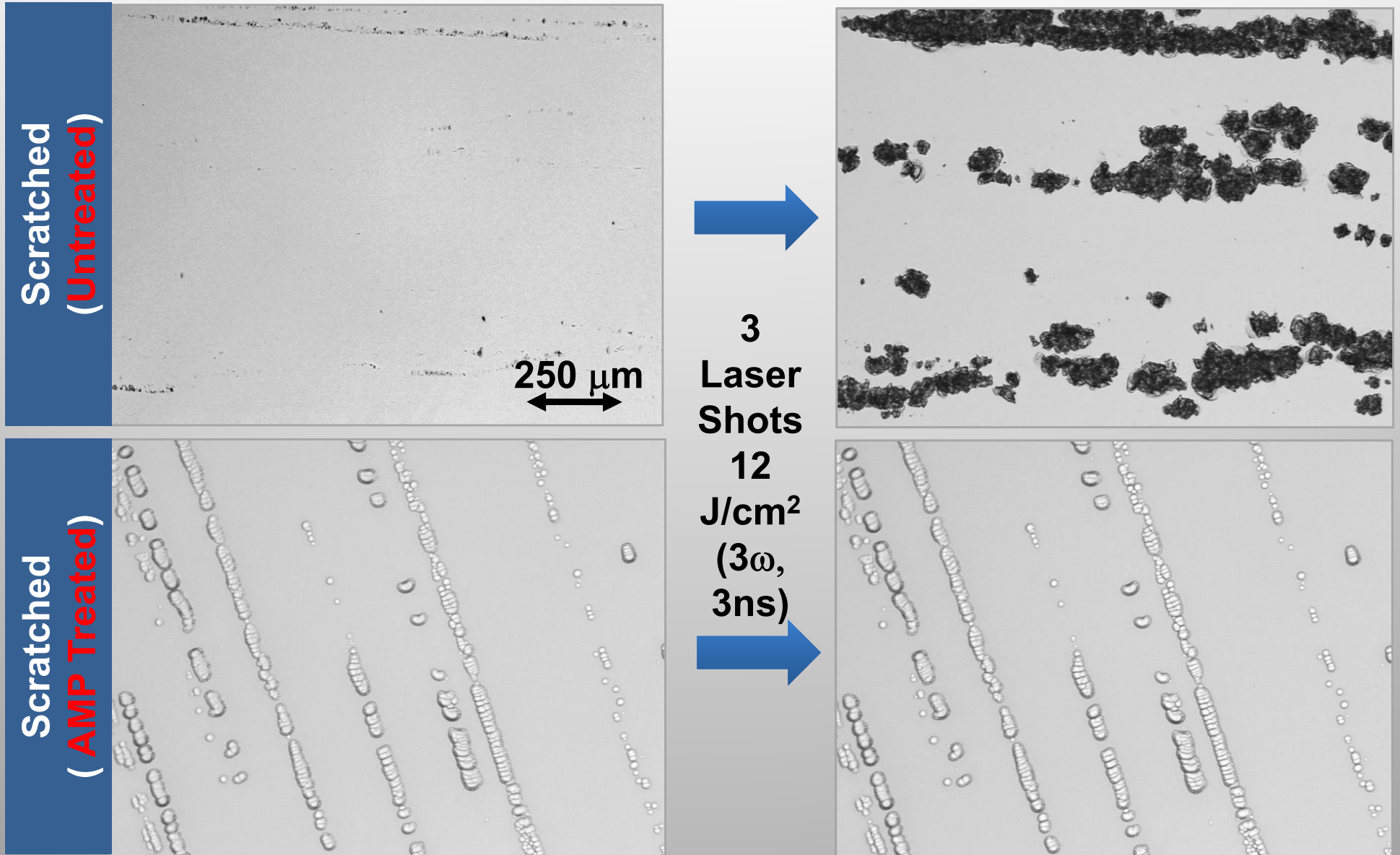
# AMP process system



T. Suratwala JACS 94(2) (2010) 416; P. Miller US Patent 0079931 (2011)  
Lawrence Livermore National Laboratory



# AMP process significantly reduces laser damage initiation per unit scratch length



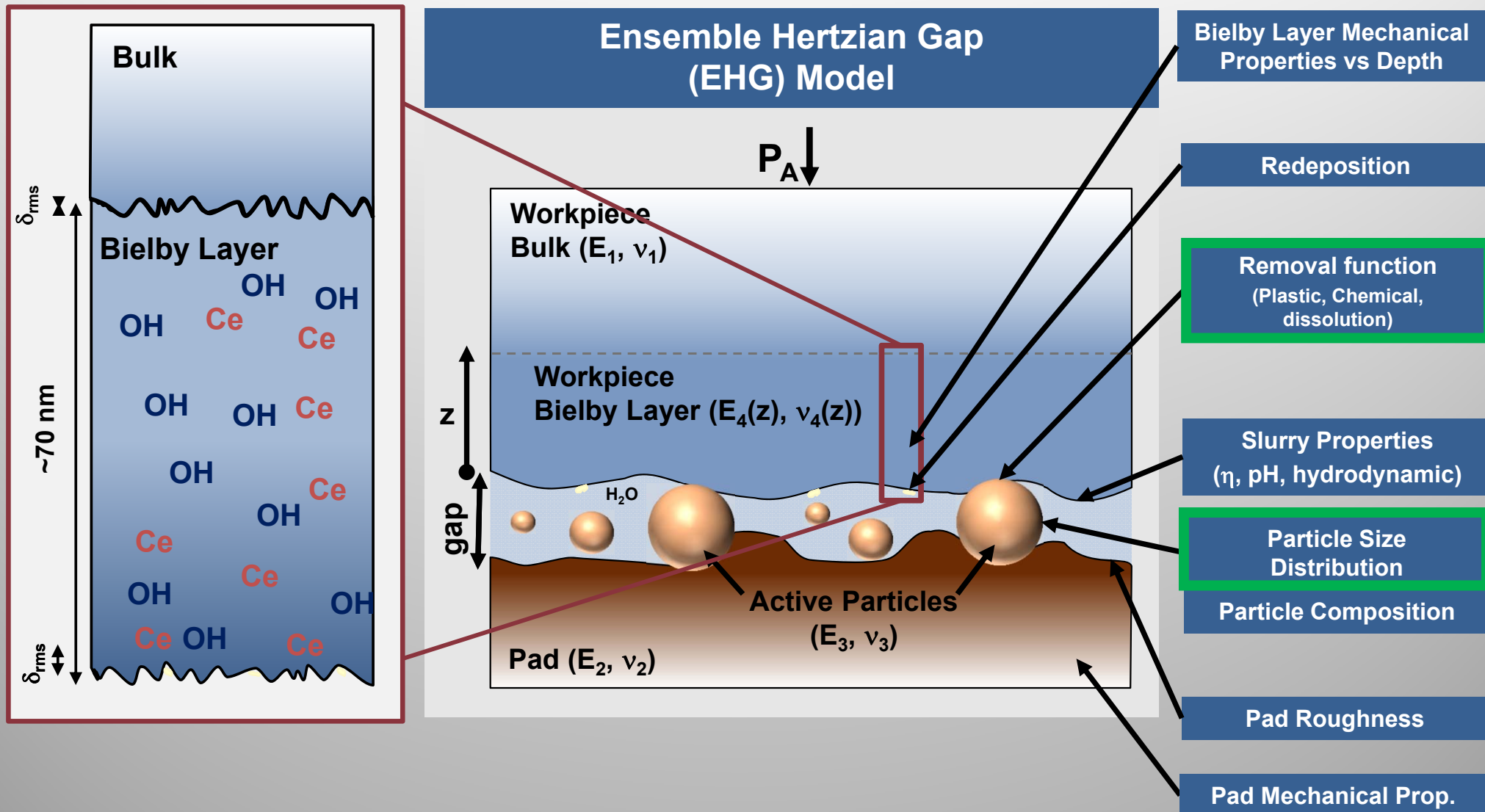
# The materials science behind grinding & polishing

**1. Sub-surface Damage (scratch/dig)**

**2. Roughness**

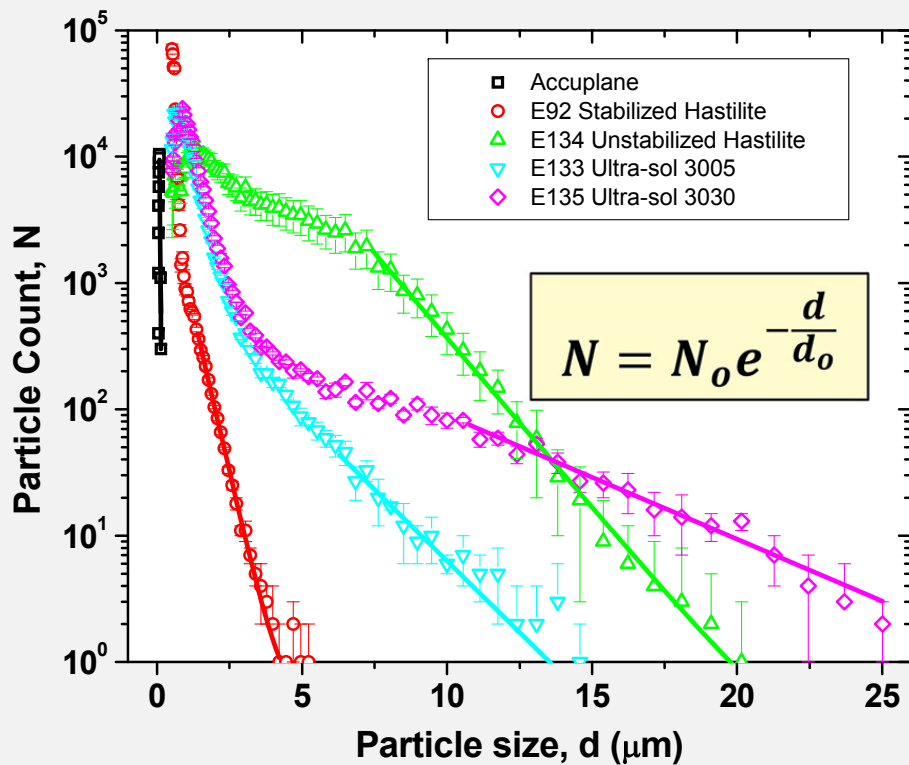
**3. Surface Figure**

# To understand surface roughness, one need to understand the complex microscopic & chemical interactions during polishing



# The tail end of the slurry's PSD\* strongly correlates with workpiece roughness

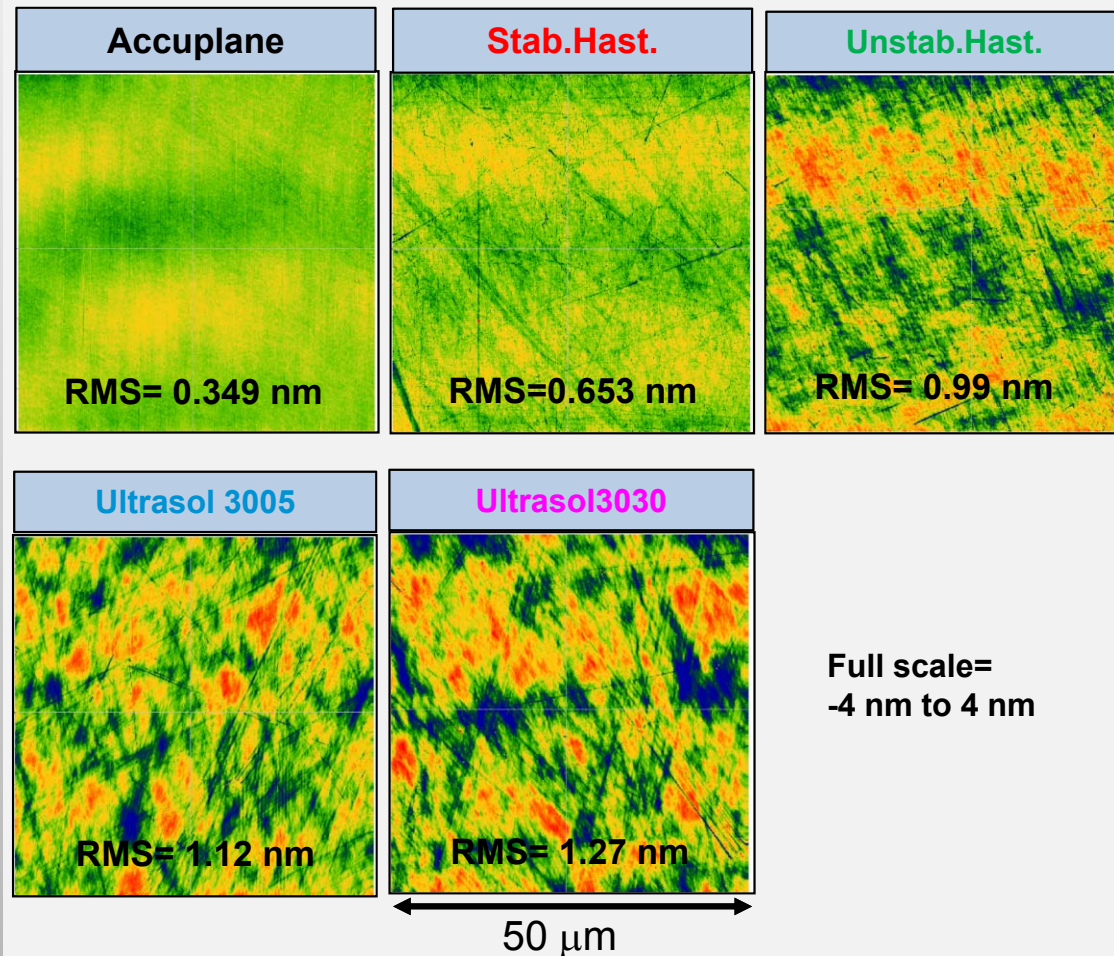
## Measured PSD\* of ceria slurries



The tail end of each slurry follows a single exponential distribution

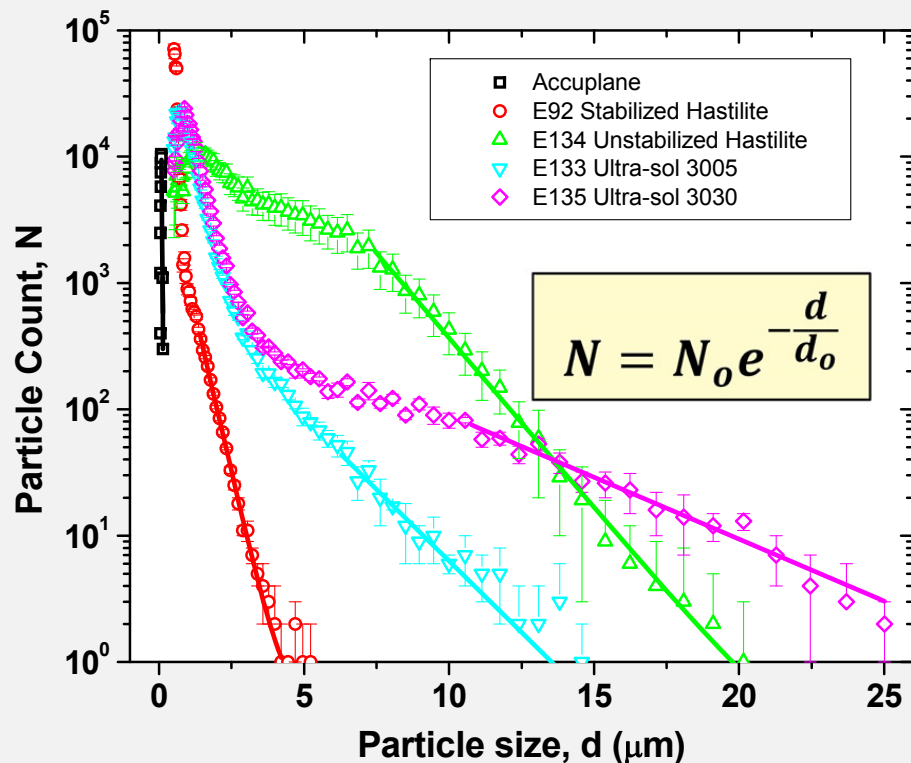
\*Particle size distribution

## AFM images of fused silica workpieces after polishing with different ceria slurries



# The tail end of the slurry's PSD\* strongly correlates with workpiece roughness

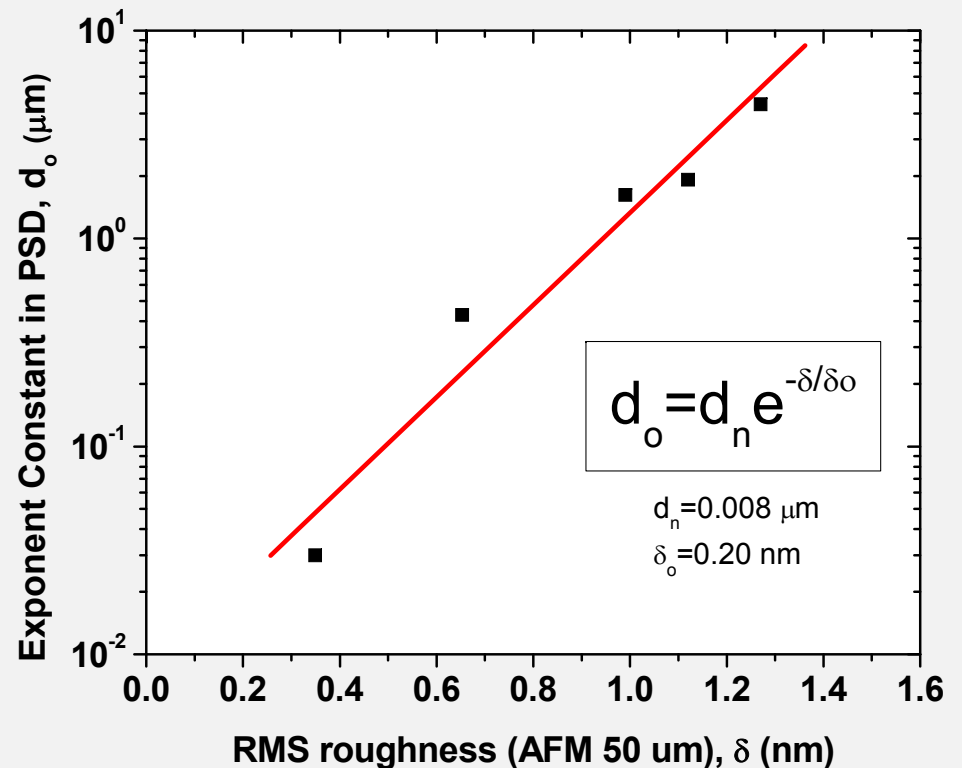
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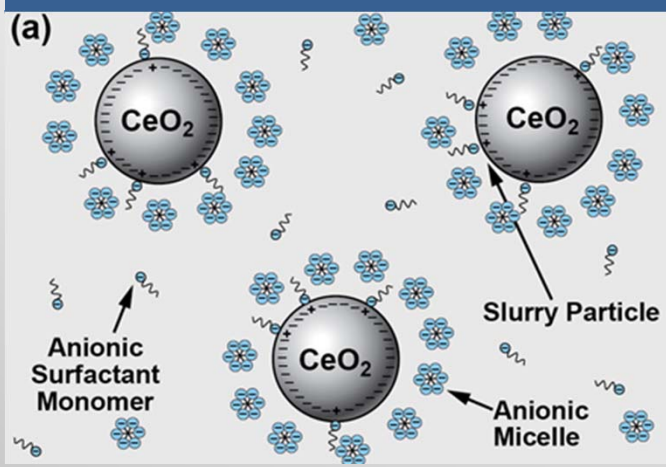
## Exponent constant in PSD of slurry vs RMS roughness of polished surface



The slope of the slurry's PSD quantitatively scales with the rms roughness

# Novel chemical slurry stabilization and engineered filtration has resulted in improve slurry PSD

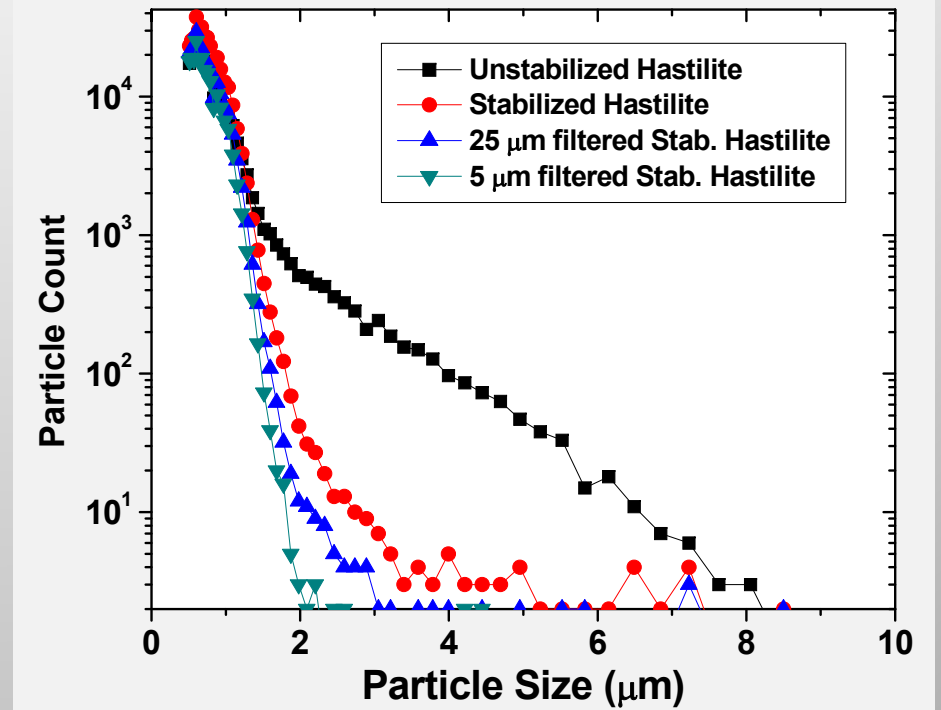
## Chemical Stabilization



## Engineered Filtration



## Improved Particle Size Distributions

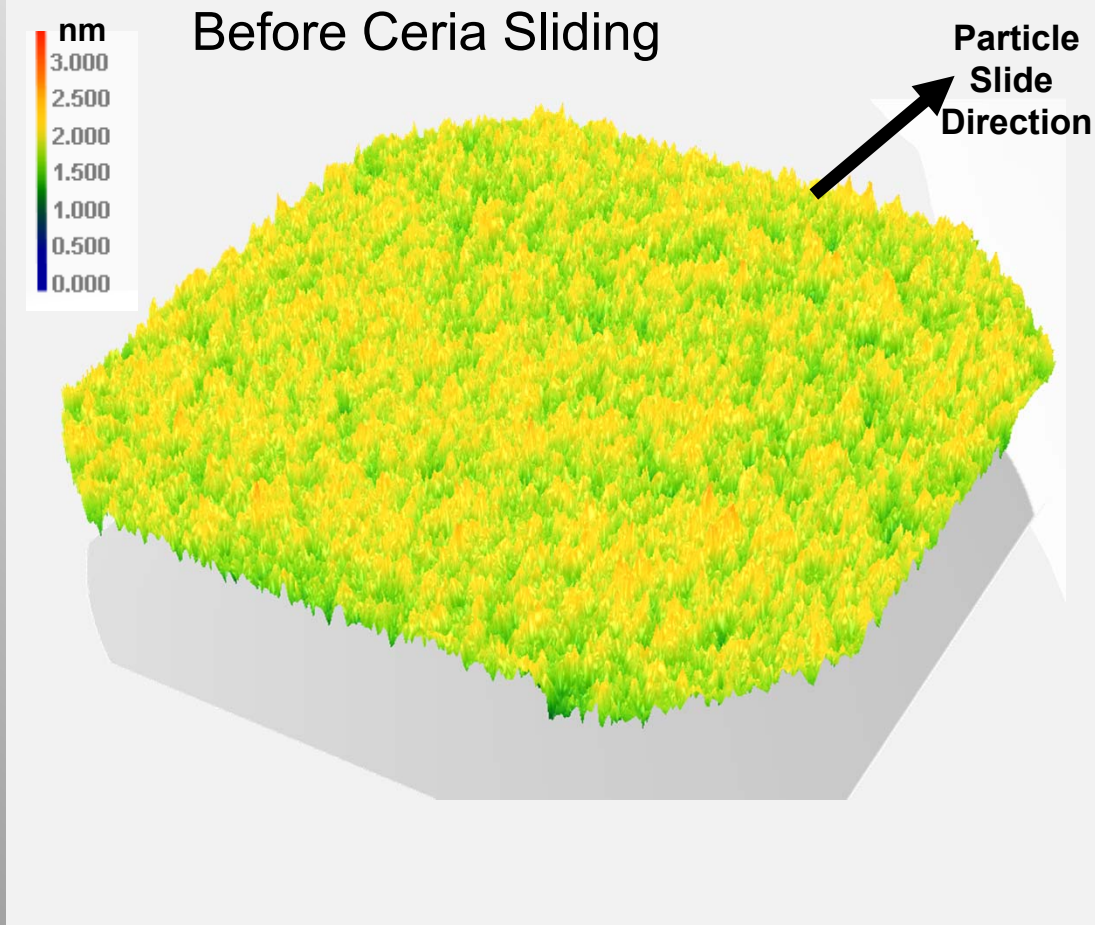


- Surfactant dramatically reduces agglomeration without reducing removal rate
- Appropriate filtration further improves PSD

US Patent Application WO 2012129244 A1 (September 27, 2012)  
R. Dylla-Spears, Colloids & Surfaces A 447 (2014) 32  
T. Suratwala, JACS 97 (2014) 81

# Single pass ceria particle sliding experiments suggest 'plastic' - type removal can occur during polishing

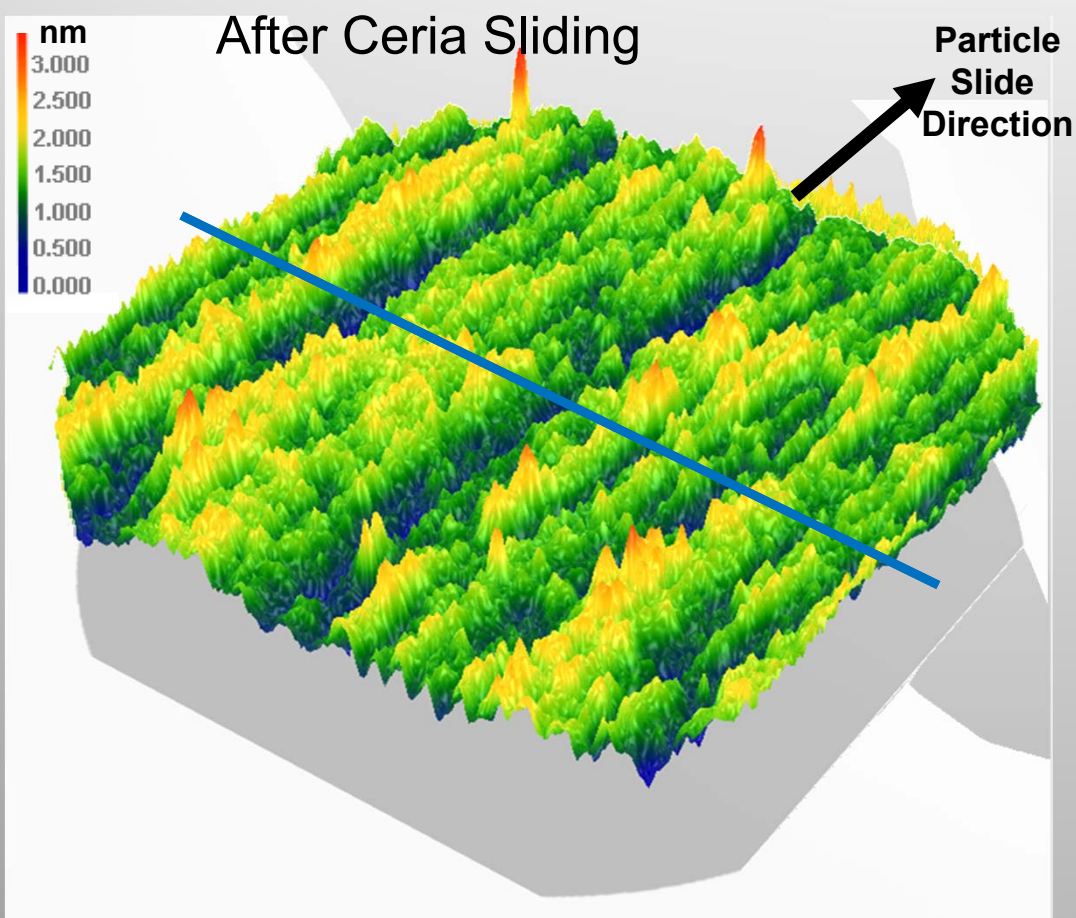
AFM Image (2  $\mu\text{m}$  x 2  $\mu\text{m}$ ) of fused silica surface



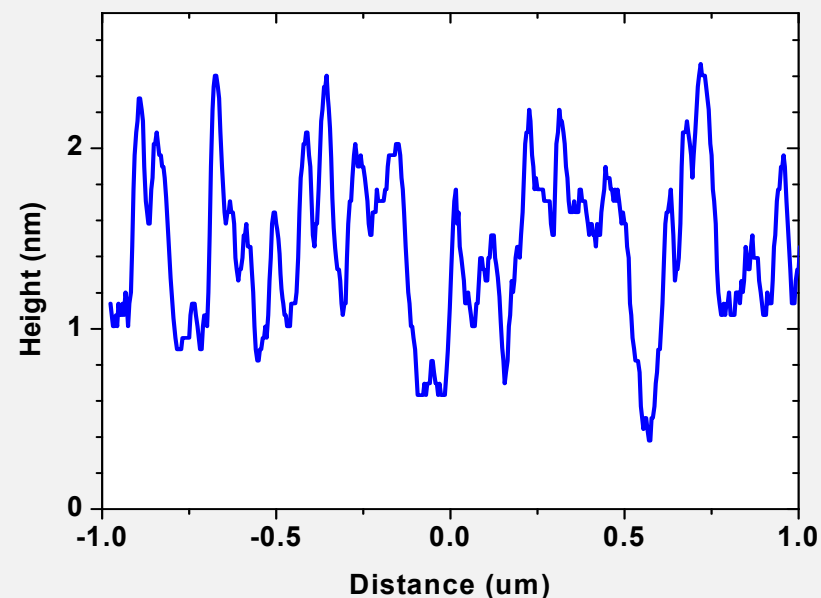
Sample 4: using Stabilized Hastilite

# Single pass ceria particle sliding experiments suggest 'plastic' - type removal can occur during polishing

AFM Image (2  $\mu\text{m}$  x 2  $\mu\text{m}$ ) of fused silica surface



Lineout of AFM Perp. to slide particle slide direction



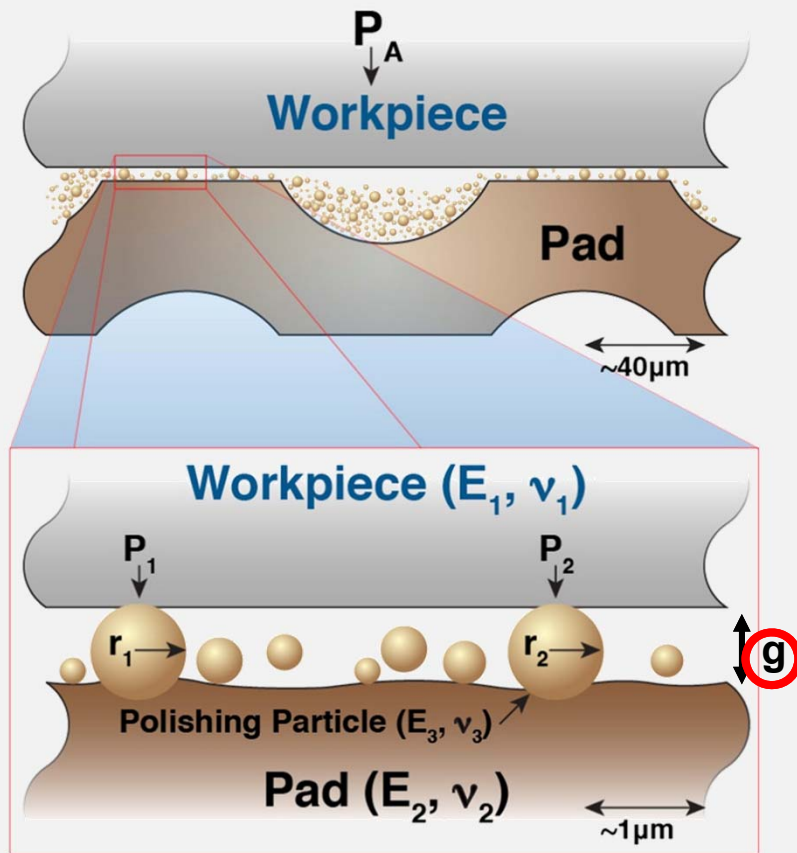
- Single pass of ceria particle removes  $\sim 1$  nm of material ( $\sim 7$  Si-O units)

Sample 4: using Stabilized Hastilite



# Ensemble Hertzian Gap (EHG) model is used to determine the gap, fraction of particles loaded, & the load per particle

## EHG Model Setup



Suratwala et. al., *J. Am. Cer. Soc.* 97(1) 2014

## Governing Relationships

### Load Balance

$$P_A = N_b 2\pi r_o^2 \int_2^\infty F(r) P(r, g) dr$$

### Number density of particles in gap

$$N_b = f_A N_p = f_A \frac{\int F(r) dr}{\int F(r) 2\pi r dr}$$

### Load on each particle (Hertzian Contact)

$$P(r, g) = \frac{4}{3} E_{eff} \sqrt{r(2r - g)^3}$$

$g$  = gap at interface

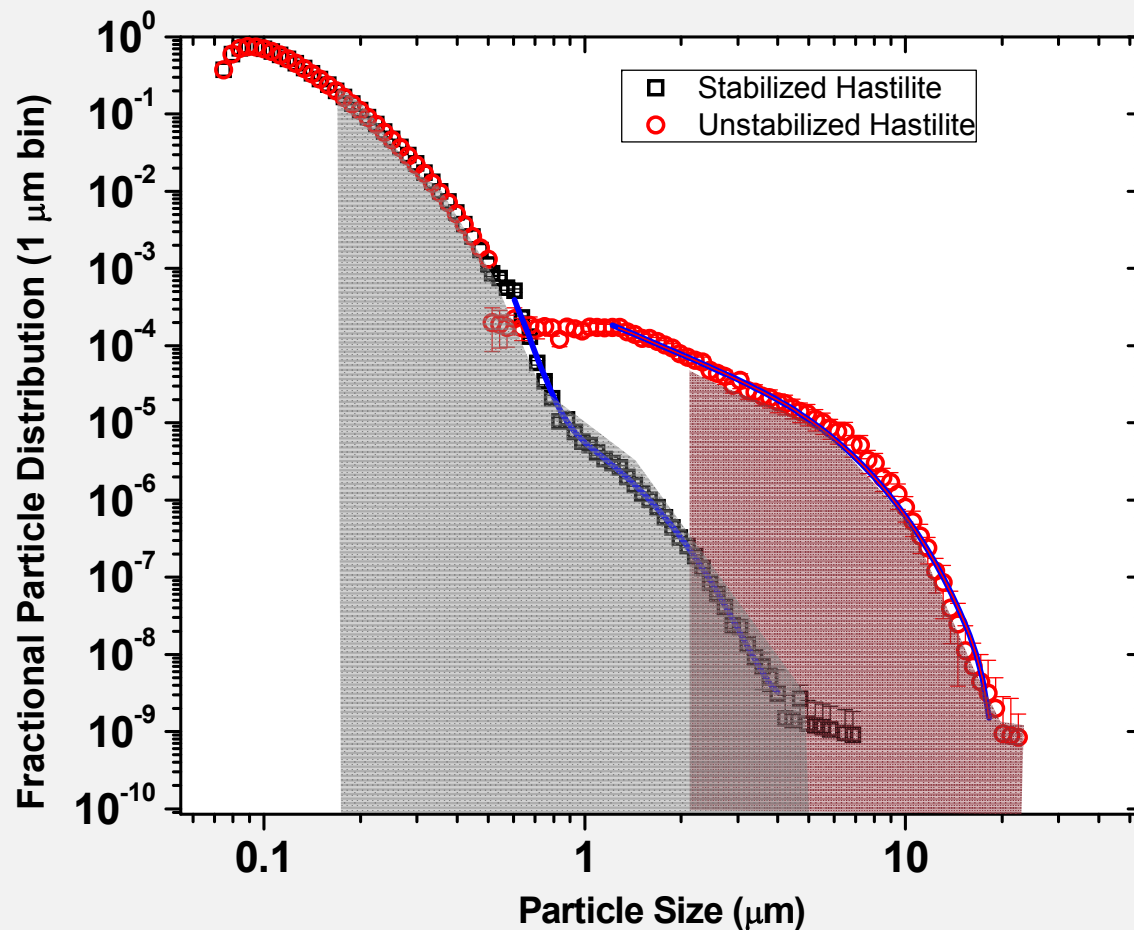
$f_A$  = fraction of pad area making contact with workpiece

$N_p$  = # of particles/area

In this formalism, only need to solve for  $g$

# Using the EHG model, the calculated fraction of “active” particles is very small

Full PSD for stabilized and unstabilized Hastilite Polishing Slurry

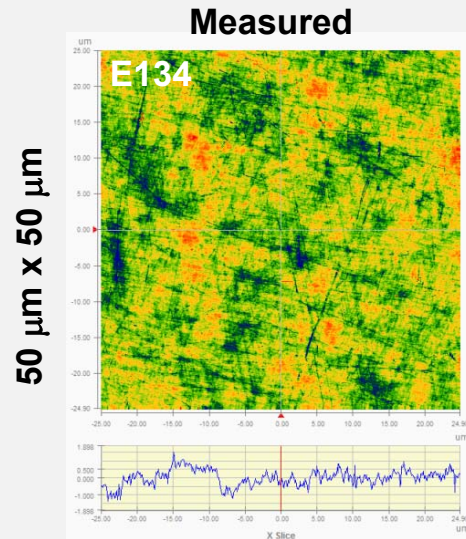


- Shaded region represents active (i.e., loaded) particles (using  $f_A=1.5 \times 10^{-4}$ )
- Stabilized Hastilite uses much smaller particles during polishing compared to Unstabilized Hastilite

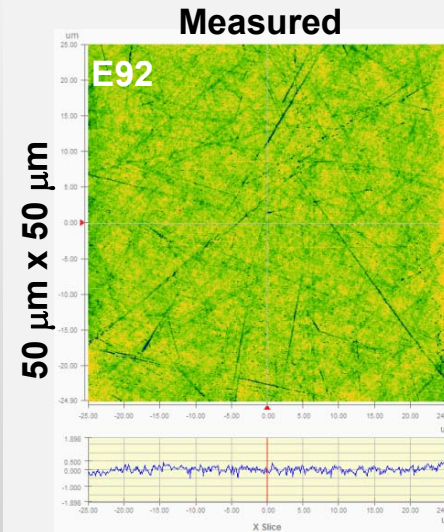
Slurry	Gap	Fraction of active particles
Stabilized Hastilite	0.07 μm	0.224
Unstabilized Hastilite	0.42 μm	0.0005

# Using the EHG model, polished surfaces using different PSDs have been simulated over multiple spatial scale lengths

## Unstabilized Hastilite PO Polished Surface

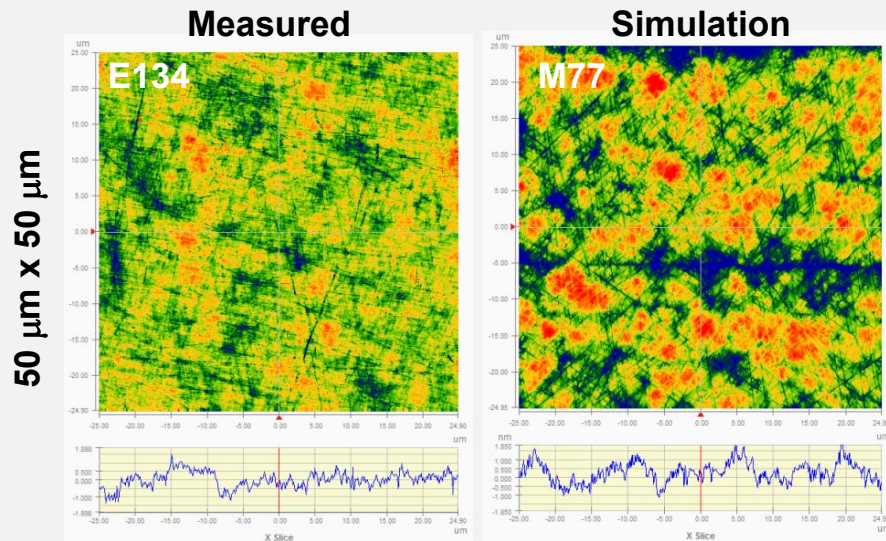


## Stabilized Hastilite PO Polished Surface

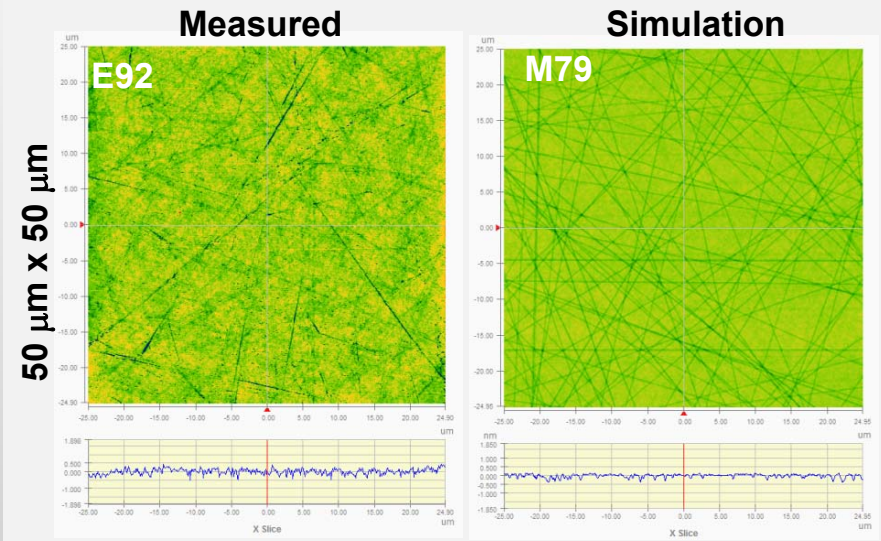


# Using the EHG model, polished surfaces using different PSDs have been simulated over multiple spatial scale lengths

## Unstabilized Hastilite PO Polished Surface

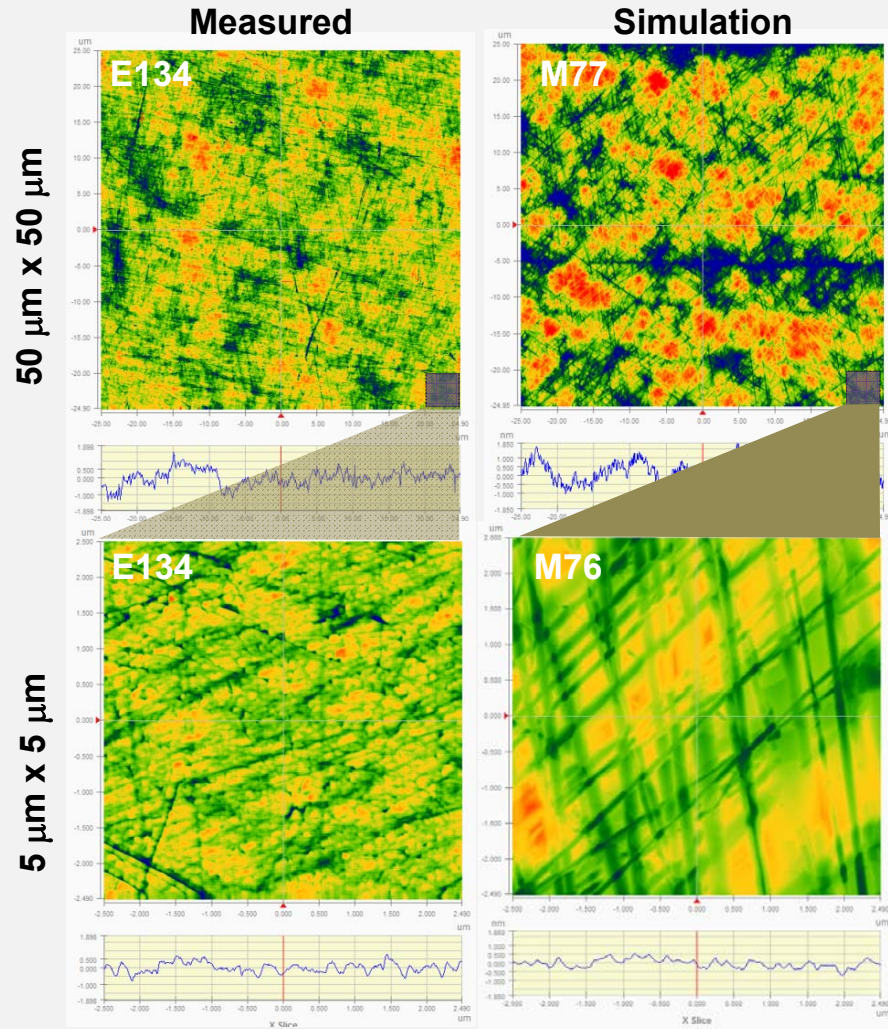


## Stabilized Hastilite PO Polished Surface

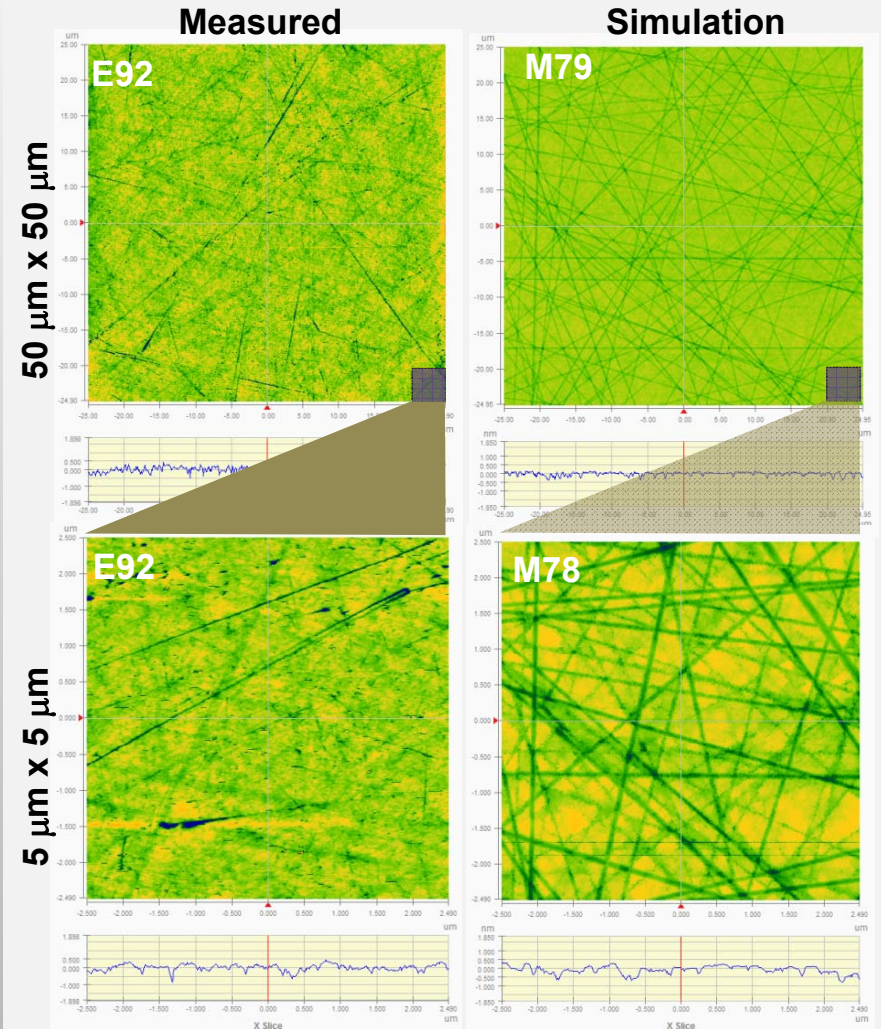


# Using the EHG model, polished surfaces using different PSDs have been simulated over multiple spatial scale lengths

## Unstabilized Hastilite PO Polished Surface



## Stabilized Hastilite PO Polished Surface



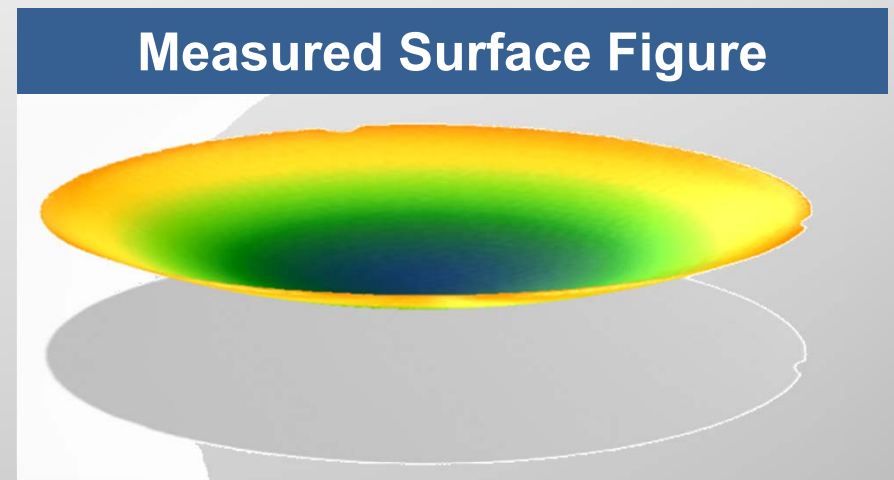
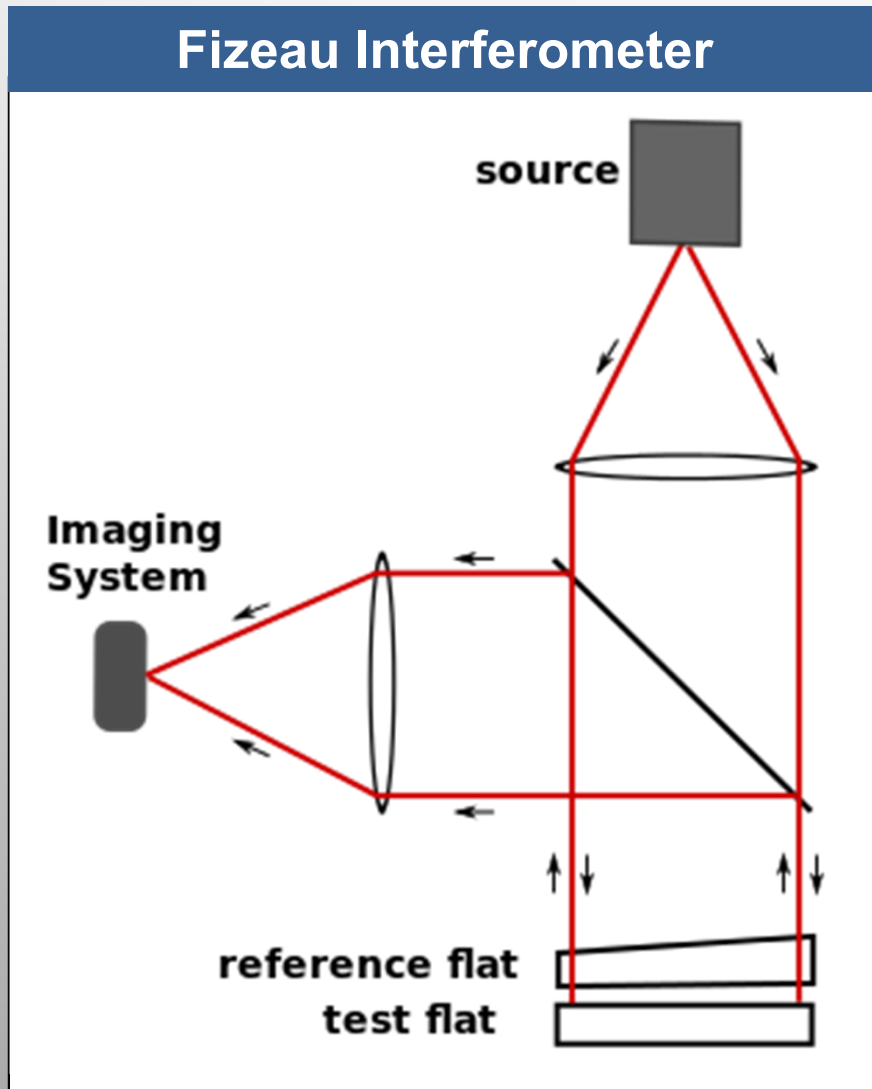
# The materials science behind grinding & polishing

**1. Sub-surface Damage (scratch/dig)**

**2. Roughness**

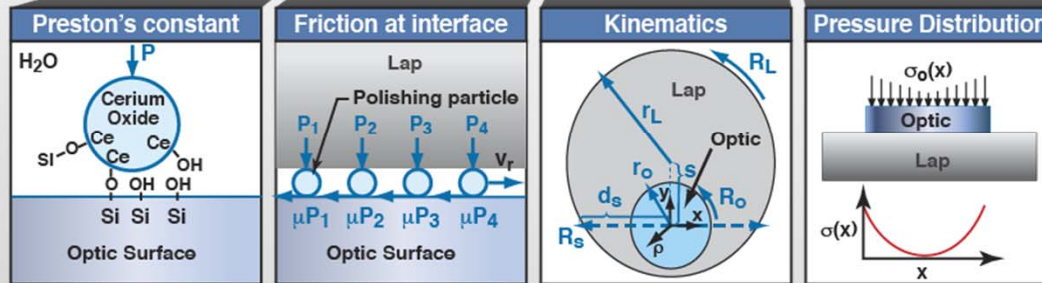
**3. Surface Figure**

# The surface figure of an optic is typically measured by interferometry



# Material removal on a workpiece is governed by a large number of phenomena

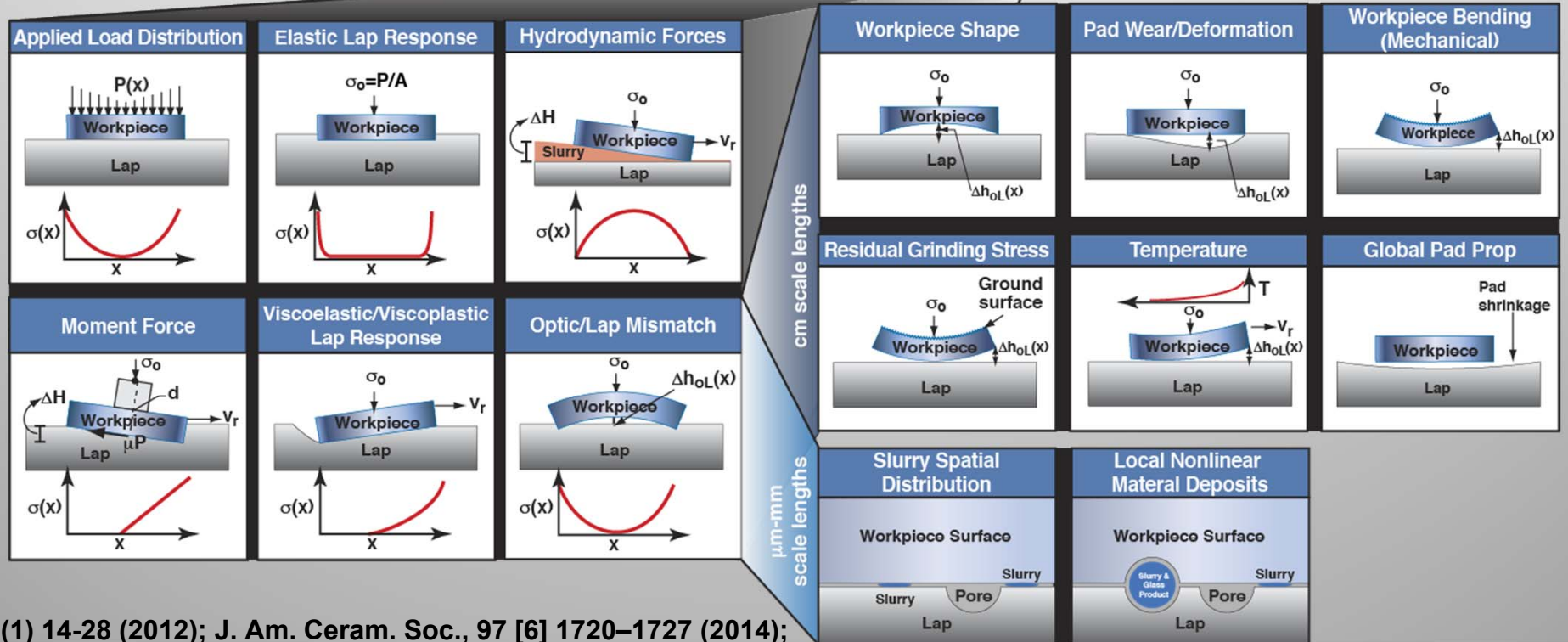
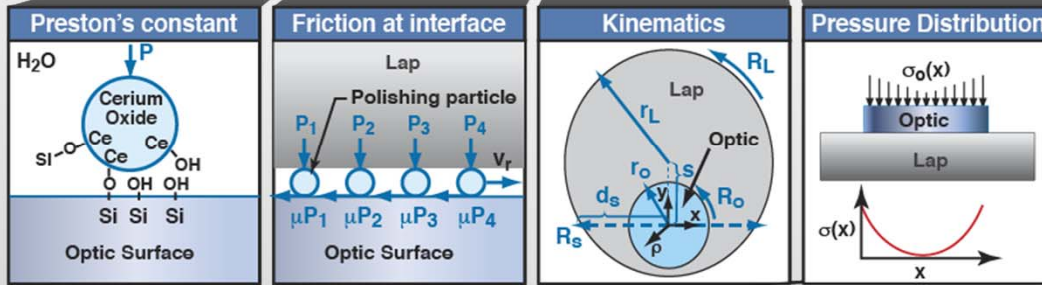
$$\frac{dh}{dt}(x, y, t) = k_p \underbrace{\mu(x, y, t)}_{\text{Friction at interface}} \underbrace{v_r(x, y, t)}_{\text{Kinematics}} \underbrace{\sigma(x, y, z, t)}_{\text{Pressure Distribution}}$$





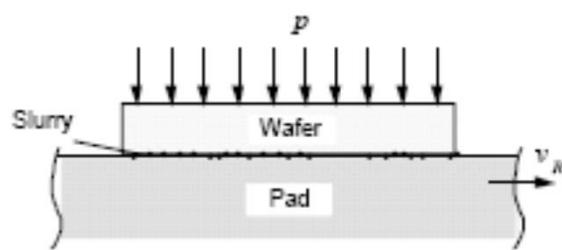
# Material removal on a workpiece is governed by a large number of phenomena

$$\frac{dh}{dt}(x, y, t) = k_p \underbrace{\mu(x, y, t)}_{\text{Friction at interface}} \underbrace{v_r(x, y, t)}_{\text{Kinematics}} \underbrace{\sigma(x, y, z, t)}_{\text{Pressure Distribution}}$$



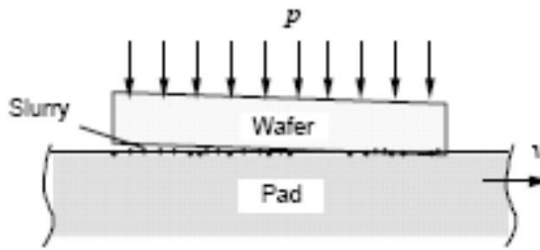
# The optic/lap can have different modes of contact which strongly influences the amount of material removal

## Contact Mode



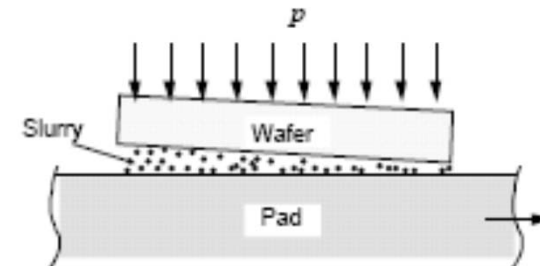
- Friction  $\mu > 0.1$
- Optic/pad mechanically make contact
- High pressure/low velocity
- Real contact area < nominal contact area
- Plastic deformation of optic/pad occurs
- Fluid film is discontinuous

## Mixed Mode

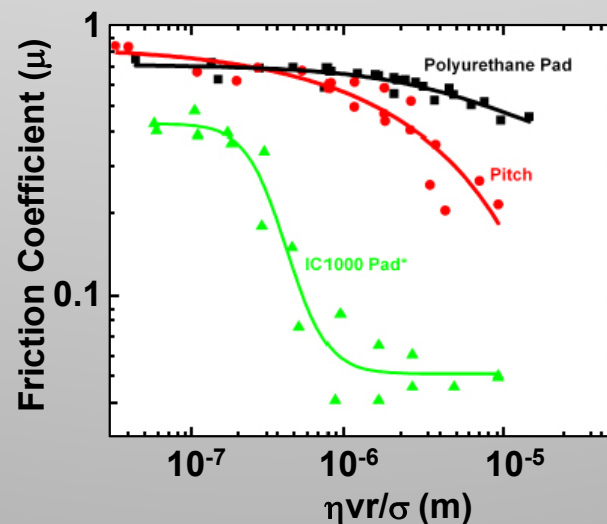


- Friction  $\mu \sim 0.01$  to  $0.1$
- Transition mode during pressure or velocity changes
- Contact is made between lap asperities and optic

## Hydroplaning Mode

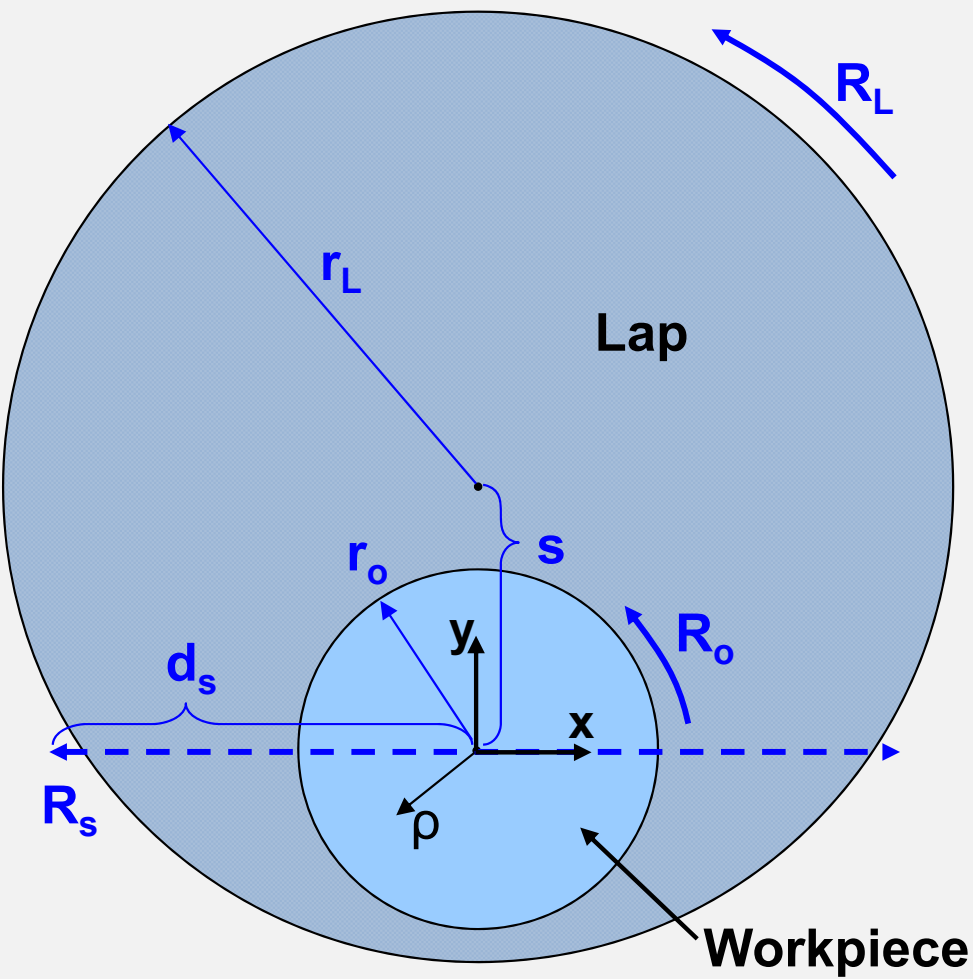


- Friction  $\mu \sim 0.001$  to  $0.01$  (due to shear of viscous fluid)
- Optic glides on fluid film without directly touching pad
- Low pressure/high velocity
- Pressure build-ups in fluid to support normal load of optic
- Pressure gradient is sensitive to wedge angle



# A geometric model is used to estimate the figure during conventional grinding/polishing

## Schematic of geometric model



The velocity vector at each point on the optic is the velocity relative to the optic rotation minus the velocity relative to the lap rotation

$$\vec{V} = (\vec{R}_{optic} \times \vec{\rho}) - (\vec{R}_{Lap} \times (\vec{\rho} - \vec{S})) + \vec{V}_s$$

where the vectors are:

$$\vec{R}_{optic} = \begin{pmatrix} 0 \\ 0 \\ R_{optic} \end{pmatrix}$$

$$\vec{R}_{Lap} = \begin{pmatrix} 0 \\ 0 \\ R_{Lap} \end{pmatrix}$$

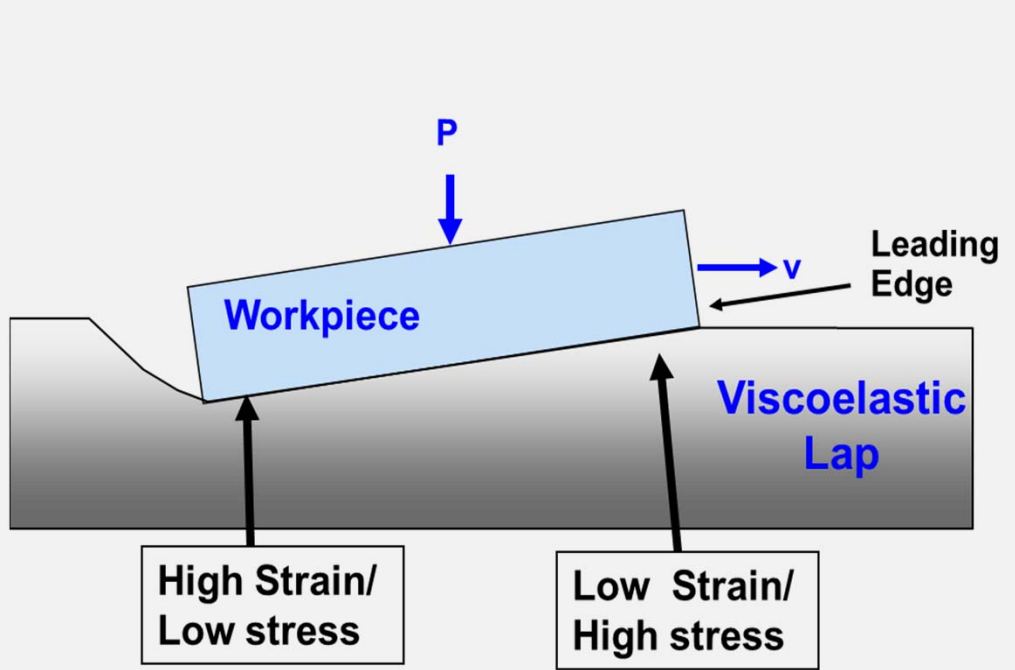
$$\vec{S} = \begin{pmatrix} d_s \sin\left(\frac{\pi v_s t}{d_s}\right) \\ s \\ 0 \end{pmatrix}$$

$$\vec{V}_s = \begin{pmatrix} v_s \cos\left(\frac{\pi v_s t}{2 d_s}\right) \\ 0 \\ 0 \end{pmatrix}$$

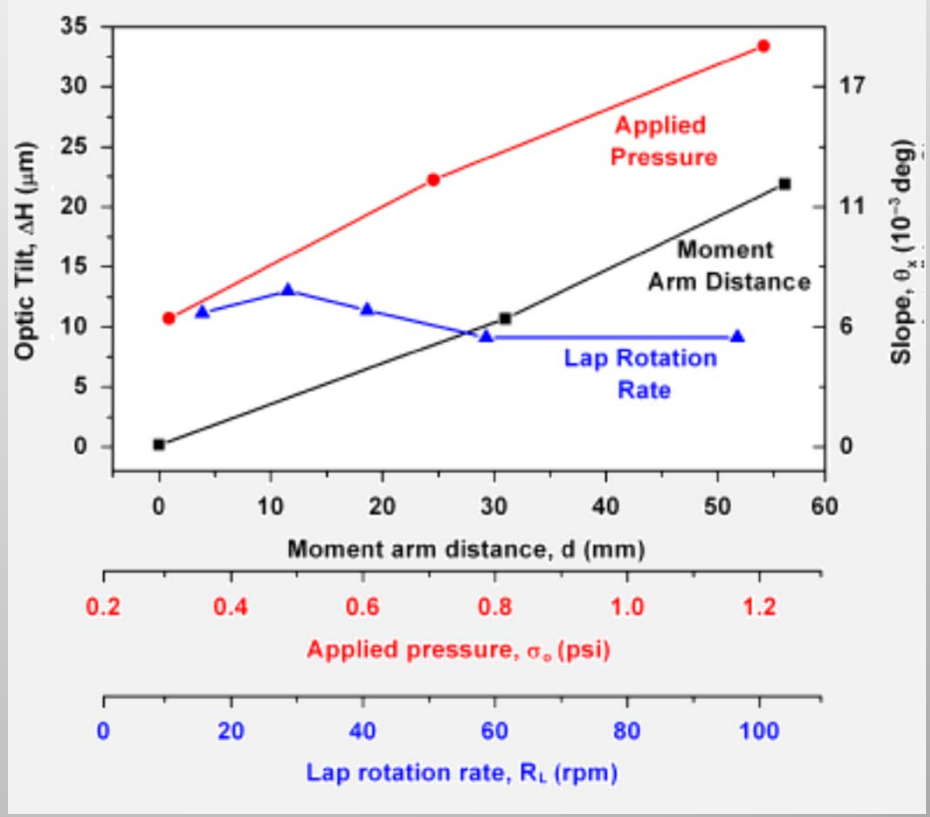
$$\vec{\rho} = \begin{pmatrix} \sqrt{x^2 + y^2} \sin(a \tan(x/y) + 2\pi R_{optic} t) \\ \sqrt{x^2 + y^2} \cos(a \tan(x/y) + 2\pi R_{optic} t) \\ 0 \end{pmatrix}$$

# For a translating workpiece on a viscoelastic lap, stress is highest at leading edge and lowest at end

## Schematic of moving workpiece on a viscoelastic lap



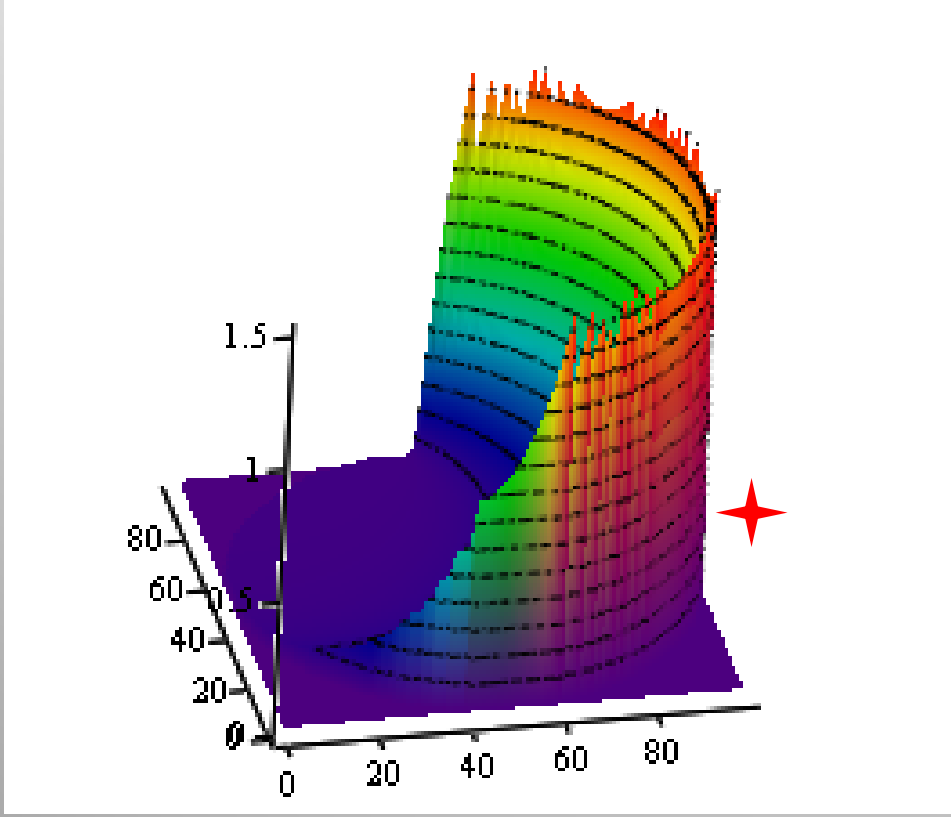
## Effect of moment on workpiece tilt



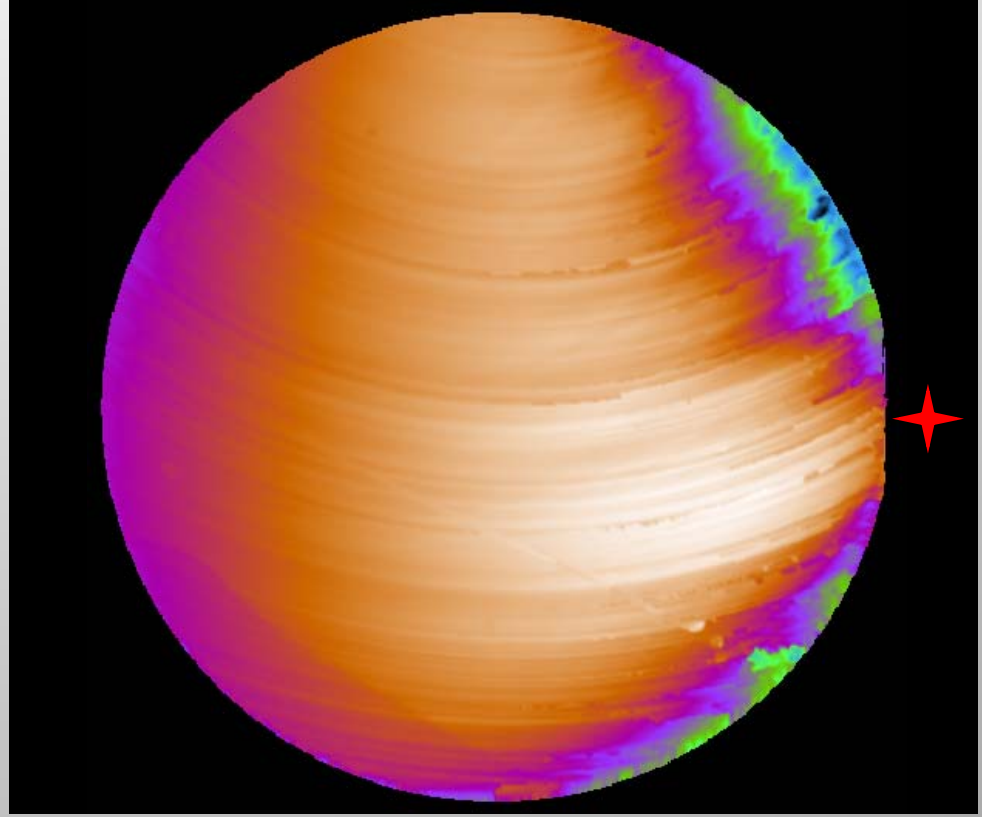
# Calculated instantaneous stress distribution is qualitatively similar to measured data

★ Leading edge

Calculated instantaneous Stress profile



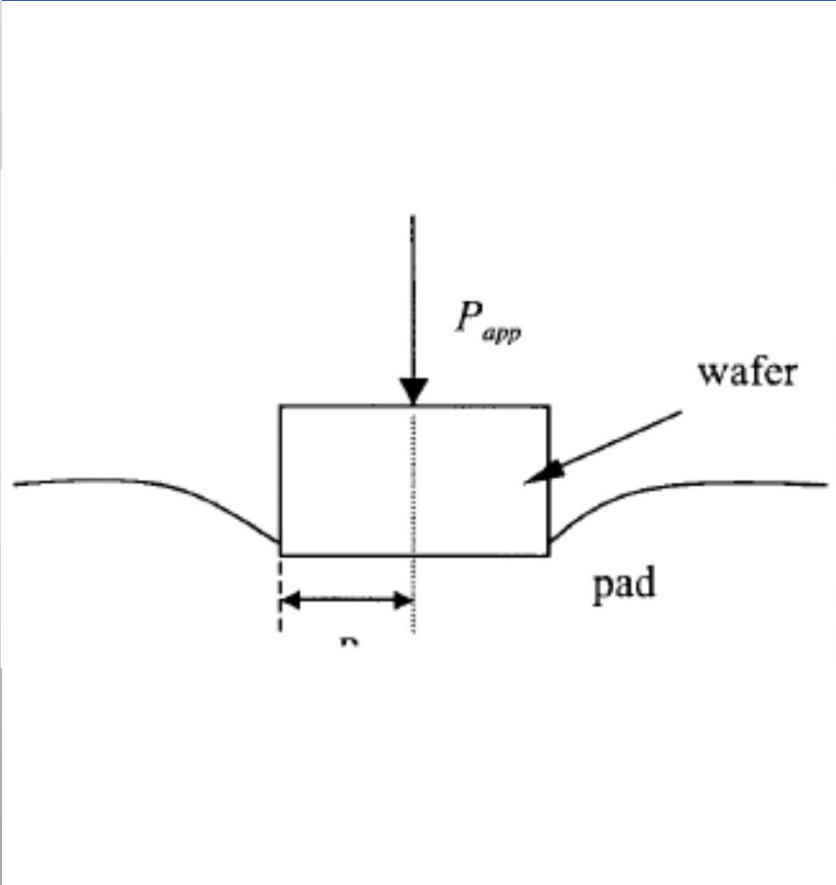
Measured removal on optic when it is not rotated (Exp B)



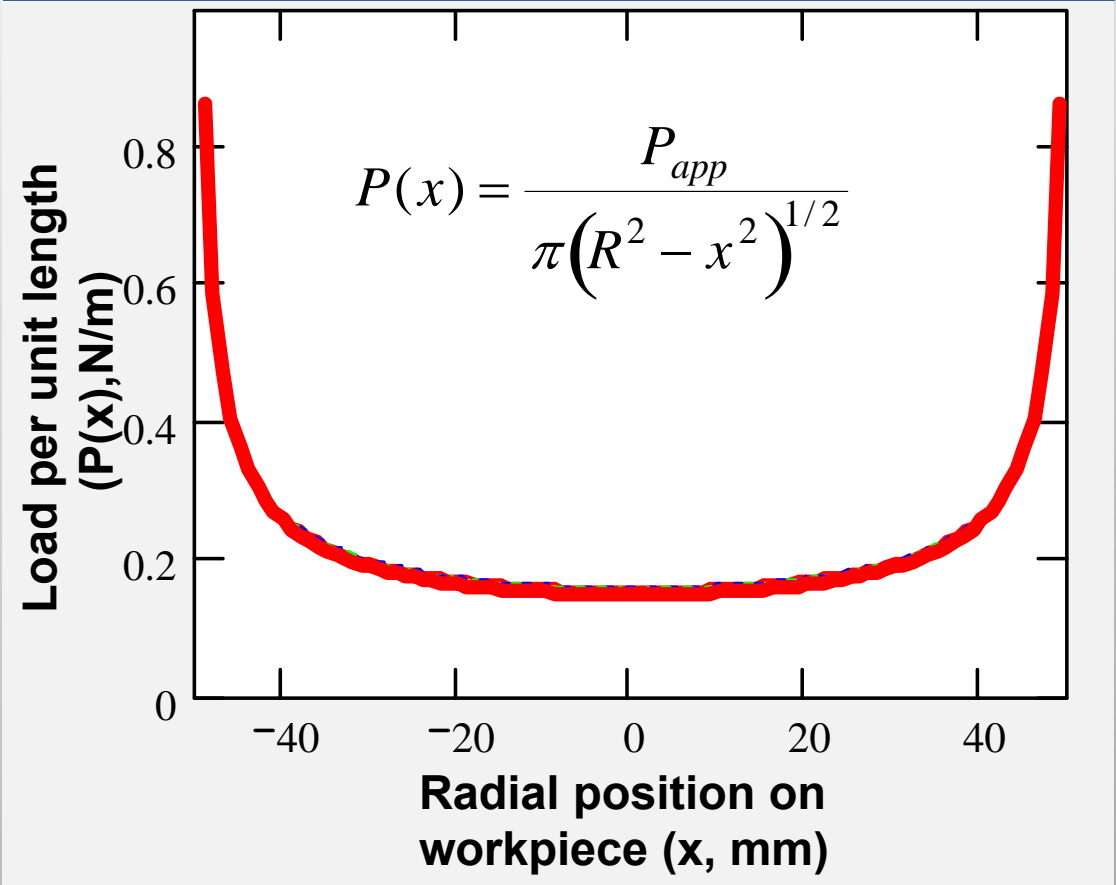
High removal was observed at leading edge consistent with viscoelastic mechanism for causing pressure distribution

The pressure distribution across the workpiece can be predicted using the rigid punch indentation model for contact mode

Rigid Flat Punch Model

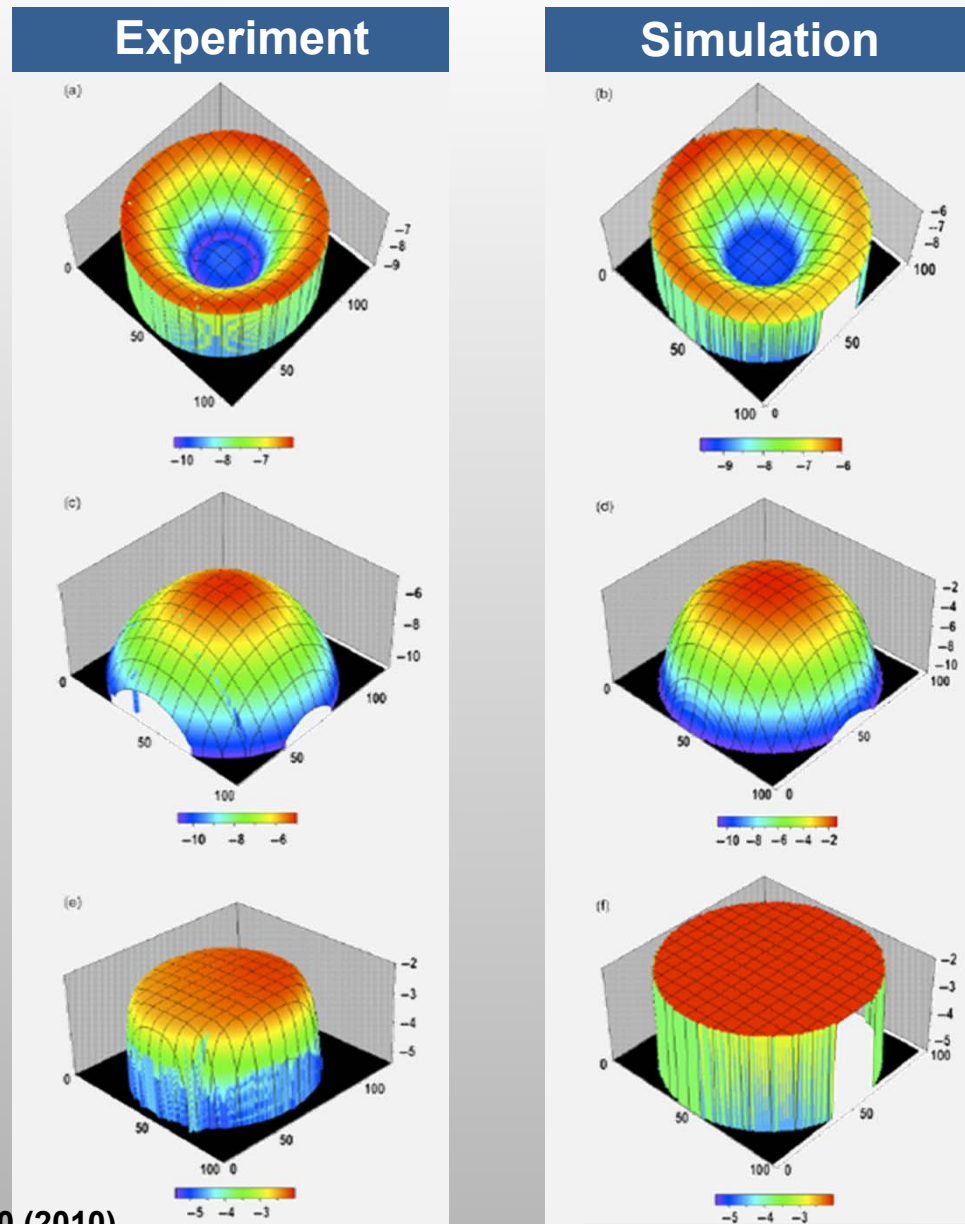


Calculated pressure/load distribution



$P_{app} = 25 \text{ N}; f = 0.1; \nu = 0.1$

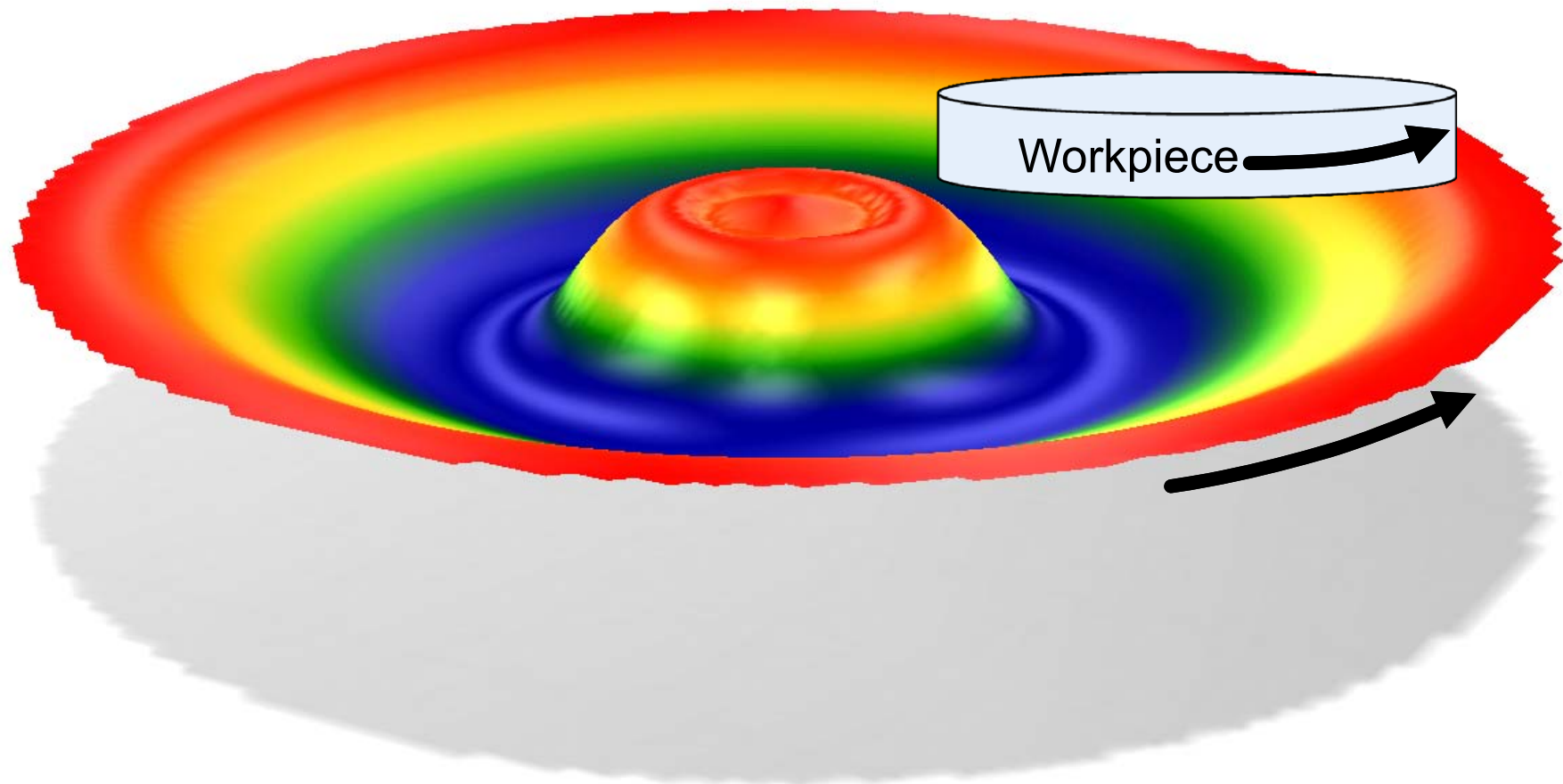
# Our code SurF incorporates these phenomena & does a good job at predicting surface



J. Am. Ceram. Soc., 93 [5] 1326–1340 (2010)

# Workpiece polishing can cause non-uniform wear of the lap

Shape of lap after polishing workpiece

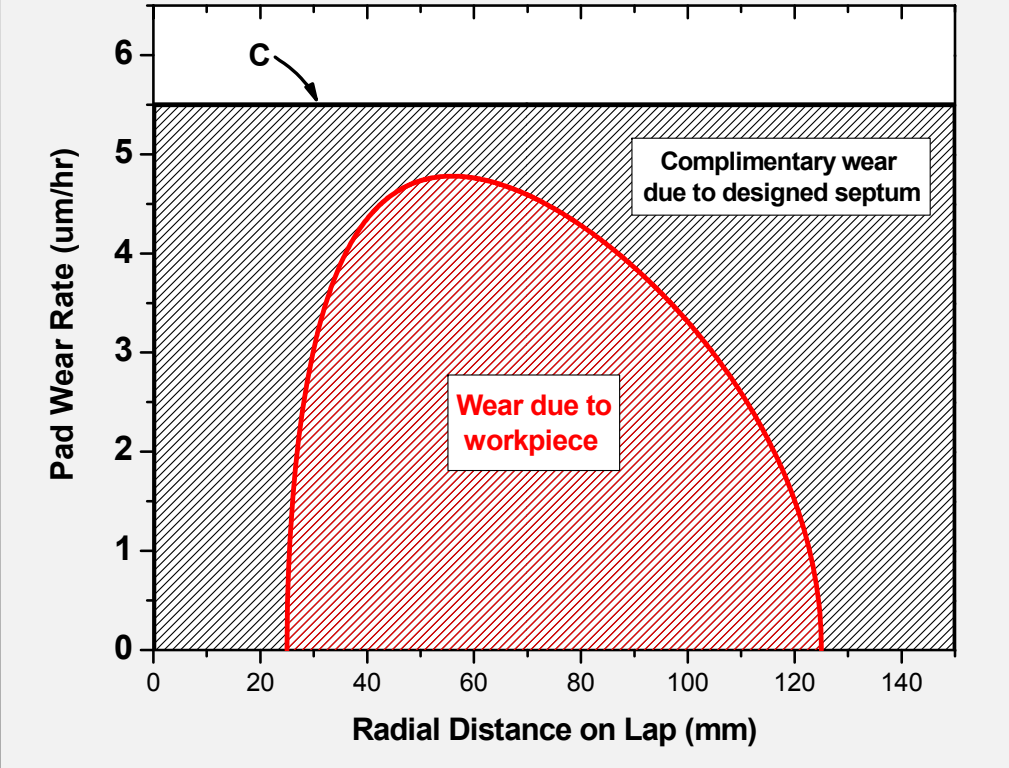


T. Suratwala et. al., IJAGS 3(1) 14-28 (2012).

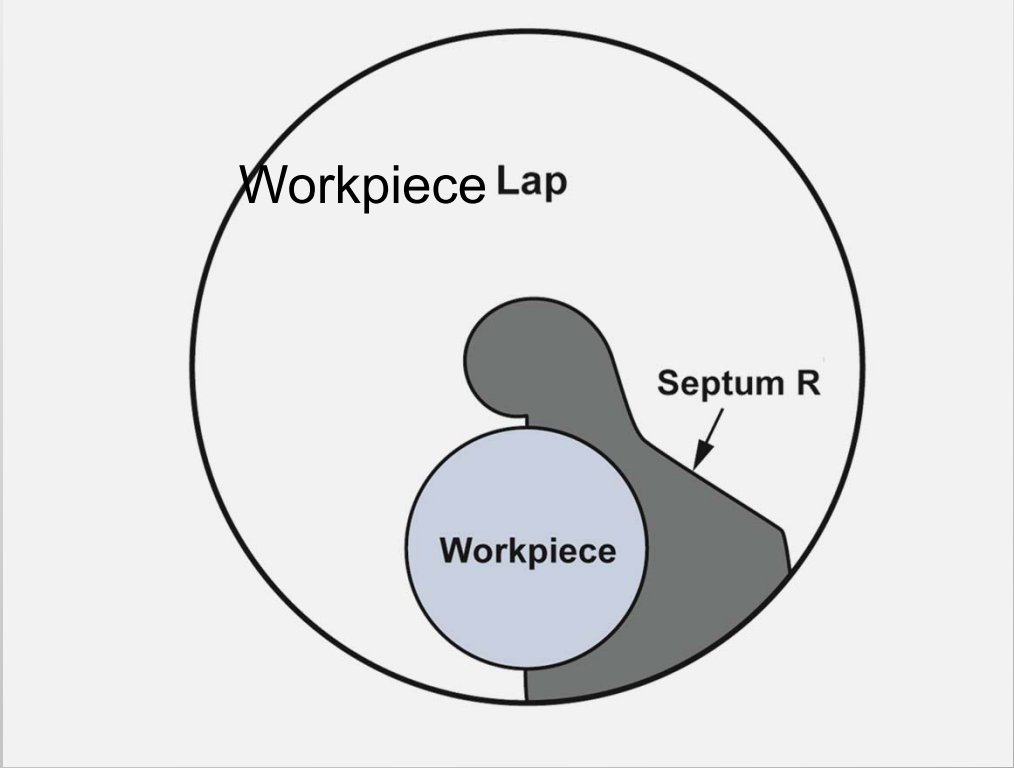


# A novel septum has been designed to counteract non-uniform wear on the pad

Pad wear vs lap radius due to workpiece and engineered septum



Determined shape of Septum



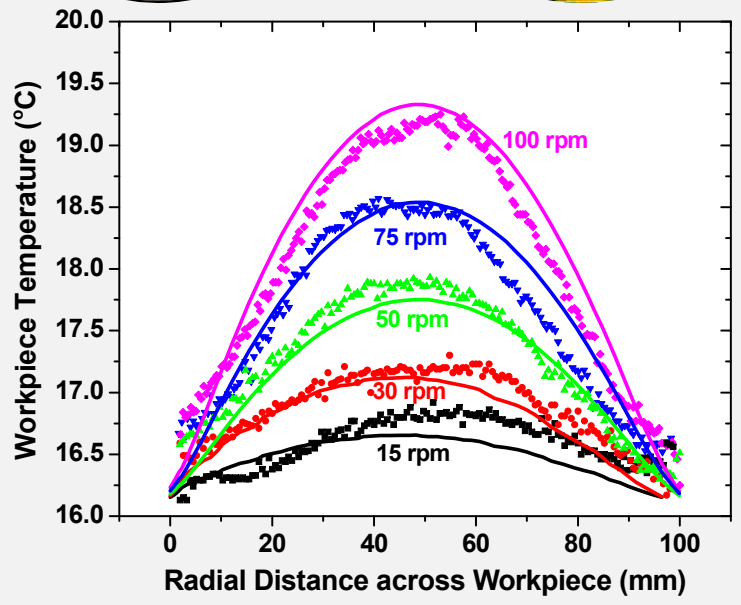
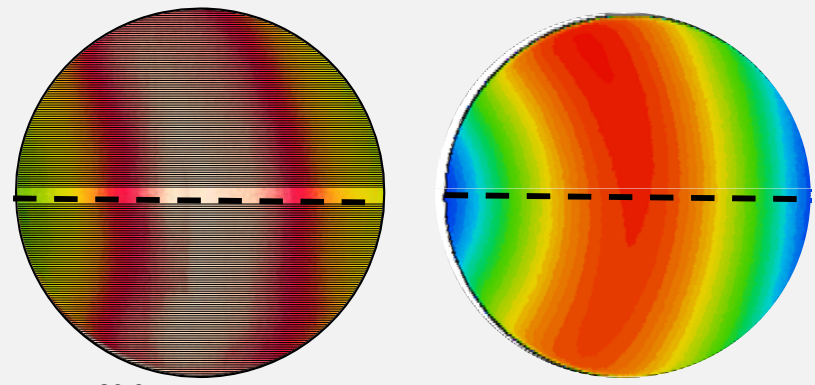
T. Suratwala et. al., IJAGS 3(1) 14-28 (2012).

# Temperature variations across workpiece can be minimized using rotated workpiece and septum

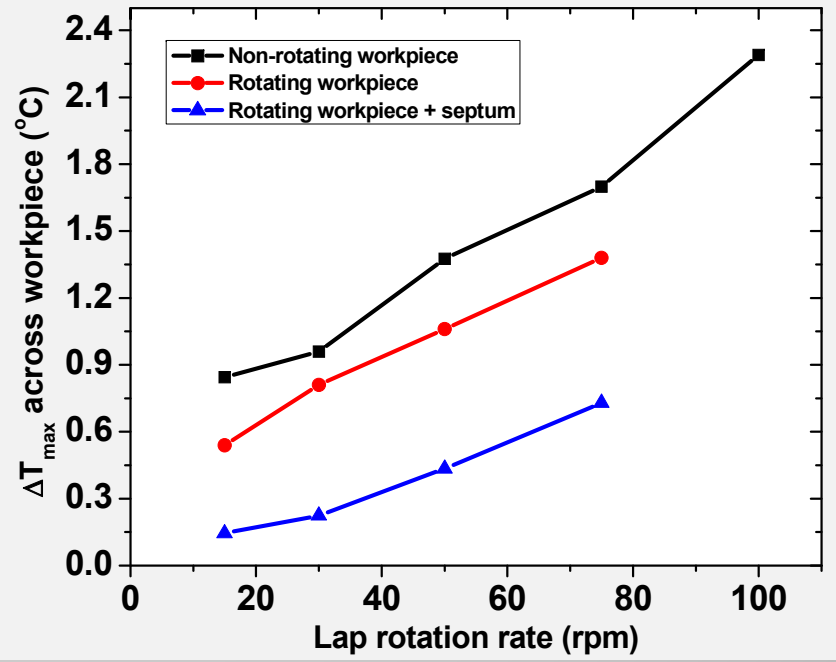
## Temperature on non-rotated workpiece

Experiment

Simulation



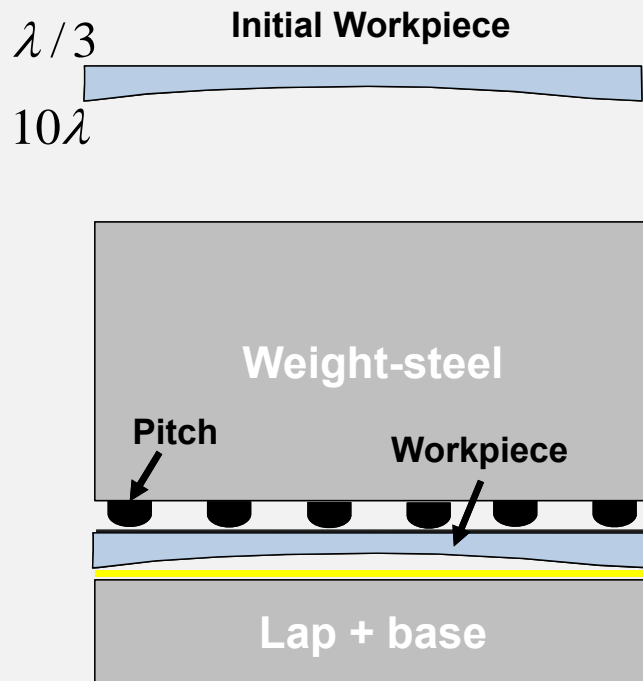
## Temperature variations vs polishing configuration



T. Suratwala et al JACS 97(6) (2014) 1720.

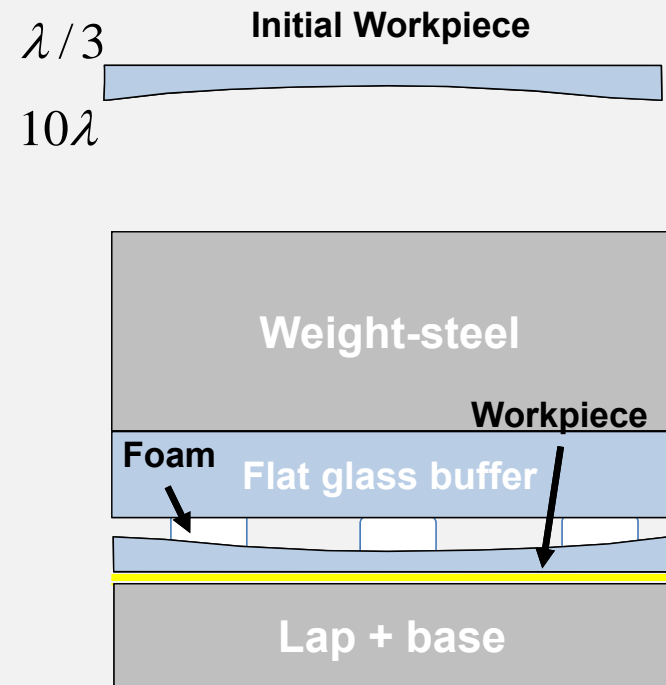
# Pitch (Stiff) Button Blocking (PBB) and Foam (Compliant) Button Blocking (FBB) allows different workpiece response during polishing for High AR workpieces

## Pitch Button Blocking (PBB)



- Workpiece does **not conform** to lap upon loading
- Allows for surface figure to match lap figure

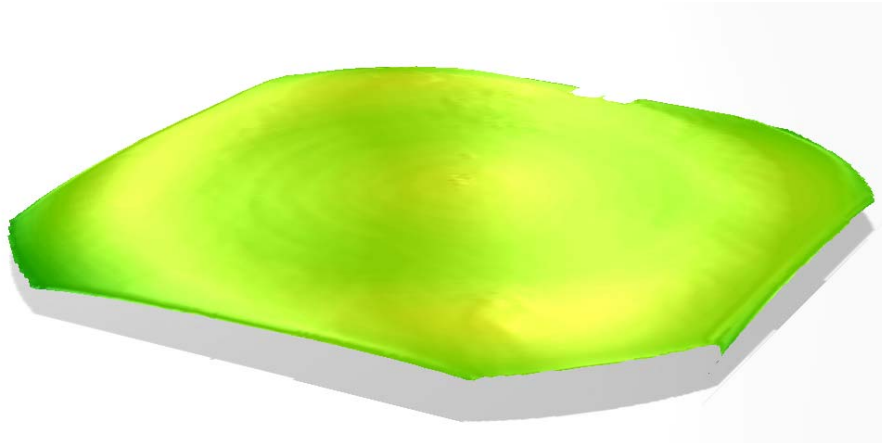
## Foam Button Blocking (FBB)



- Workpiece **conforms** to lap deform upon loading
- Allows for uniform removal on workpiece

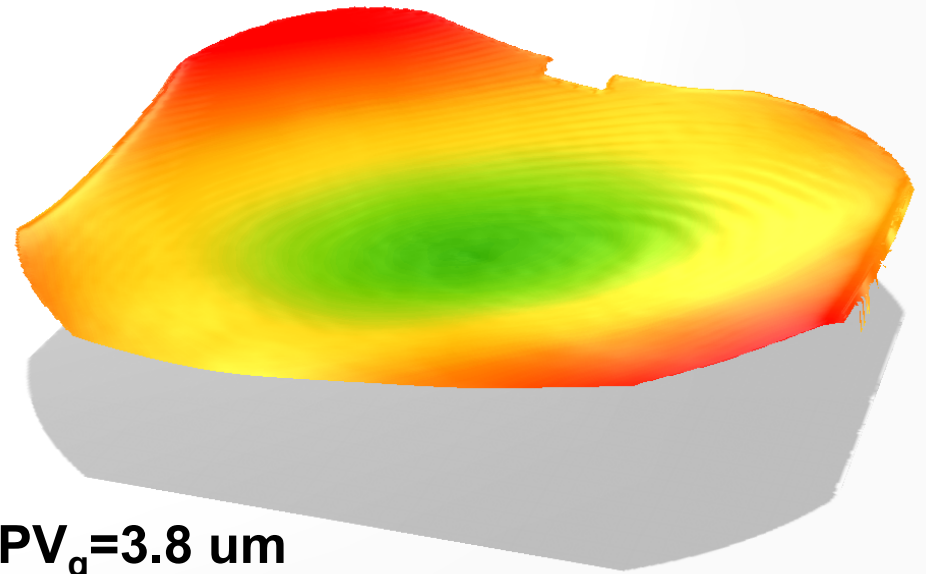
# Without stiff blocking, thin workpiece deflects during polishing

Thick Workpiece (26 x 26 x 4 cm<sup>3</sup>)  
FBB (Exp 1034)



$PV_q = 0.42 \text{ um}$

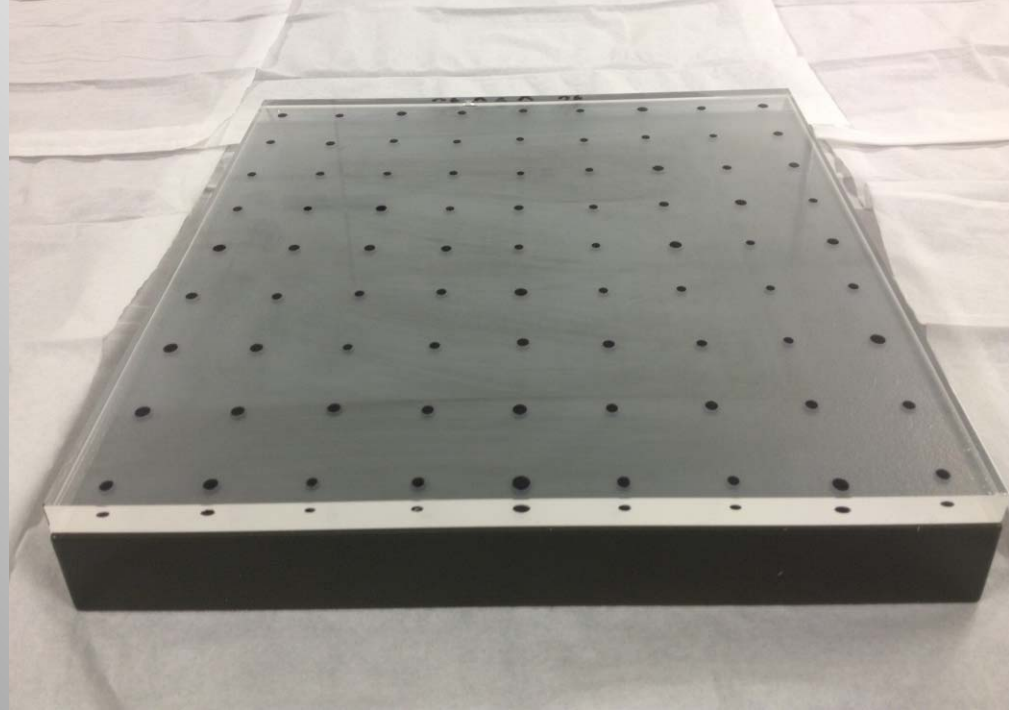
Thin Workpiece (26 x 26 x 0.8 cm<sup>3</sup>)  
FBB (E1019)



$PV_q = 3.8 \text{ um}$

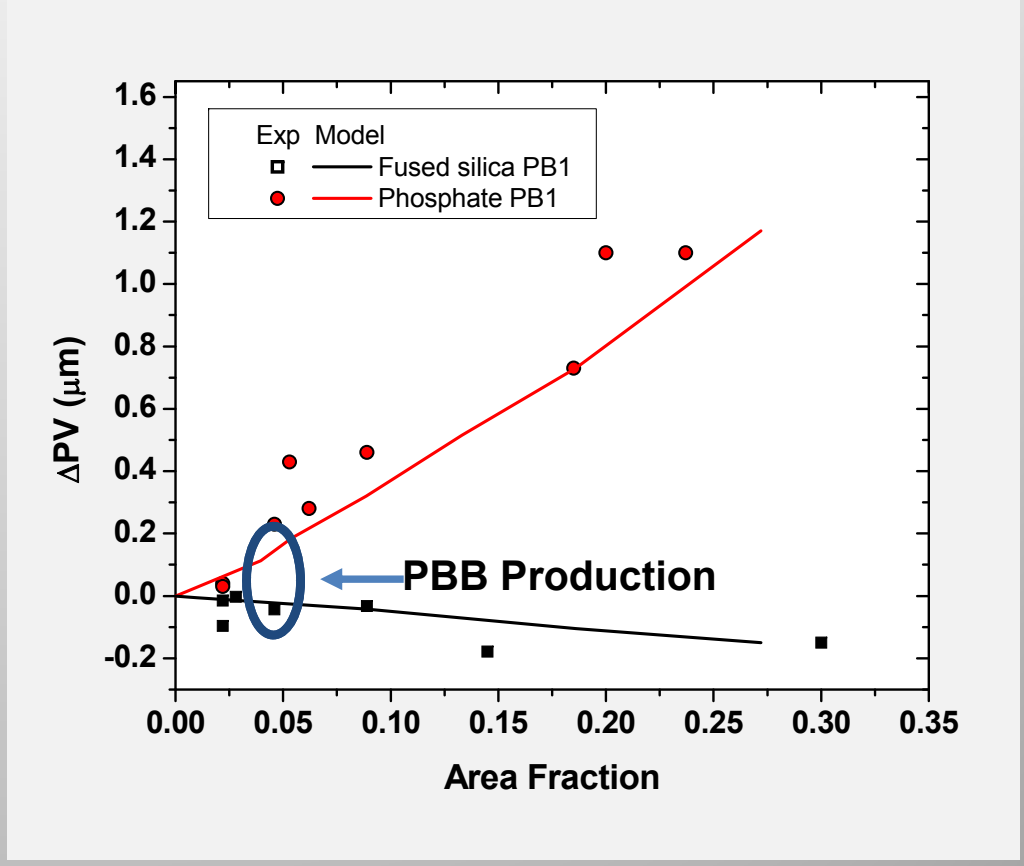
# Pitch button blocking (PBB) technique prevents workpiece from bending during polishing

265 mm (side) x 8 mm (thick)  
Fused Silica PBB



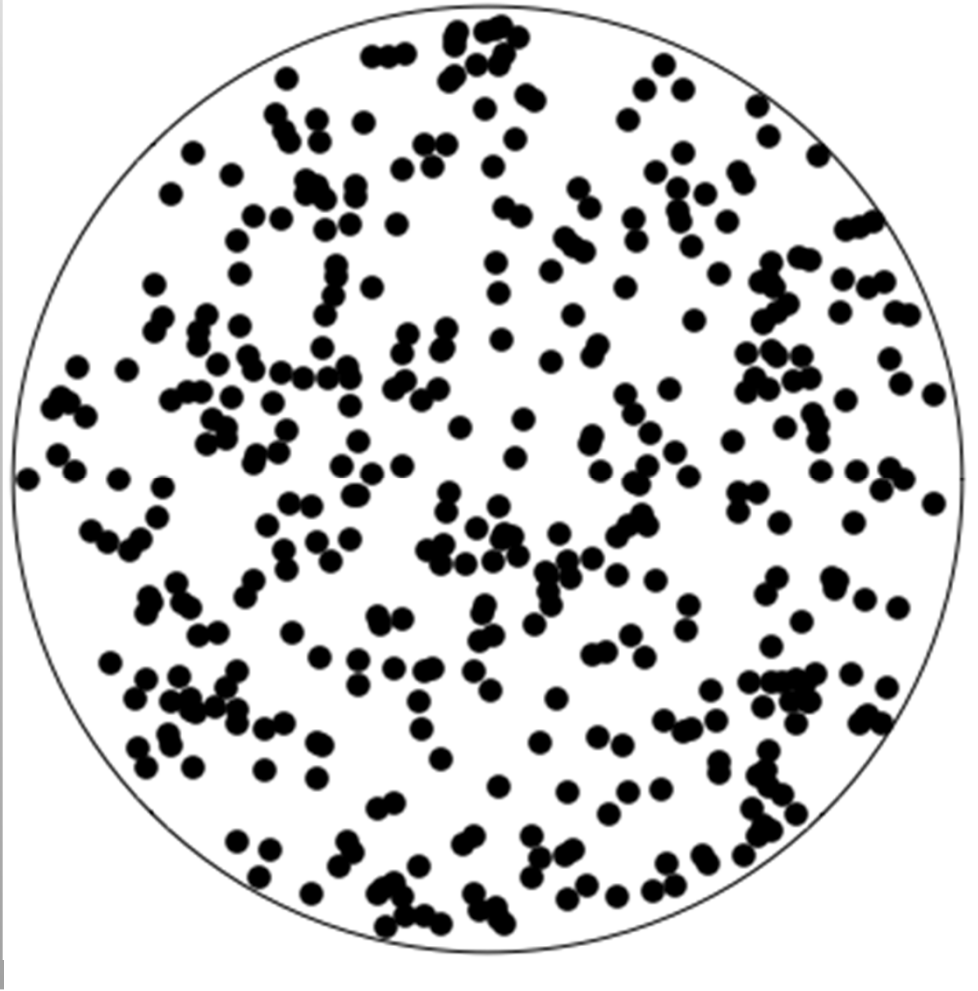
FS	$\Delta PV = 0.003 \mu m$
Phosphate	$\Delta PV = 0.035 \mu m$

Model vs Experiment:  
 $\Delta PV$  as fn of pitch button area fraction

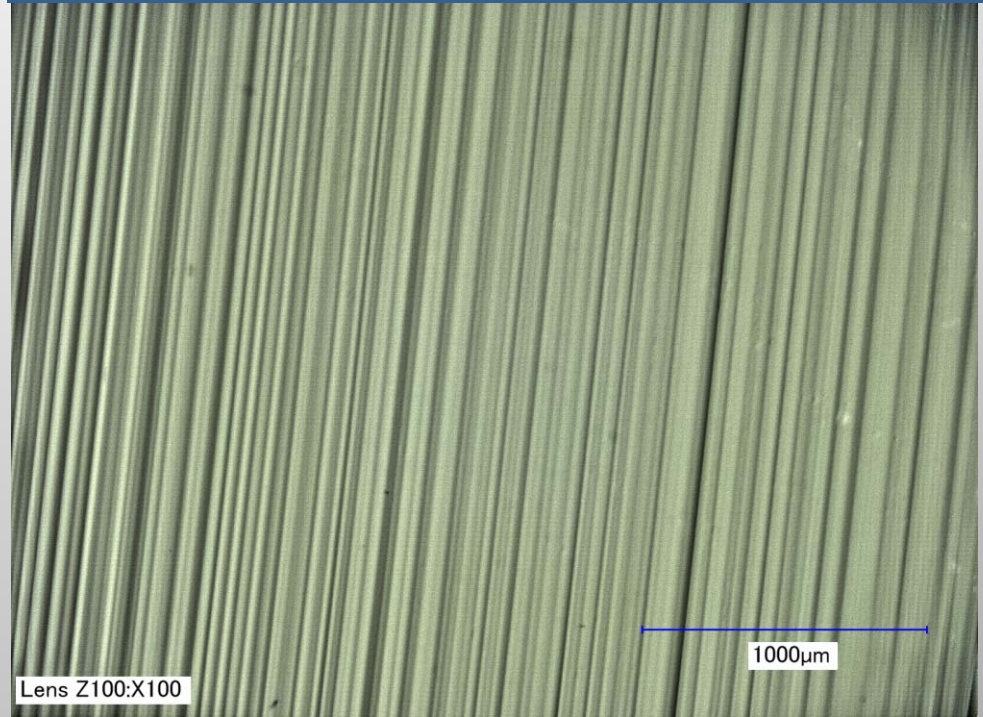


# Fine scale radial material non-uniformity is caused by local islands of slurry on the pad

Schematic representation of islands of slurry on pad

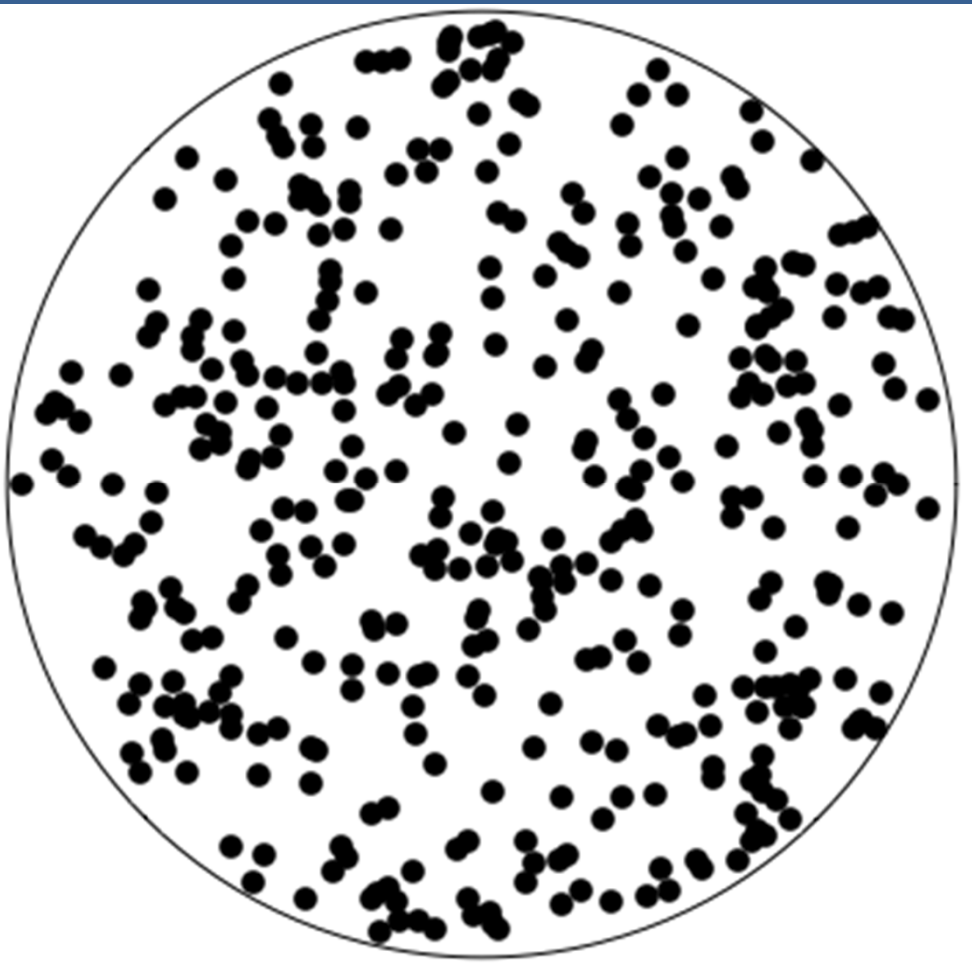


Optical micrograph of grooves observed on non-rotated workpiece

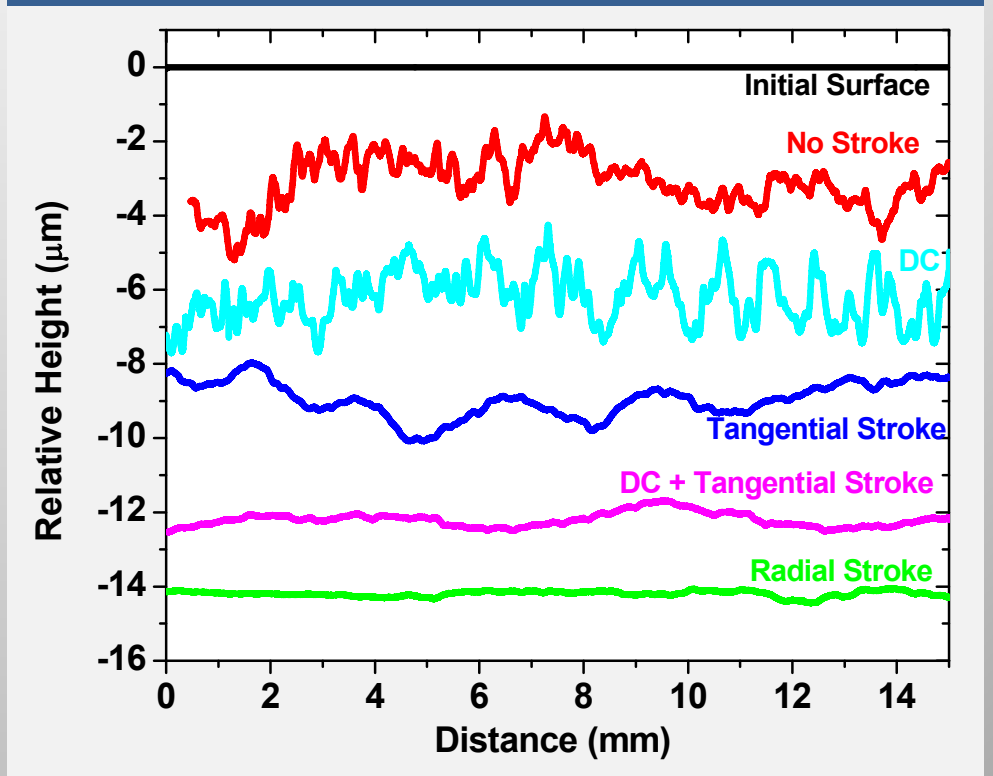


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Schematic representation of islands of slurry on pad



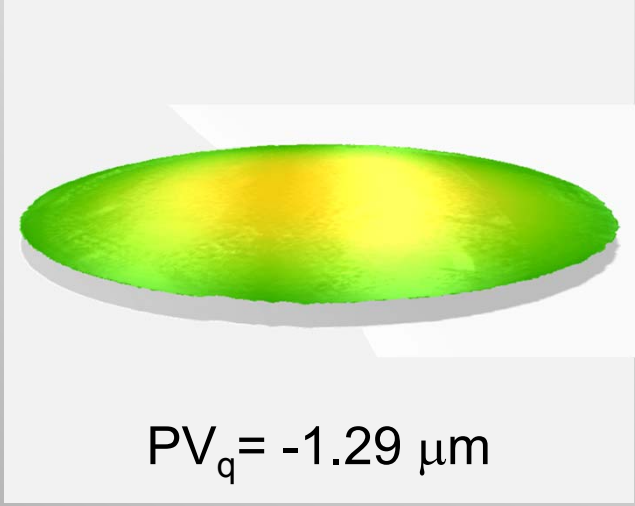
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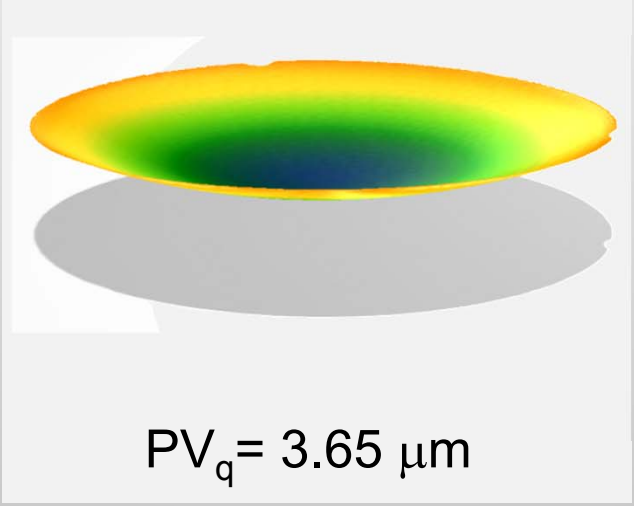
**Radial stroke motion dramatically reduces this non-uniformity**

# Residual grinding stress causes a high aspect ratio workpiece to bend

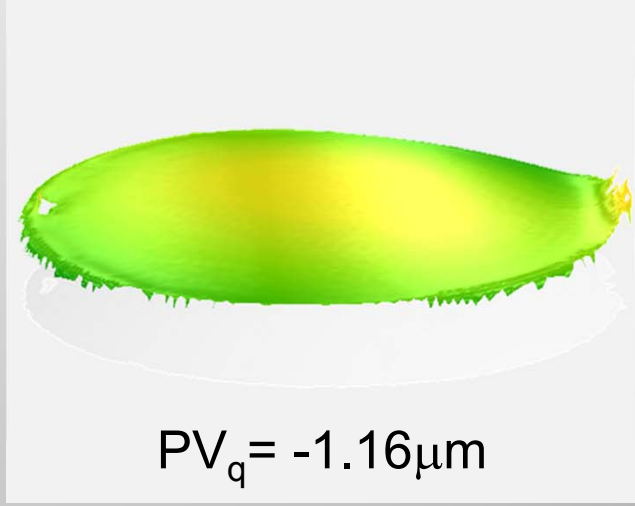
Surface Figure of S2  
(Initial)



Surface Figure of S2  
(After Grinding S1)



Surface Figure of S2  
(After Grinding/Etching\*)

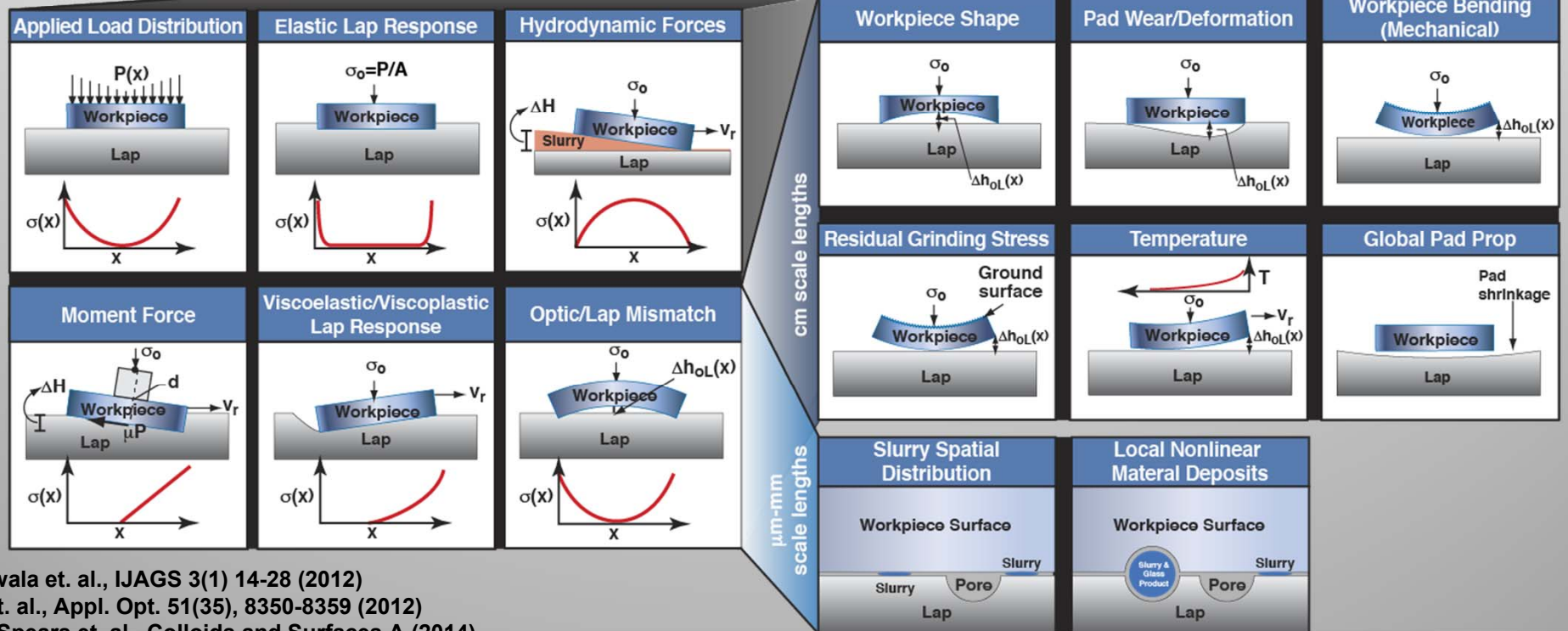
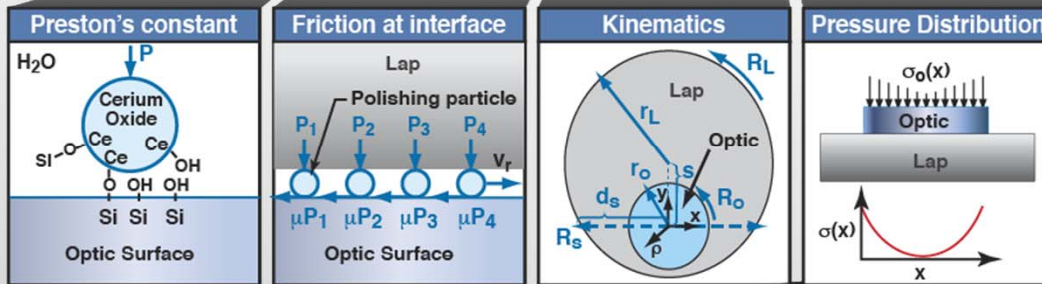


Chemical etching can effectively remove the residual stress and any complications to workpiece-lap mismatch



# Material removal on a workpiece is governed by a large number of phenomena

$$\frac{dh}{dt}(x, y, t) = k_p \underbrace{\mu(x, y, t)}_{\text{Friction at interface}} \underbrace{v_r(x, y, t)}_{\text{Kinematics}} \underbrace{s(x, y, z, t)}_{\text{Pressure Distribution}}$$



T. Suratwala et. al., IJAGS 3(1) 14-28 (2012)  
 M. Feit et. al., Appl. Opt. 51(35), 8350-8359 (2012)  
 R. Dylla-Spears et. al., Colloids and Surfaces A (2014)

# The materials science behind grinding & polishing

- 1. Sub-surface Damage (scratch/dig)**
- 2. Roughness**
- 3. Surface Figure**



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National Laboratory**